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**LOW-ENERGY ELECTRON DRIVEN REACTIONS IN LAYERED  
METHANOL/AMORPHOUS SOLID WATER FILMS**

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by

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## **Dedication**

To Jesse

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**LOW-ENERGY ELECTRON DRIVEN REACTIONS IN LAYERED  
METHANOL/AMORPHOUS SOLID WATER FILMS**

Minta Carol Akin, Ph. D.

The University of Texas at Austin, 2008

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Understanding the radiolysis of impure water and resulting reactions is crucial to many fields. Reactions driven by low energy electrons (LEE) are of special interest, as high-energy radiation generates large quantities of these electrons, which then provide the energy for most subsequent reactions. Interfacially located reactions are also of particular interest, both as models for heterogeneously distributed reactions occurring during radiolysis, and in their own right, as radiation-driven reactions at interfaces are responsible for key processes such as corrosion and DNA damage. To study LEE-driven reactions at interfaces, thin-layered films of amorphous solid water (ASW) and methanol were grown under ultra-high vacuum conditions using molecular beam techniques. The

films were exposed to a beam of low-energy (100eV or less) electrons, and studied using electron-stimulated desorption (ESD) and temperature programmed desorption (TPD).

ESD studies indicated that methanol moves through a water film during deposition at 80 K but not at 50 K. This transport was not seen during thermal annealing, but radiation-induced mixing was observed at all temperatures. Major and minor LEE radiation products of pure methanol films were identified and found to be consistent with previous results. Products of LEE irradiated layered methanol/water films were determined for the first time using ESD and TPD spectra, and found to be limited to H<sub>2</sub>, O, O<sub>2</sub>, CH<sub>2</sub>O, C<sub>2</sub>H<sub>6</sub>, CO, CO<sub>2</sub>, CH<sub>3</sub>OCH<sub>3</sub>, and CH<sub>3</sub>CH<sub>2</sub>OH.

The effect of adding methanol to an ASW film on the production in ASW of H<sub>2</sub> and O<sub>2</sub> was also examined. The interface created by the addition of CH<sub>3</sub>OH to ASW was found to generate H<sub>2</sub> in previously non-reactive regions of the water film by increasing water-water and water-methanol reactions. Radiative mixing of CH<sub>3</sub>OH and ASW enhanced this effect, presumably by increasing the region of disrupted H-bonding in the ASW. In contrast, the addition of CH<sub>3</sub>OH at low coverages suppressed O<sub>2</sub> production in both unprocessed and preprocessed ASW layers. Modeling indicates that methanol scavenging of the O<sub>2</sub> precursor OH and of the reaction-driving electrons is responsible for this reduction in O<sub>2</sub> signal.



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## Chapter 1: Introduction

An understanding of the mechanisms underlying the radiolysis of water is crucial in many fields, including biology, medicine, atmospheric sciences, nuclear reactor design, nuclear waste storage and remediation, clean energy sources, astrochemistry, and astrophysics. The radiolysis of water leads to both ions and radicals, which lead to subsequent reactions. The damage done by radiation and resulting free radicals in cells to macromolecules such as DNA is well known, and is used to sterilize biological work hoods. It is of critical importance in medicine as well, as such damage can be responsible for cellular aging and certain cancers. Further advances in treating these problems and developing new radiation-based therapies will require a thorough understanding not only of the mechanisms of radiolysis in pure water, but dilute aqueous solutions of organic compounds as well. In the upper atmosphere, radiation-driven reactions are extremely common. Photolytically generated radicals often drive such reactions, some of which act to deplete ozone concentrations or form acid rain, and many of which are thought to occur on ice nanoparticles in cirrus clouds.

Inside a water-cooled nuclear reactor, energetic particle bombardment leads to the formation of corrosive  $\text{H}_2\text{O}_2$  and OH radicals that damage the reactor's structure. To reduce the corrosion rate,  $\text{H}_2$  gas is injected into the water to scavenge the  $\text{H}_2\text{O}_2$ , but significantly greater amounts of  $\text{H}_2$  are needed than predicted by theory.<sup>1</sup> In nuclear waste tanks, the opposite problem may arise; decaying radiation generates an excess of  $\text{H}_2$  gas. This additional  $\text{H}_2$  poses an increased risk to the tanks' stability and to any workers attempting to clean up or control the waste. As in biological systems, the presence of

organic compounds in the tanks increases the complexity of the system and likely contributes to the excess  $H_2$ . However, there is a silver lining; this excess production of  $H_2$  may point the way to a cheap  $H_2$  source that could be used in a hydrogen economy.<sup>1</sup> This potential application is increasingly important as the rising environmental and monetary costs of fossil fuels drives greater interest in such clean alternative energy systems.

Finally, astrobiologists, astrochemists, and astrophysicists must also consider and understand the radiolysis of water. In space, water is the most common solid compound<sup>2</sup> and is a necessary criterion in determining where to look for life outside our own planet. Energy is needed to drive any biological or prebiotic reactions, and highly energetic radiation is a major (and sometimes only) source. Radiation-driven reactions, and especially those in amorphous solid water (ASW), have been shown to generate necessary biological precursors for earth-like life,<sup>3-6</sup> including homochiral amino acids.<sup>7, 8</sup> ASW-catalyzed reactions are also responsible for the generation and destruction of  $H_2$  on grain surfaces,<sup>3</sup> which must be considered in determining the origins and evolution of many objects, including molecular clouds and the interstellar medium.

### **Why use ASW?**

Previous work has studied radiolysis of vapor, liquid, and solid phases of water.<sup>1</sup> In the applications mentioned above, the condensed phases are of greatest concern. In the work presented in this dissertation, we limit ourselves to ASW films, and neglect liquids and crystalline solids. ASW is an eminently suitable medium for this work. It is directly



applicable to the astronomical applications, as it is the form predominantly found in those environments. It is also directly applicable to biological research, as the formation of ASW in tissue samples can lead to problems in preserving sample structure.<sup>9</sup> However, ASW's defining lack of long-range order also makes it an excellent model for crystalline ice surfaces,<sup>10, 11</sup> liquids, and glasses<sup>12, 13</sup> considered in other fields. The unique characteristics of ASW make it a preferred medium, as reactions can be slower compared to liquid water, easing measurements, and some data are available in the condensed phase only for ASW.<sup>1</sup> Additionally, the slower mixing of ASW compared to liquid water is an advantage in studying heterogeneously distributed reactions, such as those occurring at interfaces or along particle tracks. For this purpose, ASW is preferred over crystalline ice (CI), as the defect-laden structure better mimics liquid structure and provides greater mobility to guest molecules.<sup>14</sup>

However, studying these reactions in ASW is not without its complications. Considerable debate about the phase state (i.e., if it is a supercooled liquid, a true solid, or both) and other fundamental data such as the glass transition temperature exists in the literature.<sup>15-31</sup> Like crystalline ices, ASW has multiple forms, which are generally determined by the growth conditions. For example, the density of ASW can vary from 0.16 g/cc in porous structures to 1.31 g/cc in films grown at high pressure.<sup>32</sup> Such variation in density is exaggerated by the introduction of pores or voids to the ASW structure, which can contain up to 80 % of the solid's volume. The most common form of ASW is called "low-density" ASW, even though its density is comparable to that of cubic ice, ~0.94 g/cc,<sup>33</sup> to contrast it with the high-pressure forms. Low-density ASW is grown

by vapor deposition at temperatures less than  $\sim 120\text{K}$  under UHV conditions and in space, making it the most common form of water in the universe. This form is the focus of our work, and is the form referred to in this document. The various forms of ASW have required the development of new techniques to grow a consistent dense, non-porous ASW film for experimental purposes. Care must be employed in growing the films, as templating the surface with crystalline ice prevents the growth of ASW.<sup>34</sup> The preferred method, used in our experiments, requires that a molecular beam of water molecules be dosed perpendicularly to the supporting substrate held at  $T$  less than  $90\text{ K}$ . This method creates films of uniform, maximum density<sup>35</sup> and minimum porosity<sup>36</sup> without requiring annealing and prevents the growth of CI. For our purpose, this is ideal, as the development of a porous or otherwise rough surface will affect the amount of methanol deposited, the extent of the methanol/water interface, and the mobility of the methanol in the ASW.

### **Thermal processes in ASW**

To understand the non-thermal effects discussed later, a brief summary of thermal processes in pure and doped ASW is given here. As mentioned previously, there is extensive debate in the literature about fundamental characteristics of ASW, such as its phase, the nature of the crystallization transition, and the glass temperature. There is evidence that ASW is a glassy solid,<sup>2, 15, 37, 38</sup> and additional evidence that it is a liquid (or very liquid-like) instead.<sup>16, 17, 21, 30, 39-41</sup> Further debate about whether water is a strong or weak liquid complicates the matter. However, there is a growing body of evidence that if

water is a liquid, it is a strong liquid at T less than 160 K, and cannot be a fragile liquid.

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As the ASW is heated, it crystallizes into cubic ice at  $\sim 160$  K (exact crystallization temperature varies with heating histories). At this time, the increased mobility of the ASW increases mixing of the water with itself, as seen by isotopic labeling.<sup>24, 40</sup> Structural changes occur simultaneously as crystallization begins via small-domain nucleation.<sup>44</sup> Crystallization is not complete, as the crystal domains coexist with ASW domains that can trap volatiles during crystallization if the volatile concentration smaller than 10 %.<sup>44</sup> The coexisting ASW and crystal grains, and the stresses induced by crystallization, lead to the development of cracks in the water film, through which trapped species can explosively desorb, and which also provide a major transport mechanism for water.<sup>26, 42</sup> These trapped molecules would normally have desorbed at much lower temperatures, and therefore the explosive desorption marker is usually a very sharp desorption peak occurring at the water crystallization shoulder, as water desorption slows.<sup>45</sup> Similar results have been seen with molecules dosed onto porous ASW films that become trapped as the pores collapse during annealing to be released later,<sup>46-48</sup> indicating that ASW can retain possible reactants at temperatures greater than would be predicted.

The additional motion of the water molecules at the crystallization temperature increases the likelihood of reaction in the ASW. However, the effect of adding dopants to the film has been studied in only a limited manner, primarily to gather infrared (IR) spectra for astronomical surveys, rather than information on transport via diffusion or cracking channels or to gather information about reaction pathways. Studies on the

formation of clathrate hydrates, for example, have only included a few acids in the context of adsorption on stratospheric ice particle surfaces. McClure *et al.* showed that the addition of  $\text{HNO}_3$  in small quantities to ASW reduced the degree of fracture, and the associated transport, while accelerating crystallization.<sup>42</sup> Souda<sup>49</sup> found that formic acid and propanol dosed on a  $\text{D}_2\text{O}$  surface were hydrated, and suggests that these compounds quench the crystal transition by remaining on the surface and reducing surface tension.

### **Thermal processes in mixed water/methanol systems**

Gunster *et al.*<sup>50</sup> used metastable impact electron spectroscopy (MIES) and ultraviolet photoelectron spectroscopy (UPS) to study the interaction of thin films (2-10 ML) of  $\text{CH}_3\text{OH}$  and  $\text{D}_2\text{O}$  on  $\text{MgO}(100)$ . MIES is a surface-sensitive technique while UPS signals incorporate some of the bulk response, so the combination of these two techniques enabled the researchers to determine the location of each chemical, and to describe qualitatively the mixing at the surface and in the bulk. Their results indicate that a near monolayer of methanol on 6 ML water was sufficient to cover the water surface, indicating a slightly higher sticking probability of  $\text{MeOH}$  on  $\text{D}_2\text{O}$  than on  $\text{MgO}$  or  $\text{MeOH}$ . At the same time, methanol did not penetrate into the bulk of  $\text{D}_2\text{O}$ , but remained localized on the surface. Heating the  $\text{CH}_3\text{OH}/\text{D}_2\text{O}/\text{MgO}$  sample led to mixing beginning at about 140K, with desorption complete by  $\sim 165\text{K}$ . However, if methanol was pre-deposited and water dosed on top of it, mixing appeared to occur at 100K, the dosing temperature. Even dosing 8 ML  $\text{D}_2\text{O}$  atop 2 ML  $\text{CH}_3\text{OH}$  led to a surface layer that was mixed methanol/water, apparently driven by the energetic cost of solvating the

hydrophobic methyl group. Smaller changes were observed upon heating this pre-mixed sample, but at 155K the two were both comparably mixed. For contrast, films of methanol and ethanol, where both molecules are amphiphilic, were observed to intermix completely prior to the onset of desorption at  $\sim 120\text{K}$  by Ayotte and coworkers.<sup>51</sup>

Temperature Programmed Desorption (TPD) of 8 ML  $\text{D}_2\text{O}/2\text{ ML CH}_3\text{OH}/\text{MgO}$  shows two methanol peaks, occurring at 162 K, approximately the crystallization temperature of  $\text{D}_2\text{O}$ , and at 175K, when desorption of  $\text{D}_2\text{O}/\text{CH}_3\text{OH}$  is complete.<sup>50</sup> In contrast, TPD of 8 ML  $\text{D}_2\text{O}/3.5\text{ ML CH}_3\text{OH}/\text{MgO}$  shows two methanol peaks at 145K and 174K. While the 174 K peak is again due to completing desorption, the 145K peak shows different characteristics, including a sharp rise beginning at 140K and the appearance of a water signal at the same temperature not present in the 8 ML  $\text{D}_2\text{O}/2\text{ ML CH}_3\text{OH}/\text{MgO}$  sample. This temperature is too low to be caused by the ASW to cubic ice phase transition. Gunster *et al.* argue that the higher mobility of the capping water layers at 140K is responsible for the sudden appearance of  $\text{CH}_3\text{OH}$ , and the associated water peak results from entrainment by methanol desorption.

However, they do not address the likelihood, based on the observed mixing, that methanol is already present at the surface of the water multilayer. We cannot eliminate the possibility that this 140K peak is surface desorption of methanol from an enriched methanol/water surface, which would also lead to an entrained water peak, consistent with results by Wolff, Carlstedt, and Brown.<sup>52</sup> It is clear that during deposition of water, methanol is sufficiently mobile to act as a surfactant, moving to (or remaining at) the surface to minimize the total energy by placing the hydrophobic methyl group at the

surface. Any resulting “capping water layer” is likely a mixture of water and methanol. This mix would have increased mobility, leading to the lower desorption temperature, resulting from a decreased mean number of H-bonds per molecule and increased disruptions by the hydrophobic methyl group. However, the degree of mixing that occurs in sub-surface layers (e.g., if lower layers are mixed to a greater or lesser degree than the surface) when water is the capping film is unknown, and has not yet been studied.

The orientation of methanol on the surface of ice Ih (0001) at 0K was simulated by Picaud, Toubin, and Giradet.<sup>53</sup> They also found that the interaction between water and methanol is stronger than the interaction between methanol and methanol. Two probable adsorption sites for methanol on Ih were found, in which the more stable (-442meV vs. -427meV) is oriented such that the OH bond points to a water oxygen and the methyl group lies over a cavity in the ice crystal. Additional simulations by Collignon and Picaud<sup>54</sup> focused on mobile surface layers as opposed to rigid layers. Not surprisingly, the methyl groups of CH<sub>3</sub>OH are tilted away from the ice surface, and CH<sub>3</sub>OH acts to hydrogen bond (by donation and acceptance of H) with both water and other methanol molecules.

Unlike mixed alcohol films, water and methanol mixed films do not mix when the methanol is dosed at the surface. Methanol acts as a surfactant when water is dosed atop it at 100 K, moving to the surface and increasing its local concentration. This transport only occurs during deposition, and not during subsequent heating.

### **Basic radiation-driven mechanisms in pure water films**

Experiments on the radiolysis of liquid water showed that high energy particles ( $\gamma$  rays,  $\alpha$  particles, neutrons, and highly energetic electrons, for example) generate large quantities of lower-energy electrons by ionization, both directly by stripping an electron to form an energetic ion, and through subsequent collisions of that ion.<sup>1</sup> Secondary ion collisions in particular yield large quantities of these lower energy electrons, which have an average energy less than 100eV. These  $\sim 100\text{eV}$  electrons generate yet lower energy electrons, of average energy less than 10eV,<sup>55</sup> through a similar ionization mechanism. Both the first and second series of ionization events are localized in the water structure, and the subsequent excitations and newly formed ions have a localized distribution in the water, concentrated near the original particle's path, as these processes happen on a femto- to pico-second time scale.<sup>1</sup> The resulting ionized and excited water molecules can follow several reaction pathways to form  $\text{H}_3\text{O}^+$ ,  $\text{OH}^-$ ,  $\text{O}^-$ , and  $\text{H}^-$ ,  $\text{OH}$ ,  $\text{H}$ , solvated electrons,  $\text{H}_2$ ,  $\text{O}$ , and  $\text{H}$ . These species in turn can form new species such as  $\text{H}_2\text{O}_2$  and  $\text{HO}_2$ . Our full understanding of the processes leading to these products is complicated by the strong intermolecular interactions of water molecules and its high polarity, and a lack of knowledge about how these characteristics impact the structure and formation of ions and excitons.

## H<sub>2</sub> and O<sub>2</sub> production in pure water

To better understand the radiation chemistry of the reactions, research has focused on the reactions driven by the  $\sim 100\text{eV}$  electrons. In water films, the main molecular products are O<sub>2</sub> and H<sub>2</sub> but H, O, and H<sub>2</sub>O<sub>2</sub> have also been observed.<sup>56</sup> Photoionization studies have observed mainly H<sup>+</sup> at 21eV (584Å), and H<sup>+</sup> and H<sub>3</sub>O<sup>+</sup> at higher energies (41eV, or  $\sim 300\text{ Å}$ ).<sup>57</sup> Anionic H and D have been found to desorb from ASW surfaces at very low electron energies of 5.5 eV, with maximum anionic yield peaking at  $\sim 7.4\text{ eV}$ , comparable to the first water excitation at 7.3 eV.<sup>58</sup> These anions have a very high probability of trapping on the ASW surface,<sup>58</sup> where they were later found to be the source of D<sub>2</sub> production at 6.3 eV, by reaction with H<sub>2</sub>O (D<sub>2</sub>O).<sup>59</sup> At higher energies, additional reactions are available, including that of H<sub>3</sub>O<sup>+</sup> with trapped electrons, and direct formation from excited water states.<sup>60</sup> Petrik and Kimmel<sup>61</sup> later examined the production of H<sub>2</sub> from water films using  $\sim 100\text{eV}$  electrons. H<sub>2</sub> production is confined to the interfaces, in this case the water/vacuum interface and the water/Pt (111) interface. No H<sub>2</sub> was produced in the bulk regions of the water. However, the bulk region is the main region of energy absorption, indicating that excited water molecules must diffuse to the interfaces before they can react. The implications of these results are discussed in Chapter 3, where we examine the effect the addition of H-rich methanol on H<sub>2</sub> production.

O<sub>2</sub> production was previously characterized by Petrik, Kavetsky, and Kimmel,<sup>62</sup> and found to increase with exposure until it saturates. This increase in O<sub>2</sub> production is the result of several electron-driven reactions that yield increasing quantities of O<sub>2</sub>



precursors such as OH, H<sub>2</sub>O<sub>2</sub>, and HO<sub>2</sub>. These precursors are then consumed in O<sub>2</sub> production and saturation correlates to a steady-state process. The details of this multi-step reaction are discussed in Chapter 4. Briefly, using isotopically labeled water (H<sub>2</sub><sup>16</sup>O, H<sub>2</sub><sup>18</sup>O, and D<sub>2</sub>O), O<sub>2</sub> production results from HO<sub>2</sub> dissociation occurring at the water/vacuum interface only during exposure. No reactions occurred if the electron beam was turned off. If the beam was restarted, O<sub>2</sub> production immediately resumed at saturation levels. The surface concentration of HO<sub>2</sub> and other precursors (H<sub>2</sub>O<sub>2</sub> and OH) at saturation were predicted by kinetic modeling to be ~0.01 to 0.03 ML relative to the water coverage (1 ML).

### **Radiation-driven products in pure methanol**

Stockbauer, Bertel, and Madey used variable UV photoemission and photon stimulated desorption to study pure MeOH films.<sup>63</sup> They found that the primary desorbed ions were H<sup>+</sup>, which accounted for over 98% of the total ion yield. Electron stimulated desorption (ESD) experiments and isotopic labeling confirmed that in condensed films, the dominant source of H<sup>+</sup> is due to CH bond cleavage (as compared to the gas phase, where both CH and OH bond cleavage contribute) when the electron energy is 30-70 eV, consistent with the results of Burrows *et al.*<sup>64</sup> Stockbauer and coworkers state that the onset of proton desorption was ~21eV, and suggest that these protons originate from excitation of the 4a' orbital, focused on the methyl group.<sup>63</sup> The emission of anions occurs at much lower energies; Parenteau, Jay-Gerin, and Sanche<sup>65</sup> detected H<sup>-</sup> as low as 6 eV, with the signal peaking around 8.3 eV, indicating that in a mixed film both

methanol and water may generate anionic hydrogen at very low energies. By using  $\text{CH}_3\text{OD}$  and  $\text{CD}_3\text{OH}$ , they found that the hydrogens originated from the methyl and hydroxyl groups. Dissociation of the hydroxyl group is similar to that seen in water, and is primarily responsible for anion production at energies lower than 9 eV, while CH scission is the main source of  $\text{H}^-$  at energies greater than 9 eV.<sup>66</sup> Neutral CO was also generated at these energies as a result of dissociation.<sup>67</sup>

As with water, the products of pure methanol films are interface sensitive and dependent on the film thickness. Working on an Ar substrate, Kawanowa *et al.*<sup>68</sup> found that methyl ion fragments, hydronium ions,  $\text{CHO}^+$ , and  $\text{CH}_3\text{O}^+$  ions were emitted, with the highest yields seen at the lowest coverages. From a thick layer, only protons were observed. Henderson, Otero-Tapia, and Castro<sup>69</sup> studied the electron induced decomposition of methanol monolayers on  $\text{TiO}_2$  (110) using TPD and ESD. Major post-irradiation (100eV) *ion* fragments were  $\text{D}^+$ ,  $\text{O}^+$ , and  $\text{OD}^+$ ; neutrals were not reported but the authors speculated that they are major channels. Work by Schwaner and White<sup>70</sup> examined the low energy electron induced fragmentation of methanol on silver (111). As on  $\text{TiO}_2$  (110),<sup>69</sup> methanol was not observed to thermally decompose. Following irradiation, primary products were water, methane, hydrogen, formaldehyde, and glycoaldehyde, the latter observed only from multilayers. CH bond dissociation was found to be the primary route to  $\text{H}_2\text{CO}$  formation, while CO bond dissociation led to  $\text{CH}_3$  and OH groups; OH bond dissociation was found to occur only at long irradiation times.<sup>70</sup> Of particular interest to our work with oxygen-rich water, Sasaki, Itai, and Iwasawa<sup>71</sup> studied the decomposition of methanol on Ru (001) precovered with O. The

presence of the oxygen enhanced selective CH scission and suppressed CO scission, promoting the formation of CO relative to Ru (001) not precovered with O. These results lead us to expect large quantities of H or H<sub>2</sub> from our methanol-doped water films, as well as significant CO and CH<sub>2</sub>O signals. However, results of electron-induced reactions (EIR) and TPD experiments by Harris *et al.*<sup>72</sup> indicate that C<sub>2</sub>H<sub>4</sub>, (CH<sub>2</sub>OH)<sub>2</sub>, CH<sub>3</sub>OCH<sub>2</sub>OH, CH<sub>3</sub>OCH<sub>3</sub>, H<sub>2</sub>CO, and CH<sub>3</sub>CH<sub>2</sub>OH are also possible products, and that detection of CH<sub>3</sub> and CH<sub>4</sub> is likely. A more thorough discussion of observed products and possible mechanisms will be given in Chapter 2.

### **An increasingly complicated system: Radiation-driven processes in doped water films**

As mentioned previously, most work with water/organic mixed films has focused on IR spectra for astronomical identification or to determine possible products, many of which have produced methanol or methanol fragments.<sup>73-80</sup> However, despite the ubiquity of methanol/water mixes in astronomical and terrestrial environments, limited work has been completed examining processes of these mixed or layered films. Much of the work that has been done has focused on very energetic ions or specific photoemission lines common in space.

Palumbo, Castorina, and Strazzulla examined the effects of ion irradiation of 3-30keV ions on pure methanol and mixed methanol-water ices using IR spectroscopy. While they found that the pure methanol produced significant water during irradiation, the methanol-water mixes showed much smaller changes, although some CO and CO<sub>2</sub>

was detected.<sup>81</sup> Likewise, Brunetto *et al.*<sup>80</sup> examined the radiolysis products of methanol and water-methanol mixtures exposed to 30 keV and 200 keV ion radiation, and found CO and CH<sub>4</sub> to be the primary products. Wu, Yang, and Judge determined the ion desorption yields of pure water, pure methanol, and mixed water-methanol ices at 77K caused by radiation at 58.4 nm (21.2 eV).<sup>82</sup> They found that the mixed ices showed enhanced ion desorption yields compared to the pure ices, possibly due to greater disruption of H-bond network or to reduced ionization potentials previously observed in the condensed phase.<sup>83</sup>

Radiation-driven processes in pure ASW and in pure methanol have been examined, but work so far on mixtures of the two has been limited and has neglected the role of the methanol/water interface. However, such mixtures are extremely common in many settings where ASW research has applications: comets and icy bodies, clouds, cells, and retired nuclear reactors. In these circumstances, the role of the interface can be crucial, as the introduction of any interface disrupts the H-bonding network of ASW and changes its reactivity. Major products of ASW radiolysis, H<sub>2</sub> and O<sub>2</sub>, are formed primarily at such interfaces. These reactions require both matter and energy transfer across that interface. Studying these mixed films and their interfaces will improve our understanding fundamental topics such as hydrogen-bonding networks, mixing at low temperatures, and energy transport.

## Dissertation Overview

This dissertation examines radiation-driven processes in mixed methanol-water films. Extra attention is given to the generation and destruction of molecular hydrogen and molecular oxygen due to the importance of these species in environments of interest, nuclear waste tanks and astronomical ices. In the former, the presence of  $H_2$  poses a serious hazard to attempts to clean up contaminated sites. The build up of gases in these waste tanks also increases the risk of developing a leak in the tank, especially in the case of older, single-walled tanks. Previous studies have found greater quantities of  $H_2$  present in these tanks than predicted by theory. Our research shows that this excess  $H_2$  is likely due to the presence of small quantities of organic compounds, a factor that must be included in future models of nuclear waste storage and treatment. The formation of  $O_2$  from water present in these tanks only increases the combustion and containment hazards posed by  $H_2$  build up, and consequently must be considered.

Water and methanol mixes are common in astronomical ices of many types, including comet nuclei, interstellar dust grain mantles, asteroids, and moons/planetary bodies. Depending on the particular ice environment, the motivation for understanding these processes changes. In a comet, we are most interested in reaction byproducts and the possible formation of organic compounds relevant to life's origins. On a grain mantle or in a gas cloud, both possible organic compounds and the creation and destruction of  $H_2$  are of importance.

All of the experiments described in this dissertation were performed using an ultra-high vacuum chamber and molecular beam techniques to grow smooth, dense, non-porous ASW, CH<sub>3</sub>OH, and layered films. A TiO<sub>2</sub> (110) crystal was used as the growth substrate. However, some of the experiments reference ASW films grown on a Pt (111) crystal under the same conditions. In very thin films (40 ML or less), the substrate does play a role in determining reaction products and promoting reactions. However, in our experiments, we focused on relatively thick films of 80 ML or more, rendering the nature of the substrate irrelevant. Experiments with thick ASW films on TiO<sub>2</sub> (110) and Pt (111) yield very similar ESD spectra and are comparable. TPD peaks from these experiments are not compared to those using a Pt (111) substrate, although the basic shape of the water desorption peak is similar.

Chapter 2 comprises an overview of the results from these experiments. ESD and TPD spectra are analyzed to determine major products and processes of irradiation. Pure methanol, methanol-capped water films (methanol/water/TiO<sub>2</sub> structures), and methanol-sandwiched films (water/methanol/water/TiO<sub>2</sub> structures) are discussed. These experiments show that methanol is quite mobile during deposition at 80 K, acting as a surfactant, but immobile at 50 K. We also find that the methanol-water films, even for 30 ML thick methanol layers, produce fewer product species. The kinetics of desorption are not discussed, as up to 4 peaks overlap during desorption. The TPD data indicate that methanol and water co-desorb over a broad temperature range, and are mixed during the irradiation cycle.

Chapter 3 discusses how methanol changes  $H_2$  production from water films.  $H_2$  generation in both methanol and water begins immediately with the onset of radiation. Methanol generates copious quantities of hydrogen compared to pure water. Although the CH bond is slightly weaker than the OH bond as described above, we find that the main difference at the energy levels examined is not the quantity of H generated at each functional group, but the sustainability of  $H_2$  production by that group, with  $H_2$  production from the  $CH_3$  group persisting longer. Capping layers of methanol on ASW quickly block the prompt  $H_2$ -forming water-vacuum interface. However, at sub-monolayer doses, methanol increases the ability of water to generate  $H_2$  by increasing  $H_2$  production at later times. This increase appears to be due to the creation of an extended methanol/water/vacuum interface. Similar results were seen with buried methanol/water interfaces, where the  $H_2$  signal from water was observed to increase by as much as 40%. This increase is due to the creation of a reactive methanol/water interface in regions of the bulk water that are typically unreactive. When the effect of mixing between the water and methanol layers is considered, i.e., at longer irradiation exposures, the increase is greatest. We propose that these new interfaces increase the number of dangling bonds, more easily trapping the excitons that drive the reaction. The disruption of ASW's H-bonding network by methanol may also increase the mobility of water molecules near the interface and aid  $H_2$  production.

The fourth chapter covers the suppression of  $O_2$  production from water and explores the mechanisms by which methanol interrupts this multi-step reaction process. In water,  $O_2$  is known to form at the vacuum interface. We find that the addition of

methanol to this interface, even at very low (0.05 ML) coverages, suppresses the production of  $O_2$  from water in an unprocessed film. Similarly, a monolayer of methanol in the upper 30 layers of a water film also suppresses  $O_2$  production, with greater suppression observed as the methanol was placed closer to the vacuum interface, and no  $O_2$  produced during the radiation cycle when it was in the uppermost 10 layers. Unlike  $H_2$  production, in which hydrogen formed at the methanol/water interface could come from either source, the little  $O_2$  that was observed to form is almost exclusively (more than 95%) from water, with very little O mixing between the two layers. We found that methanol was similarly opaque to  $O_2$  produced below the methanol layer, with nearly all of the detected  $O_2$  resulting from water capping layers. Again, buried methanol layers act as an internal interface in a manner strongly resembling the interface created by Pt or  $TiO_2$ , creating a reactive interface in the normally non-reactive bulk water. These results, and  $O_2$  suppression, are even more noticeable in pre-processed water films that have a saturation concentration of  $O_2$  precursor molecules ( $HO_2$ ,  $H_2O_2$ , and  $OH$ ). We confirm that the  $O_2$  suppression ability of methanol is a long-range effect that does not require methanol to be present at the precursor-saturated interface. These results all suggest that methanol is preferentially trapping excitons and reacting with  $OH$  at the vacuum interface, preventing the formation of the necessary  $O_2$  precursors  $HO_2$  and  $H_2O_2$  in the film. Expanding upon the kinetic model used by Petrik *et al.*,<sup>62, 84</sup> we show that the reactions of methanol with electrons,  $HO_2$ , and  $OH$  account for the  $O_2$  suppression in the unprocessed and preprocessed films.



In the final chapter, the major findings, and possible applications, of these experiments are summarized. Future avenues of research are also discussed.

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## **Chapter 2: Observations on electron-driven reactions between methanol and ASW**

### **Introduction**

A significant body of literature studying pure water and pure methanol exists, including both radiation-driven and thermal processes. Mixed water/organic systems, such as are found in cells, the atmosphere, nuclear waste tanks, and comets, have been studied less. However, understanding these mixed systems is necessary to accurately model many systems of interest, such as protein folding and DNA damage in cells, or the origins of prebiotic chemistry in space. Radiation-driven processes are of particular interest for these systems, as they are either responsible for the more pertinent consequences (e.g., accelerating cellular aging or creating tumors) or are the major source of energy (e.g., nuclear waste tanks and astrophysical environments). To model these non-thermal processes in mixed water/organic solutions, we use low energy electrons and layered films of methanol and amorphous solid water (ASW). Low energy electrons are generated in copious quantities by the radiolysis of water and drive most of the subsequent reactions.<sup>1</sup> Methanol is used as a model organic compound because it is known to be present in many of the environments mentioned above, is a common product of radiolytic reactions between water and simpler organics such as  $\text{CH}_4$ ,<sup>2</sup> and does not irreversibly thermally decompose.<sup>3</sup> While some studies have been performed on the thermal processes occurring in mixed methanol/ASW films,<sup>4, 5</sup> no previous works have been published regarding low-energy electron-driven processes in solid mixes of methanol and water at cryogenic temperatures.

## Methods

### *Chamber Set Up*

Experiments were done in an ultra-high vacuum (UHV) chamber, equipped with a closed cycle helium cryostat, low-energy electron gun, quadrupole mass spectrometer, and a molecular beam line. Median base pressure for the system was  $\sim 1.1\text{E-}10$  torr and base sample temperature was  $\sim 22\text{K}$ . Films were grown on a clean  $\text{TiO}_2$  (110) crystal approximately 10 mm in diameter and 0.5mm thick. The crystal was cleaned by neon ion sputtering, followed by annealing at 850 K in vacuum, to yield a consistent  $\text{TiO}_2$  (111) surface. The sample was resistively heated, and the temperature measured by a type K thermocouple spot-welded to the back of the sample.

### *Deposition and Growth Conditions*

High-Pressure Liquid Chromatography-grade  $\text{CH}_3\text{OH}$ , distilled, deionized  $\text{H}_2\text{O}$ , and their isotopologues ( $\text{CD}_3\text{OH}$ ,  $\text{CD}_3\text{OD}$ ,  $\text{D}_2\text{O}$ , and  $\text{H}_2^{18}\text{O}$ ) were freeze-pump-thawed prior to use to remove dissolved gases and to ensure purity. All films were dosed at temperatures colder than 100 K by molecular beams at normal incidence to the sample, creating a dense non-porous film.<sup>6, 7</sup> The films did not cover the entire substrate surface, but were centered on the  $\text{TiO}_2$ . Water coverage calibration was based on previous calculations using a coverage of  $1 \times 10^{15}$  molecules\* $\text{cm}^{-2}$ .<sup>8</sup> Direct measurements of methanol saturation coverage on ASW for calibration purposes are difficult due to mixing processes during desorption. Instead, methanol coverage was calibrated based on the integration of the first monolayer peak in the temperature programmed desorption spectra



from a *bare* TiO<sub>2</sub> crystal. Based on the relative coverage of methanol on bare TiO<sub>2</sub> (110),  $3.2 \times 10^{14}$  molecules cm<sup>-2</sup>,<sup>9</sup> one monolayer of methanol on ASW was defined to be roughly three times the exposure needed for one monolayer on methanol on TiO<sub>2</sub>. This definition of a CH<sub>3</sub>OH monolayer on ASW has a comparable coverage to that of a water monolayer on ASW,  $1 \times 10^{15}$  molecules\*cm<sup>-2</sup>. The same exposure definition (in torr s) was used for each of the isotopically labeled varieties of methanol used, CH<sub>3</sub>OH, CD<sub>3</sub>OH, and CD<sub>3</sub>OD, although the calibration was performed only for CH<sub>3</sub>OH. We must emphasize that our monolayer definition is strictly to make comparing the effects of a monolayer of methanol with those of a water monolayer easier on a per-molecule basis, and is not based on any measurement of the actual coverage of CH<sub>3</sub>OH on ASW. Estimates of CH<sub>3</sub>OH coverage on crystalline ice surfaces (none are available for ASW surfaces) range in value, but are comparable to its coverage on TiO<sub>2</sub> (110).<sup>10-12</sup>

The structured methanol/water films in our experiments often required different growth temperatures for different layers. Underlying foundational water layers (in contact with the TiO<sub>2</sub> surface) were grown at 80K, conditions known to produce consistently dense and smooth ASW surfaces.<sup>6, 7</sup> Surfation, or the phase separation and resulting movement of methanol to the vacuum interface, was observed during deposition of upper water layers in “sandwich” experiments. In these experiments, layers of water are dosed atop methanol to isolate it from the vacuum interface, creating a layered film with a sandwich-like structure of water/methanol/water/TiO<sub>2</sub>. When the upper layers were deposited at 80K, the methanol promptly appeared on the surface in subsequent electron stimulated desorption (ESD) experiments. When the upper layers were dosed at 50K or

less, it eliminated the prompt appearance of methanol from subsequent ESD experiments, even if the film was heated to 80 K from the lower dose temperature. Heating gently to 80K and irradiating had no effect on the ESD signal structure compared to irradiation at 50 or 25K. (For details, see results section.) To eliminate the effects of such surfaction in studies of ESD and temperature-programmed desorption (TPD) products in mixed films, all upper films were grown at 80K or less, depending on their position in the final film structure. Capping water layers, or layers dosed atop methanol, were grown at 50K or less to minimize the surfactant properties of methanol. Methanol films were grown at 80K or less if their final position was located at the vacuum interface (i.e., an “open-faced” sandwich structure, also referred to in this paper as a methanol-capped film), and at 50K or less if in the interior (i.e., in a “sandwich” experiment).

### *Radiation Conditions*

To eliminate the effects of thermal mixing and focus on radiative mixing and reaction products, all irradiation was performed at 80 K or colder; changes in the ESD temperature do not appear to change the signal structure, although it may affect the signal intensity (See results section). Capped films were irradiated at 80 K, when the surfactant properties of methanol could be neglected. Sandwich films were irradiated at their growth temperature unless otherwise noted. The electron beam was incident at 35° to the sample normal. The films were irradiated with 100 eV electrons at a current of  $\sim 2 \mu\text{A}$  for 100 scan cycles (for a total exposure of  $\sim 97$  s) unless otherwise noted. A scan-averaging mode was used that samples the signal repeatedly within a single cycle, rastering across

the film sample to generate “pixels.” The pixels were then averaged to generate a single data point per cycle with a very high signal-to-noise ratio, as described in detail in Petrik *et al.*<sup>8</sup>

Experimental cracking fractions in our system were determined during isothermal measurements of CH<sub>3</sub>OH and are given in Table 2.1. These cracking fractions are used instead of literature cracking fractions (e.g., NIST) for the purpose of making assignments of ESD and TPD products.

## Results and Discussion

### *Surfation*

Methanol has been previously observed to act as a surfactant,<sup>4</sup> meaning that the methanol molecules preferentially congregate at the water/vacuum interface. The presence of methanol at the vacuum interface suppresses O<sub>2</sub> production from water even at low (<0.1ML) concentrations (See Chapter 4). Therefore, we can use the O<sub>2</sub> ESD signal as a tracer of methanol’s presence at the surface. To examine the ability of methanol to surfact, we used sandwiches of 30 ML H<sub>2</sub>O/1 ML CH<sub>3</sub>OH/ 50 ML H<sub>2</sub>O/TiO<sub>2</sub> (110). This structure was chosen for several reasons. For films of this total thickness (81 ML), there should be no detectable products from the TiO<sub>2</sub>/ASW interface,<sup>8, 13</sup> allowing us to focus on surfation at the vacuum interface. Methanol buried under 30 ML of H<sub>2</sub>O should not receive significant energy from impinging electrons that would allow the molecule to react,<sup>14</sup> avoiding any effects caused by methanol by-products. Finally, we found that O<sub>2</sub> production saturates when 30 or more ML H<sub>2</sub>O are deposited atop CH<sub>3</sub>OH

(See Chapter 4), giving us a large control signal for easy comparison. The sandwich films were grown and irradiated at various temperatures, allowing us to explore the effect of temperature on the ability of methanol to move through the film. Our data show (Figure 2.1) that while methanol does act as a surfactant, it does so only under certain conditions.

The lowest available temperature of the chamber is  $\sim 22\text{K}$ . To best exclude any possible thermal effects on surfaction, the sandwich film was grown and irradiated at 25 K. Results are shown in Figure 2.1. In this “ideal” case,  $\text{O}_2$  production begins immediately with the onset of irradiation, and grows until saturation, consistent with  $\text{O}_2$  production from a pure water film. Repeating the experiment with a growth temperature of 25 K and irradiation temperatures of 50 and 80 K yielded nearly identical line shapes, once they were scaled for differing saturation values. The key characteristic, prompt production of  $\text{O}_2$ , was still present. Therefore, diffusion of methanol to the surface during heating is slow enough that it does not cause surfaction. Similar results were obtained when the growth temperature was 50 K and the irradiation temperature was 50 or 80 K. However, when the sandwich film was grown at 80 K, the prompt  $\text{O}_2$  production signal vanishes, indicating that methanol is present at the vacuum interface at the beginning of the ESD. During deposition at 80 K,  $\text{CH}_3\text{OH}$  is mobile enough to move to or remain at the surface, where the hydrophobic methyl groups’ solvation energy can be minimized. At deposition temperatures less than or equal to 50 K, methanol is immobilized, and no surfaction is detected.

Deposition temperature appears to have little effect on the ESD signal shape and intensity. For example, if capping layers of methanol that are deposited at 50 K and

irradiated at 80 K show very similar H<sub>2</sub> and other signals as capping layers deposited and irradiated at 80 K. The greatest difference is seen in the 32 amu signal, especially at very low coverages (Figures 2.2 and 2.3). When CH<sub>3</sub>OH is deposited on 80 ML ASW at 80 K, the O<sub>2</sub> signal recovers sooner than when methanol is deposited at 50 K, implying that less methanol is on the surface when deposited at 80K. This difference is only apparent when 0.35 ML CH<sub>3</sub>OH or less are deposited, and is most obvious at near-zero coverages. It is unlikely that the sticking coefficient for methanol on ASW changes greatly over this temperature range. The supporting ASW layers were grown at 80 K in both cases and therefore have similar morphologies. Instead, increased mixing during deposition effectively moves small quantities of the methanol into the water layer, causing the reduced apparent surface concentration of methanol when deposited at 80 K. This mixing may be due to stronger H-bonding interactions between methanol and water than between methanol and methanol,<sup>15</sup> but appears to be a weaker effect than the surfaction-inducing forces that move buried methanol to the ASW surface.

#### *Deposition of pure methanol*

30 ML of CH<sub>3</sub>OH were deposited at 80K and then heated at a ramp rate of 2 K/s. One major peak at 172K was detected (See Table 2.2), and is assigned to the molecularly desorbing CH<sub>3</sub>OH multilayer. Only masses resulting from CH<sub>3</sub>OH fragmentation are observed at this peak. Greater quantities of masses 18 and 28 are observed than are predicted by methanol cracking fragments, the result of background H<sub>2</sub>O and CO in the chamber. We use our experimentally defined cracking fragments shown in Table 2.1 in

assigning peaks and compounds in subsequent experiments. Additional minor peaks were observed at ~315 K and ~550 K. The latter peak lacks a 31 amu signal but is consistent with the presence of small quantities of CH<sub>2</sub>O. These results are consistent with those of Henderson, Otero-Tapia, and Castro,<sup>3</sup> who examined the surface chemistry of thin layers of pure methanol deposited on TiO<sub>2</sub> (110). Four major temperature programmed desorption (TPD) peaks were identified, including a multilayer peak at 150K and a peak associated with molecular desorption of the CH<sub>3</sub>OH monolayer at 295K.

#### *ESD and TPD of pure methanol*

As with water, the main irradiation product of 30 ML CH<sub>3</sub>OH is H<sub>2</sub>. Other products include H<sub>2</sub>O, CH<sub>3</sub>OH, CH<sub>2</sub>O, CH<sub>4</sub>, CO, and CO<sub>2</sub>, and likely C<sub>2</sub>H<sub>4</sub> and C<sub>2</sub>H<sub>6</sub>, which are convoluted with the larger signals from CO and CH<sub>2</sub>O respectively. Heavier mass products such as HCOOH are also detected, but in very small quantities. Methanol fragments (masses 31, 32, and 15, and a portion of the mass 29 signal) start at a high initial, or “prompt,” signal, and then rapidly decay as methanol is consumed. Fragments of methanol byproducts such as H<sub>2</sub>CO and C<sub>2</sub>H<sub>6</sub> (masses 2, 29, and 30) also decrease with time, but the decrease is less rapid as additional byproducts are generated by the consumption of methanol. In contrast, the production rates of H<sub>2</sub>O, CO, C<sub>2</sub>H<sub>4</sub>, and CO<sub>2</sub> (masses 18, 28, and 44) increase with radiation exposure. These signals do not increase when pure water is irradiated, and are not due to changing background levels of these molecules in the experimental chamber, but to the formation of these species in the

methanol film. Their increase with respect to time is unsurprising given the additional steps required to generate these products compared to  $\text{CH}_3$  or  $\text{H}_2\text{CO}$ . Reducing the electron flux (from  $5\mu\text{A}$  to  $2\mu\text{A}$ ) does not change these general trends, although they become less pronounced and overall signal intensity decreases (Figures 2.4 and 2.5). Similar effects are seen when the electron energy is reduced from 100 eV to 20 eV (Figure 2.6).

As in unprocessed methanol films, the major TPD peak in processed films occurs at  $\sim 170\text{K}$ . Methanol cracking fragments 15, 29, 31, and 32 dominate this peak, consistent with the desorption of the methanol multilayer and byproducts such as  $\text{CH}_2\text{O}$  (Figure 2.7). However, several additional peaks at temperatures ranging from  $\sim 110$  to  $\sim 200\text{ K}$  are also present.  $\text{CH}_4$  and  $\text{CH}_3\text{OCH}_3$  (dimethyl ether) are observed desorbing in a two-peak system at  $\sim 109$  and  $\sim 128\text{ K}$  after irradiation using 20eV electrons at  $2\mu\text{A}$  (Figure 2.7A). Small, minor peaks are also observed at higher temperatures for masses 27, 28, 29, and 30, indicating the presence of  $\text{H}_2\text{CO}$  at  $\sim 550\text{ K}$  and  $\text{C}_2\text{H}_4$  at  $\sim 650\text{ K}$ .

Increasing the total energy dosed, as in Figure 2.8, which used 100 eV electrons at  $5\mu\text{A}$ , leads to both larger signals and additional product species. As with lower energy doses, the main peak remains at  $\sim 170\text{ K}$  and is dominated by the same species, but is smaller in relative size when compared to other peaks than it is in the lower-energy case. Besides the main peak at 170K, additional peaks are present at 125, 139, 153, 180, and 232K. The two-peak system found at 125 and 139 K (Figure 2.8A) is similar in peak structure to the one found at 109 and 128 K in the low-energy experiment (Figure 2.7A), but is shifted to higher temperatures and results from a more complex origin. The peak

found at 125 K is due to desorbing dimethyl ether, while the peak at 139K is due to CH<sub>4</sub>, CO, CO<sub>2</sub>, CH<sub>3</sub>OOCH<sub>3</sub>, and a combination of ethanol, HCOOH, CH<sub>3</sub>OCH<sub>3</sub>, C<sub>2</sub>H<sub>6</sub>, and (CH<sub>2</sub>OH)<sub>2</sub> that cannot be determined from the TPD data. Of these, ethanol fits the data while only requiring one species to form and so is the presumptive source. However, combinations of C<sub>2</sub>H<sub>6</sub> + (CH<sub>2</sub>OH)<sub>2</sub> + HCOOH and C<sub>2</sub>H<sub>6</sub> + (CH<sub>2</sub>OH)<sub>2</sub> + CH<sub>3</sub>OCH<sub>3</sub> also fit the data, about as well as ethanol alone. Measuring additional TPD masses could help resolve the source(s), but the signals from the additional masses (12, 13, 25, 26, and 62) are expected to be quite small, so a spectroscopic method would be preferred. The peak at 153 K is due to desorbing ethylene glycol, while the peaks at 180, 232, and 480 K are due to water (for comparison, a thick water film has a distinct shoulder at 180K and peaks at ~193 K). Additional very small peaks are present at 585 and 610 K, possibly artifacts.

#### *Temperature effects in irradiated pure methanol films*

Increasing the ESD temperature  $T_{\text{irr}}$  of 30 ML CH<sub>3</sub>OH from 25 to 50 K made no significant difference in the methanol signal during ESD. However, the temperature increase led to a total increase in signal from methanol products (masses 2, 15, and 28) during the ESD, primarily in the prompt region. Saturation levels were similar except in the case of 2 amu, where saturation at 50 K is difficult to determine. The final data point for 2amu at 50 K was roughly double that at 25K. A further increase to 80K led to a very large increase in the 15, 29, and 32 amu signals, especially in the prompt region. H<sub>2</sub> and CO production at 80 K is at least double that at 50 K. These results—that increasing  $T_{\text{irr}}$



leads to increased signal intensities—are consistent with increases in the H<sub>2</sub>O, H<sub>2</sub>, and O<sub>2</sub> signals observed in ESDs of pure water films with increasing T<sub>irr</sub>.

No difference was observed in the location of subsequent TPD peaks and only a small difference in the intensity of TPD peaks for the monitored masses (12,13,14,15,16,18 28, 29, 30, 31, 32, 33, 44, 45, and 46 amu) when the irradiation temperature was increased from 25 to 50 K. When the temperature is increased to 80 K, a number of changes appear, although the main peak at 170 K remains constant. These changes include a 7-9 K increase in the desorption temperature of most of the methanol products. A methane + CO<sub>2</sub> TPD peak at 130K (masses 12, 13, 14, 16, 44, 45, and 46 amu) shifts to 139 K when T<sub>irr</sub> is increased from 50 to 80K. The CO<sub>2</sub> peak resulting from irradiation at 80 K is also ~4 times larger than that from irradiation at 50K, while the corresponding peak at 170 K is about half the size it was at 50 K. A similar relative increase of the ~139K peak relative to the 170K peak is observed in methane desorption, but is not as pronounced as in the 44 amu channel. The 45 and 46 amu signals show a similar shift, and a small concomitant increase, from 130 to 139 K, but the peaks at 170 K did not change in intensity. A second H<sub>2</sub>O TPD peak (18 amu) appears at 178K when T<sub>irr</sub> is increased to 80 K (Figure 2.10). At T<sub>irr</sub> = 50 K, there is only one major peak for water, occurring at 170K. This new peak at 178 K indicates increased water production from methanol irradiated at 80 K and is comparable to water desorption temperatures from bare TiO<sub>2</sub> (110). For H<sub>2</sub>CO (masses 15, 29, and 30), a TPD peak at 110 K disappears when T<sub>irr</sub> is raised from 50 to 80 K (Figure 2.9); it may be converted to other products. Another H<sub>2</sub>CO peak at 132 K shifts to 139 K (15, 28, 29, and 30 amu). Methanol

fragment  $\text{CH}_2$  (mass 14) shows the disappearance of a small peak at 525 K when  $T_{\text{irr}}$  is increased to 80 K. No major changes are observed in the TPD signal for mass 32 ( $\text{CH}_3\text{OH}$  and  $\text{O}_2$ ), although there is an increase in the high-temperature shoulder signal at  $\sim 200\text{-}250$  K, and none are observed for masses 31 or 33 (a major and minor methanol signal, respectively). These results suggest increased production of methanol products in the film during irradiation at higher temperatures, in agreement with the increased signals observed during ESD. However, the lack of major changes in the main methanol signals (31 and 32 amu) indicates that the products are still a relatively small component, forming in a film that remains mostly methanol. The 7-9 K increase in desorption temperatures of the methanol products observed after irradiation at 80 K may be the result of several processes. The products may form at or diffuse to greater depths in the methanol film (further from the vacuum interface), or may be better trapped by accelerated electron-induced annealing at higher irradiation temperatures.

#### *ESD products in layered methanol/water films*

##### *Capped films*

In capped films, major methanol ESD products  $\text{H}_2$ ,  $\text{CH}_3\text{OH}$ ,  $\text{CH}_2\text{O}$ ,  $\text{CO}$ , and  $\text{CO}_2$  increased as expected with increasing methanol dose, as shown in Figure 2.13 for  $\text{CO}$ , while the  $\text{H}_2\text{O}$  and  $\text{O}_2$  signals, resulting from water, decreased. Thorough discussions of  $\text{H}_2$ ,  $\text{O}_2$ , and  $\text{CH}_3\text{OH}$  products, and the processes affecting them, are included in Chapters 3 and 4.

### *Sandwich films*

As increasing quantities of water are deposited atop methanol, the signals from methanol and its major products, CO and CH<sub>2</sub>O, decrease. This decrease is only noticeable at 2 or more capping layers of water; a single layer appears to make no difference in the ESD signal, even at the earliest times when mixing is minimized and capping water quantity is maximized. These signals all reach their minimum when the capping water layer is greater than 20 ML thick, and show an exponential decay in total signal with increasing water dose. Only one notable difference appears between the expected signals based on pure methanol ESDs and signals from capped films: the CH<sub>2</sub>O signal is as big as, or bigger than, the CH<sub>3</sub>OH signal at each of these buried depths. This result may be due to reactions at the water interface, or simply due to retaining greater quantities of methanol for the longer periods needed to generate H<sub>2</sub>CO.

### *TPD products after irradiation in layered methanol/water films*

#### *Capped films*

TPDs from non-irradiated films of 1 ML CH<sub>3</sub>OH on 80 ML H<sub>2</sub>O (Figure 2.12) show a consistent peak structure common to all of the methanol-dominated channels (15, 29, 30, 31, and 32amu). Onset of methanol desorption occurs at 140K, approximately the same temperature as it does from pure methanol films. The peak structure consists of a major peak at 195 K with two low temperature shoulders resulting from peaks at 161 and 179K. The major peak at 195 K coincides with the major water desorption peak, has a

similar structure (Figure 2.12C), and is likely due to entrained methanol during water desorption. The shoulder located at  $\sim 179$  K coincides with a similar shoulder observed in processed pure ASW films. It is also coincident with the major methanol peak from irradiated 1 ML  $\text{CH}_3\text{OH}/80$  ML  $\text{H}_2\text{O}$  films, suggesting that its origins may be methanol in contact with ASW. The origin of the shoulder at 160 K is less clear. As it is not present in irradiated films of 1 and 4 ML  $\text{CH}_3\text{OH}/80$  ML  $\text{H}_2\text{O}$ , in which less than 1 ML  $\text{CH}_3\text{OH}$  are calculated to remain after sputtering, but is present in irradiated films of 10 ML  $\text{CH}_3\text{OH}/80$  ML  $\text{H}_2\text{O}$ , we assign it to the desorption of a methanol multilayer from the water surface. This temperature is  $\sim 10$  K higher than Henderson *et al.*'s observed first methanol multilayer desorption temperature from bare  $\text{TiO}_2$  (110), and  $\sim 5$  K lower than the desorption temperature for H-bonded  $\text{CH}_3\text{OH}$  on bare  $\text{TiO}_2$  (110).<sup>3</sup> However, it is lower than our observed peak desorption temperature for processed 30 ML methanol films, and has a similar onset temperature, as would be expected for a partial multilayer.

These channels also show a small broad peak at  $\sim 340$  K in the unprocessed film. Although methanol on bare  $\text{TiO}_2(110)$  recombinatively desorbs at  $\sim 350$  K,<sup>9</sup> the thick water layer is expected to prevent the methanol from contacting the  $\text{TiO}_2$  surface. The peak is not due to  $\text{CH}_2\text{O}$ ,  $\text{O}_2$ , or another species, as it shifts in all methanol channels to  $\sim 316$  K after processing. The same data indicate that it is not an artifact of deposition, as the small quantity of methanol that might deposit on the bare  $\text{TiO}_2$  would be removed or converted to  $\text{CH}_2\text{O}$  by electron sputtering. In irradiated films of 4, 10, and 30 monolayers of methanol on ASW, this peak becomes difficult to isolate as it appears convoluted with the tail of the major desorption signal, becoming a high-temperature shoulder. However,

it is present as a high-temperature shoulder in the same channels (15, 29, 30, 31, and 32amu) but not higher mass channels (e.g., 44 or 46 amu), which suggests that it is due to methanol desorption and not the desorption of a newly formed heavier species, such as formic acid or ethanol.

The signal from 1 ML  $\text{CH}_3\text{OH}$  on 80 ML  $\text{H}_2\text{O}$  is reduced by  $\sim 93\%$  after irradiation (Figure 2.12A), indicating that nearly all of the methanol is removed electron-induced desorption. The remainder is likely protected by mixing to some degree with the water layer, as ESDs indicate that  $\sim 3$  ML of  $\text{CH}_3\text{OH}$  are sputtered during irradiation under these conditions. (For comparison,  $\sim 2.3$  ML of  $\text{H}_2\text{O}$  are sputtered from a pure water film under the same conditions.) This degree of sputtering is also observed in processed films of 4 ML  $\text{CH}_3\text{OH}$  on ASW, where integration of the 31amu channel shows that less than a monolayer of methanol desorbs during the TPD. TPDs of mass channels 15, 31, and 32 show the same structure, with two peaks located at  $\sim 180$  and 193 K. The peak at 193 K is of similar intensity as peaks observed during desorption of pure water films and is due to background/residual methanol desorption during desorption of the water peak. The peak at 180K is the main peak, due to methanol desorption.

Note that the 32 amu signal is a special case, as it is the mass channel for both methanol and molecular oxygen generated during the ESD. When pure water is irradiated, this channel shows three peaks—the background water desorption peak at 195K, and two additional peaks of comparable intensity at 180 and 170 K (Figure 2.12B). However, due to the different peak structure and earlier onset of  $\text{O}_2$  desorbing from water, it is plain that no or little  $\text{O}_2$  is desorbing from the processed film of 1 ML

CH<sub>3</sub>OH/ASW. This result is consistent with our other results (Chapter 4) showing that the addition of methanol suppresses the production of O<sub>2</sub> at the water/vacuum interface.

Other products include CH<sub>2</sub>O, which was detected desorbing in a broad peak centered at ~265K that overlaps with methanol desorption observed at 315K. We note the appearance of another broad peak, centered at ~625K, consistent with the appearance of small quantities of ethane. The 16 amu channel was also monitored, and in the unprocessed film largely overlaps with O desorption from processed and unprocessed water films, peaking at ~194K (Figure 2.13). However, in the processed 1 ML CH<sub>3</sub>OH/ASW film, a low-temperature shoulder appears, indicating an additional source at ~187 K. While most of the 16 amu signal bears the characteristics of O desorbing from H<sub>2</sub>O, a small fraction appears to be sourced in methanol. This contribution to the 16 amu signal is not due to CH<sub>4</sub>, as it occurs at a much higher temperature than observed from a pure methanol film, and is many times larger than the 15amu signal. Therefore, this is additional atomic O resulting either from the irradiated methanol, or from water at the methanol/water interface.

Similar films of 4, 10, and 30 ML CH<sub>3</sub>OH were deposited on 80 ML ASW and irradiated at 80K using 100 eV electrons at 5  $\mu$ A. In all cases, the main water peak remains located at 195 K, and small but significant quantities of methanol are commingled with the water desorption at each coverage (Figure 2.14). At 4 ML coverage, the main methanol desorption peak is located at 170K (Figure 2.14A). As the methanol dose increases, this peak first grows (Figure 2.14B) and then shifts to 180K (Figure 2.13C). As the methanol dose increases, water begins to co-desorb with the methanol, as

observed in Figure 2.14C. The multilayer peak assigned to 160 K also grows and shifts to higher temperatures with increasing methanol dose, ending at ~168 K for a 30 ML CH<sub>3</sub>OH dose. CO and CO<sub>2</sub> desorb with the water and main methanol peaks at all coverages. Low levels of H<sub>2</sub>CO are again observed in a broad peak ranging from ~220 to ~320K (Figure 2.15A) at 4 and 10 ML CH<sub>3</sub>OH coverages, but a large tail prevents observation at the 30 ML CH<sub>3</sub>OH dose.

At 10 ML CH<sub>3</sub>OH coverage, a new peak appears at 187K (Figures 2.14B and 2.15B). This peak is particularly noticeable in the 15, 16, 28, 44, 45, and 46 amu channels, but also increases the signal in the 29 and 31 amu channels so that the “valley” between the 170 and 195 K peaks is higher than would be expected for two Gaussian or exponential curves. The cracking patterns of these 44-46 amu channels are consistent with the desorption of small amounts of dimethyl ether and/or ethanol. The remaining channels indicate additional methanol; the location suggests that this methanol may be well mixed with water. This peak disappears or combines with other peaks at the 30 ML dose, as would be expected if only limited quantities of methanol near the methanol/ASW interface are radiatively mixed. Another new peak is present at 125 K in both the 10 and 30 ML CH<sub>3</sub>OH covered films (Figures 2.15B and 2.15C). The cracking patterns for 44, 45, and 46 amu present at 125 K are similar to those described above, again suggesting dimethyl ether or ethanol; as dimethyl ether is observed desorbing at this temperature from an irradiated pure methanol film, we assign it to this peak. Finally, at the 30 ML CH<sub>3</sub>OH coverage, a peak at 158K, again with a similar cracking pattern, is present (Figure 2.15C).

### *Sandwich films*

Films of  $n$  ML  $\text{H}_2\text{O}$  on 1 ML  $\text{CH}_3\text{OH}$  on 80- $n$  ML  $\text{H}_2\text{O}$  on  $\text{TiO}_2$  were studied as well. The upper layers of these films were grown at 25 K to minimize surfaction, and irradiated at 25 K using 100eV electrons at  $\sim 2\mu\text{A}$  current. These films were then heated at a rate of 2 K/s to gather TPD data on several species. Figure 2.16 shows the TPD data for mass 31, representing methanol desorption. Multiple peaks are present, including the main water desorption peak at  $\sim 193$  K and an analogue to the main methanol desorption peak at 165-170K. As the methanol is placed deeper in the film, the entrained methanol peak at  $\sim 195$ K grows. Increasing burial depths of methanol decrease the quantity that is removed by electron sputtering during ESD, leading to a growing total signal.

The evolution of the main methanol peak at 165-170 K is particularly interesting, although somewhat difficult to interpret. For coverages of 0-5 capping ML  $\text{H}_2\text{O}$  (that is, thin “upper slices”), the leading edge of the peak does not shift from its onset temperature of  $\sim 150$ K. This indication that methanol is still near the vacuum interface is consistent with the expectation that  $\sim 2.3$  ML of  $\text{H}_2\text{O}$  are removed during the ESD. As the capping water layer thickness  $n$  increases, the onset of desorption is delayed, slightly at  $n = 10$  ML, and by  $\sim 15$  K at  $n = 20$  ML, whereupon it rises sharply. Thicker capping layers of 30 ML  $\text{H}_2\text{O}$  do not further increase this onset temperature of  $\sim 165$  K, indicating that the appearance of methanol is not the result of simple diffusion through the thicker capping layers. The sharp rise is reminiscent of species that are released by crystallization processes, which may occur in the 10-20 ML of  $\text{H}_2\text{O}$  directly atop the methanol. The



overall result is that the main methanol peak at 165K grows in intensity with increasing capping water layer thickness to 10 ML, but then is quickly suppressed and shifted at thicknesses greater than 20 ML. Related methanol signals (15, 28, 29, 30, and 32 amu) are similar in this range, indicating that nearly all of the products desorbing at 165-170 K are due to methanol. Small quantities of CH<sub>2</sub>O are detected at ~270 K, decreasing slightly in temperature with increasing capping water layer thickness, and peaking in intensity at 20 ML capping water layer thickness. There is also a small O<sub>2</sub> signal at 550 K that increases as the capping water layer grows. Extremely small peaks corresponding to heavier products are detected at 90 K (up to capping water layer thicknesses of 10 ML), 130K (up to thicknesses of 5 ML), and 160 K (thicknesses greater than or equal to 10 ML). These peaks also shift to higher temperatures with increasing depths.

### *Surface Area Measurements*

The surface area of various methanol/water layered films was measured using Kr. The films were prepared at 80K, and Kr was dosed at less than 30 K. TPDs monitoring Kr were then taken using a ramp rate of 2 K/s. The TPDs are shown in Figure 2.17. The desorption onset of Kr begins and peaks at approximately the same temperatures (25 and 33K respectively) regardless of the amount of water or methanol at the surface. The clearest trend is observed at temperatures greater than ~37K, where increasing surface concentration of methanol corresponds to completion of Kr desorption at lower temperatures, suggesting that the water-dominated surface may be slightly rougher. Annealing the films made little difference in the structure or intensity of the Kr

desorption peak. Performing similar experiments using  $\text{CO}_2$  as the probe molecule yielded similar results. Sandwich films of  $n$  ML  $\text{H}_2\text{O}/1$  ML  $\text{CH}_3\text{OH}/80-n$  ML  $\text{H}_2\text{O}/\text{TiO}_2$  (110) were grown at 80 K and then dosed with 120 torr\*s of  $\text{CO}_2$  at 21 K. When grown in this manner, surfaction will cause decreasing amounts of methanol to appear at the surface as  $n$  increases. The results, shown in Figure 2.18, indicate that as more water is present at the surface, more total  $\text{CO}_2$  is adsorbed, and remains adsorbed to higher temperatures. While this result is consistent with the Kr desorption results, we must be cautious in drawing any further conclusions, as the  $\text{CO}_2$  may H-bond more effectively and in larger numbers with a water-dominated surface, and that may be the cause of its higher desorption temperature and intensity rather than surface roughness.

## Conclusions and Future Work

Methanol surfaction is minimized for deposition temperatures less than or equal to 50 K. At deposition temperatures of 80 K, the methanol is mobile enough to move to the surface. However, this mobility exists only during deposition; heating a film deposited at 25 K to 80 K does not lead to an increased concentration of methanol at the surface. Products other than methanol appear only after radiative processing. From a pure methanol film, these include  $\text{H}_2$ ,  $\text{CH}_2\text{O}$ ,  $\text{CO}$ ,  $\text{CO}_2$ ,  $\text{H}_2\text{O}$ ,  $\text{CH}_4$ ,  $\text{C}_2\text{H}_6$ ,  $\text{C}_2\text{H}_4$ , and heavier species such as  $\text{HCOOH}$ ,  $\text{CH}_3\text{OCH}_3$ ,  $\text{CH}_3\text{OOCH}_3$ ,  $\text{CH}_3\text{CH}_2\text{OH}$ , and  $(\text{CH}_2\text{OH})_2$ . The variety and quantity of products increases as the total energy deposited increases. From a mixed methanol/water film, fewer products are seen, with  $\text{CH}_3\text{OH}$  and  $\text{H}_2\text{O}$  dominating TPDs. Observed products from these films included  $\text{H}_2$ ,  $\text{O}$ ,  $\text{CH}_2\text{O}$ ,  $\text{C}_2\text{H}_6$ ,  $\text{CO}$ ,  $\text{CO}_2$ ,

CH<sub>3</sub>CH<sub>2</sub>OH, CH<sub>3</sub>OCH<sub>3</sub>, and O<sub>2</sub>. TPDs indicate significant mixing in the layered films due to radiative processing during ESD. Surface area measurements suggest that water-dominated surfaces are marginally rougher than methanol-dominated surfaces. Confirmation of these products by spectroscopic methods (e.g., infrared spectroscopy), improved surface area measurements, and the effects of extended irradiation exposures will be included in future work.

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## **Chapter 3: The effect of creating chemical interfaces in amorphous solid water/methanol films on electron-stimulated H<sub>2</sub> production**

### **Introduction**

In a broad spectrum of research fields, including biology, energy research, and astrophysics, the mechanisms of non-thermal reactions in condensed water phases are of critical importance. Reactions occurring at interfaces, such as water solvating a DNA molecule or corrosion reactions, are of special importance. However, studying these reactions using liquid water, where the interface constantly changes, is difficult. To understand the role of the interface and study heterogeneously located reactions, amorphous solid water (ASW) serves as a model. Transport processes are slower in ASW, easing determination of the processes involving interfacial molecules and the extent of the interface.

Previous work with water showed that as high-energy radiation passes through water, lower-energy secondary electrons, of energy less than 100 eV, form in large quantities along the ray's path.<sup>1</sup> These electrons are the primary drivers of subsequent reactions, including the production of H<sub>2</sub>, O<sub>2</sub>, H, O, and H<sub>2</sub>O<sub>2</sub>.<sup>2</sup> H<sub>2</sub> production is of particular interest, as excessive H<sub>2</sub> production in nuclear waste tanks poses increased hazards associated with waste storage and environmental clean-up efforts.<sup>1</sup> H<sub>2</sub> creation and destruction, especially on ice-coated grains, is also of critical interest to astrophysicists, who use it to determine stars' and clouds' origins and evolution. Finally, cheap H<sub>2</sub> production is of the utmost importance to all who would like to decrease

reliance on fossil fuels by switching to a hydrogen economy. To model the effects of interfaces with organic compounds on non-thermal H<sub>2</sub> production from water, we use 100 eV electrons to study reactions occurring in layered methanol/ASW systems.

## **Previous Work**

Petrik and Kimmel<sup>3</sup> found that hydrogen is formed in ASW at the films' interfaces with the supporting Pt (111) substrate and the vacuum, although the energy to drive these reactions is absorbed in the bulk of the film. The total H<sub>2</sub> yield peaked in films of about 25 ML ASW, decreasing with increasing thickness until ~70 ML, when it reached a constant level that was ~30% of the peak value. The contributions from each interface were observed to appear at different times after the electron beam was turned on, allowing the yield from each interface to be determined. At coverages greater than ~60 ML, virtually all of the H<sub>2</sub> was generated at the vacuum interface, and the Pt interfacial contribution was negligible. However, at coverages less than ~50 ML, the contribution from Pt was significant; isotopic labeling showed that the Pt interface was responsible for about 80 % of H<sub>2</sub> produced during the peak production level at ~25 ML thickness. Isotope labeling also determined that almost no H<sub>2</sub> was produced in the film region greater than ~3 ML from the substrate and more than ~10 ML from the vacuum interface. While no molecular hydrogen was produced in this “dead” region and it did not contribute any reactive species such as OH or H, energy was absorbed in this region and transferred to the interfaces. Evidence of this energy transfer lies in D<sub>2</sub> produced at the

substrate interface in 30-50 ML thick films, as Laverne and Pimblott found the penetration depth of 100 eV electrons in water not to exceed 30 ML.<sup>4</sup>

To avoid complications of H<sub>2</sub> production from the substrate interface, we studied thick (80 ML) films, allowing us to focus on the water/vacuum, methanol/vacuum, and water/methanol interfaces. At these thicknesses, contributions from the water/substrate interface are negligible, while the water/vacuum interface contributions are nearly constant. By imposing these experimental limits to eliminate contributions from the TiO<sub>2</sub> substrate, we focus on the methanol-induced changes to the film-vacuum interface. We also examine the effect of creating interior interfaces in the “dead” region by placing layers of methanol in this portion of the ASW film in a sandwich structure (described in detail later). If H<sub>2</sub> is produced at depths greater than ~10 ML from the vacuum interface, then we know that the addition of methanol forms a separate interface similar in some respects to the Pt interface used previously.

## **Methods**

### *Chamber Set Up*

Experiments were done in an ultrahigh vacuum (UHV) chamber, equipped with a closed cycle helium cryostat, low-energy electron gun, quadrupole mass spectrometer, and a molecular beam line. Median base pressure for the system was ~1.1E-10 torr and base sample temperature was ~22K. Films were grown on a clean TiO<sub>2</sub> (110) crystal approximately 10 mm in diameter and 0.5mm thick. The crystal was cleaned by neon ion

sputtering, followed by annealing at 850 K in vacuum, to yield a consistent TiO<sub>2</sub> (111) surface. The sample was resistively heated, and the temperature measured by a type K thermocouple spot-welded to the back of the sample.

### *Deposition and Growth Conditions*

High-Pressure Liquid Chromatography-grade CH<sub>3</sub>OH, distilled, deionized H<sub>2</sub>O, and their isotopologues (CD<sub>3</sub>OH, CD<sub>3</sub>OD, D<sub>2</sub>O, and H<sub>2</sub><sup>18</sup>O) were freeze-pump-thawed prior to use to remove dissolved gases and to ensure purity. All films were dosed at temperatures colder than 100 K by molecular beams at normal incidence to the sample, creating a dense non-porous film.<sup>5, 6</sup> The films did not cover the entire substrate surface, but were centered on the TiO<sub>2</sub>. Water coverage calibration was based on previous calculations using a coverage of  $1 \times 10^{15}$  molecules\*cm<sup>-2</sup>.<sup>7</sup> Direct measurements of methanol saturation coverage on ASW for calibration purposes are difficult due to mixing processes during desorption. Instead, methanol coverage was calibrated based on the integration of the first monolayer peak in the temperature programmed desorption spectra from a *bare* TiO<sub>2</sub> crystal. Based on the relative coverage of methanol on bare TiO<sub>2</sub> (110),  $3.2 \times 10^{14}$  molecules cm<sup>-2</sup>,<sup>8</sup> one monolayer of methanol on ASW was defined to be roughly three times the exposure needed for one monolayer on methanol on TiO<sub>2</sub>. This definition of a CH<sub>3</sub>OH monolayer on ASW has a comparable coverage to that of a water monolayer on ASW,  $1 \times 10^{15}$  molecules\*cm<sup>-2</sup>. The same exposure definition (in torr s) was used for each of the isotopically labeled varieties of methanol used, CH<sub>3</sub>OH, CD<sub>3</sub>OH, and CD<sub>3</sub>OD, although the calibration was performed only for CH<sub>3</sub>OH. We must



emphasize that our monolayer definition is strictly to make comparing the effects of a monolayer of methanol with those of a water monolayer easier on a per-molecule basis, and is not based on any measurement of the actual coverage of CH<sub>3</sub>OH on ASW. Estimates of CH<sub>3</sub>OH coverage on crystalline ice surfaces (none are available for ASW surfaces) range in value, but are comparable to its coverage on TiO<sub>2</sub> (110).<sup>9-11</sup>

The structured methanol/water films in our experiments often required different growth temperatures for different layers. Underlying foundational water layers (in contact with the TiO<sub>2</sub> surface) were grown at 80K, conditions known to produce consistently dense and smooth ASW surfaces.<sup>5, 6</sup> Surfaction, or the phase separation and resulting movement of methanol to the vacuum interface, was observed during deposition of upper water layers in “sandwich” experiments. In these experiments, layers of water are dosed atop methanol to isolate it from the vacuum interface, creating a layered film with a sandwich-like structure of water/methanol/water/TiO<sub>2</sub>. When the upper layers were deposited at 80K, the methanol promptly appeared on the surface in subsequent electron stimulated desorption (ESD) experiments. When the upper layers were dosed at 50K or less, it eliminated the prompt appearance of methanol from subsequent ESD experiments, even if the film was heated to 80 K from the lower dose temperature. Heating gently to 80K and irradiating had no effect on the ESD signal structure compared to irradiation at 50 or 25K. (For details, see Chapter 2.) To eliminate the effects of such surfaction, all upper films were grown at 80K or less, depending on their position in the final film structure. Capping water layers, or layers dosed atop methanol, were grown at 50K or less to minimize the surfactant properties of methanol. Methanol layers were grown at

80K or less if their final position was located at the vacuum interface (i.e., an “open-faced” sandwich structure, also referred to in this paper as a methanol-capped film), and at 50K or less if in the interior (i.e., in a “sandwich” experiment).

### *Radiation Conditions*

To eliminate the effects of thermal mixing and focus on radiative mixing and reaction products, all irradiation was performed at 80 K or colder; changes in the ESD temperature do not change the signal structure, although it may affect the signal intensity (See Chapter 2). Capped films were irradiated at 80 K, when the surfactant properties of methanol could be neglected. Sandwich films were irradiated at their growth temperature unless otherwise noted. The electron beam was incident at 35° to the sample normal. The films were irradiated with 100 eV electrons at a current of ~2  $\mu$ A for 100 scan cycles (for a total exposure of ~97 s) unless otherwise noted. A scan-averaging mode was used that samples the signal repeatedly within a single cycle, rastering across the film sample to generate “pixels.” The pixels were then averaged to generate a single data point per cycle with a very high signal-to-noise ratio, as described in detail in Petrik *et al.* <sup>7</sup>

## **Results and Discussion**

### *Relative sensitivity of $H_2$ and $D_2$ in the QMS*

The QMS showed different sensitivity to  $H_2$  than to  $D_2$ . To determine the ratio of these sensitivities,  $H_2$  and  $D_2$  gases were leaked in at various pressures and the signal measured. After correcting for the ionization sensitivity of the ion gauge used to measure

the leaked gas pressure (Stanford Research, error ~10%), we found that the quadrupole was roughly twice (2.04 times) as sensitive to H<sub>2</sub> detection than D<sub>2</sub> detection. That is, for the same gas pressure, the H<sub>2</sub> signal appears twice as large as the D<sub>2</sub> signal. To determine mass balance from water and methanol films, we set the quadrupole sensitivity to HD to be the average of the H<sub>2</sub> and D<sub>2</sub> sensitivities, or 1.52. Doing so allows us to compare the hydrogen produced from an H<sub>2</sub>O film with that from a D<sub>2</sub>O film by weighting the HD and D<sub>2</sub> signals appropriately. For example, to determine the total hydrogen signal from a D<sub>2</sub>O film, we measured the H<sub>2</sub> (background hydrogen), HD (primarily desorbed D atoms reacting with background H), and D<sub>2</sub> (molecularly formed in D<sub>2</sub>O film) signals. If we perform a weighted sum of these signals such that

$$\text{total hydrogen} = \text{H}_2 \text{ signal} + 1.52 (\text{HD signal}) + 2.04 (\text{D}_2 \text{ signal}),$$

we find that the total hydrogen signal from D<sub>2</sub>O is nearly identical (within typical variation in signal during ESD) in intensity and shape to the total hydrogen signal from H<sub>2</sub>O (Figure 3.1). We will use these weightings to determine hydrogen production from various layers of water/methanol films, and in each figure with multiple isotopologues, we have weighted the HD and D<sub>2</sub> signals accordingly. However, we use D<sub>2</sub> as our signal of choice, as it has a single source, unlike the H<sub>2</sub> and HD signals, which can be affected by background levels of hydrogen and are observed during ESD of bare TiO<sub>2</sub>.

*Production of H<sub>2</sub>, HD, and D<sub>2</sub> from pure water and pure methanol films*

In pure water, the hydrogen signal initially spikes and then returns to a nearly constant rate (Figure 3.1). As determined previously,<sup>3</sup> the hydrogen signal in water arises from H<sub>2</sub> produced at the water/vacuum interface in films thicker than 60 ML, and it is this interface that is responsible for the prompt signal.

Methanol often behaves similarly to H<sub>2</sub>O, and it is expected that the methanol/vacuum interface also plays an important role in H<sub>2</sub> production from pure methanol. Figures 3.2, 3.3, and 3.4 show the production of H<sub>2</sub>, HD, and D<sub>2</sub> from 30 ML CH<sub>3</sub>OH, 10 ML CD<sub>3</sub>OH, and 10 ML CD<sub>3</sub>OD respectively. Although these thinner layers of methanol may be affected by the TiO<sub>2</sub> interface, they should serve as an adequate point of comparison for later mixed methanol/water structures.

As in pure water, hydrogen production in thin pure methanol films promptly appears after the electron beam turns on. The H<sub>2</sub> signal from methanol quickly rises and then declines steadily when irradiated at warm temperatures (Figure 3.2 shows the results of irradiating the film at 50 K. Similar results are observed for temperatures greater than 50K). In contrast, hydrogen formation in CH<sub>3</sub>OH at 25 K increases slowly, and the large signal remaining after the electron beam is turned off indicates that a significant portion of the detected hydrogen must diffuse out of the methanol film, suggesting that the majority of H<sub>2</sub> formed at this temperature is not formed at the methanol/vacuum interface. It is unclear if the H<sub>2</sub> is forming in the bulk, or, as in water films of similar thickness, at the substrate. We focused on thick mixed films of water and methanol to simplify the number of interfaces, and so our primary concern is establishing that pure

methanol also generates a prompt  $H_2$  ( $D_2$ ) signal to determine the signal source in mixed films.

After accounting for the different sensitivity of the QMS to each isotopologue, the total signal intensity ( $H_2 + 1.52HD + 2.04D_2$ ) of  $CD_3OH$  is about 25% larger than the total signal intensity of  $CD_3OD$ , suggesting an isotope effect. By comparing the three signals, it is clear that substituting D for H ( $H_2 \rightarrow HD$ ,  $HD \rightarrow D_2$ ) leads to a decrease in the signal intensity by a factor of 0.68. This factor is likely the result of both reduced formation rates and reduced desorption rates of the heavier molecules.

Previous work suggests that at these electron energies, methanol contributes H primarily from its methyl group.<sup>12-14</sup> To determine the contribution of the methyl and alcoholic hydrogens to hydrogen production from methanol films, we compare the  $H_2$ , HD, and  $D_2$  signals. Examining the  $D_2$  signal from  $CD_3OH$  (Figure 3.3), which has a single source, we see that the contribution from methyl Ds reacting to form  $D_2$  is nearly constant over the radiation scan. The  $H_2$  signal from  $CD_3OH$ , which is the result of alcoholic hydrogens reacting with each other, or desorbing to react with adsorbed H on the chamber walls, is also nearly constant. However, the  $D_2$  signal from  $CD_3OD$ , resulting from three sources (two methyl Ds, two alcoholic Ds, or one methyl D and one alcoholic D) rapidly declines. We posit that the decrease observed is due to a reduction in the formation of  $D_2$  from one methyl D and one alcoholic D.

This hypothesis is reinforced when one examines the HD signals from  $CD_3OH$  and  $CD_3OD$ . HD from  $CD_3OD$ , which results from the desorption of D atoms that react with H adsorbed on the chamber walls, is a relatively small signal, and decreases slowly.

The HD from CD<sub>3</sub>OH is the result of both desorbing D atoms reacting with H present in the chamber, and D atoms reacting with alcoholic H atoms in the film. Its initial signal is roughly six times larger than the HD signal from CD<sub>3</sub>OD, an increase which must be due to methyl-alcoholic HD formation since fewer D atoms are available to desorb and react with chamber H. It also decreases quickly, like the additional D<sub>2</sub> signal from CD<sub>3</sub>OD that can be attributed to methyl-alcoholic D<sub>2</sub> formation. Addition of the three weighted signals for CD<sub>3</sub>OH and CD<sub>3</sub>OD yields two curves with the same shapes, showing that no major additional processes (e.g., hot D<sub>2</sub> reacting with H adsorbed to chamber walls to form HD) are occurring. Because the D<sub>2</sub> and H<sub>2</sub> signals from CD<sub>3</sub>OH are nearly constant, the decrease seen in D<sub>2</sub> from CD<sub>3</sub>OD is not from reactions of two methyl deuteriums or two alcoholic deuteriums, but from a decrease in the reaction rate of methyl deuterium with alcoholic deuterium. The mechanism responsible is unclear; if it were the result of consuming either the alcoholic or methyl D atoms, we would expect to see a decrease in the D<sub>2</sub> and H<sub>2</sub> signals from CD<sub>3</sub>OH.

*Production of H<sub>2</sub>, HD, and D<sub>2</sub> from layered water/methanol films: Capped films, a.k.a. “open-faced sandwiches”*

Because thick films of pure water and pure methanol both show a prompt hydrogen production signal, we cannot use different time scales to determine the kinetics of each species. Instead, we must focus on results from isotopic labeling. As shown in Table 3.1, H<sub>2</sub> and HD are more likely to have non-zero background levels or to be formed by desorbed atoms reacting with hydrogen present in the chamber. D<sub>2</sub> has no effective

background level and in many isotopic films has only one possible source, making it the signal of choice for determining the methanol- or water-based origins of hydrogen production.

The simplest layered water/methanol film is the capped film. A large quantity of water was deposited, typically 80 ML, to eliminate the effects of the water/substrate reactions. A thinner layer of methanol varying in thickness was grown atop the water, resulting in two interfaces: the methanol/vacuum interface, and the water/methanol interface.

Figure 3.5 shows the  $D_2$  signal from an isotopically labeled layered film of  $n$  ML  $CD_3OD$  on 80 ML  $H_2O$ . The  $D_2$  signal arises solely from the methanol portion of the film, showing an increase in total  $D_2$  as more  $CD_3OD$  is dosed. The signal rapidly rises as soon as the beam is turned on, and then continues to rise slightly before decreasing with time; the time of peak signal intensity increases as the  $CD_3OD$  dose increases, with the signal peaking about 10 seconds after the beam starts for the thickest dose, 5 ML  $CD_3OD$ . In this respect, the signal from  $n$  ML  $CD_3OD/80$  ML  $H_2O$  acts more like the thicker pure methanol films, as the shape of the  $D_2$  curve is comparable to the  $H_2$  curve from 30 ML  $CH_3OH$ . However, it is quite different from the  $D_2$  signal from 10 ML  $CD_3OD$  (Figure 3.4). While both curves show a prompt increase in the signal, that from 10 ML  $CD_3OD$  immediately begins to decrease. This difference in shape, and the similarity of the very thin capping layer signals to the thicker pure methanol film, suggests that the substrate may be affecting the signal in the 10 ML pure methanol films, but does not affect a thin film of methanol on a thick water base, as expected. The total

D<sub>2</sub> signal increases linearly with CD<sub>3</sub>OD thickness. This increase is observed over both short (3 s) and long (100 s) integration periods.

Figure 3.6 shows the D<sub>2</sub> signal from a labeled, layered film of n ML CH<sub>3</sub>OH on 80 ML D<sub>2</sub>O, irradiated at 50K. In this case, the D<sub>2</sub> signal arises solely from the water layers of the film, and allows us to determine how methanol acts as a barrier to D<sub>2</sub> formation and diffusion from the film. The addition of methanol, even in submonolayer quantities, suppresses the prompt formation of D<sub>2</sub> in the film associated with the water/vacuum interface. As more methanol is added, this effect becomes greater and lasts for longer periods. Integrating the D<sub>2</sub> signal over the first 3 seconds of irradiation to reflect this prompt D<sub>2</sub> formation shows that the D<sub>2</sub> signal decays exponentially with increasing CH<sub>3</sub>OH coverage, with a 1/e constant of 1.14 ML (1.56 ML at 80K, likely due to an increased CH<sub>3</sub>OH desorption rate). In comparison, the D<sub>2</sub> signal from pure water produced at the vacuum interface decays with a constant of 2.7 ML, suggesting that CH<sub>3</sub>OH effectively eliminates the water/vacuum interface at lower coverages. Integration over the 100 second irradiation cycle is more complicated. At low doses of methanol, the D<sub>2</sub> signal from water increases by up to 40% when irradiated at 50K, as a result of increased D<sub>2</sub> production at later times. This increase persists until about 0.6 ML of CH<sub>3</sub>OH are dosed, after which the total D<sub>2</sub> signal also decays exponentially, with a 1/e constant of 1.04 ML CH<sub>3</sub>OH. There appears to be some temperature dependence in this process. When the experiment is repeated at 80K, the increase over the 100s integration period is much smaller, persisting to only 0.2 ML, after which it decays with a 1/e constant of 2.28 ML.



While submonolayer coverages of  $\text{CH}_3\text{OH}$  decreased the prompt portion of the  $\text{D}_2$  signal, they also increased the long-term production of  $\text{D}_2$  in the upper layers (Figures 3.7 and 3.8) above that seen from a pure  $\text{D}_2\text{O}$  film. The mechanism for this increase is unclear, but as it is the result of later production, it may be due to a methanol/water/vacuum interface with an increased number of dangling bonds to localize excitations and to higher mobility. The post-irradiation  $\text{D}_2$  signal (after the beam is turned off) from these submonolayer coverages, which results from  $\text{D}_2$  diffusing out of the film, is higher than for the pure  $\text{D}_2\text{O}$  film. Surface roughening is another possibility, though unlikely; measurements of surface roughening of methanol/water films showed little difference (see Chapter 2).

Coverages greater than a monolayer suppress both early and late  $\text{D}_2$  production in the  $\text{D}_2\text{O}$  that recovers only as the capping methanol layer is sputtered away. A number of causes may lead to this suppression. First, the addition of the methanol layer moves the uppermost layers of water deeper into the film, where they receive lower levels of energy and are less likely to be excited. However, as this suppression occurs even when the water has been moved away from the vacuum interface by only a few monolayers, another mechanism is more probable. Second, the water/methanol interface may be less reactive, mimicking the behavior of a water/water interface in the bulk, where reactions do not occur. We will show later that this is also unlikely. Third, the methanol layer may act to trap the energetic electrons and/or the resulting excitations, therefore reacting at a higher rate than  $\text{D}_2\text{O}$ , explaining the disproportionately high quantities of  $\text{D}_2$  generated in the  $\text{CD}_3\text{OD}/\text{H}_2\text{O}$  film. Petrik and Kimmel showed that only the uppermost 10 layers

are involved in generating  $H_2$  from  $H_2O$  at the vacuum interface. For comparison,  $\sim 1.2$ - $1.3$  monolayers of  $CD_3OD$  at the vacuum interface generates the same quantity of  $D_2$  as a pure 80 ML  $D_2O$  film over the course of the radiation scan and during the prompt regime. Finally, it is possible that  $D_2$  is forming in the water layer or at the water/methanol interface and being physically trapped by multiple monolayers of  $CH_3OH$  and prevented from diffusing. However, this idea conflicts with the higher diffusion levels seen in films capped with submonolayers of  $CH_3OH$ .

To elucidate the nature of the water/methanol interface and determine if it may be more reactive, fully deuterated films of  $n$  ML  $CD_3OD/80$  ML  $D_2O$  were dosed and irradiated. In these films, the addition of methanol increased the  $D_2$  production (Figure 3.9), even at low coverages. This increase is greater than can be attributed to either methanol or water, in both the prompt and later time periods. For example, the addition of 0.6 ML  $CD_3OD$  to the  $D_2O$  surface led to an increase of roughly 0.1 units at each point during the full scan of the ESD (Figure 3.9), while the contribution from purely methanol peaks at only 0.05 units (Figure 3.5). Clearly, the methanol/water interface is responsible for some of the  $D_2$  production. To determine how much, the  $D_2$  signals from the labeled films  $CD_3OD/H_2O$  ( $D_2$  solely from methanol) and  $CH_3OH/D_2O$  ( $D_2$  solely from water) were subtracted from the  $D_2$  signals from the  $CD_3OD/D_2O$  films, with the difference attributed to  $D_2$  that is formed from both methanol and water. For ease in referring to these species, D from methanol is labeled here as “Dm” and D from water as “Dw.” This “interfacial” signal is shown for selected methanol doses in Figure 3.10. The small signal seen for the 0 ML methanol dose is due to variation in ESD signals between two pure

D<sub>2</sub>O films. We can see that the interfacial contribution is significantly larger than this variation signal, indicating that it is a real effect and not due to changes in the chamber conditions over the course of the experiments, such as increased background D levels due to repeated D<sub>2</sub>O dosing. The interfacial contribution rises promptly for submonolayer coverages, with the peak signal time increasing as the methanol dose is increased. The prompt signal seen with submonolayer coverages is consistent with Dm<sub>2</sub> and Dw<sub>2</sub> production from the methanol and water layers, which both contain rapid rises. The increasing delay in the time of peak signal for the interface is also consistent with the delays seen in Dw<sub>2</sub> production as the methanol layer thickens and the water/methanol interface moves away from the vacuum interface and receives less energy. The DmDw signal peaks at 1 ML CD<sub>3</sub>OD coverage, where there is the greatest interaction of water and methanol molecules, least distance to the vacuum interface and the desorbing surface, and a high electron flux. This prompt peak at 1 ML coverage occurs at both 50 and 80 K (Figure 3.11). If the integration range is expanded to include the full ESD, and any mixing effects, the peak occurs at ~2 ML methanol coverage at both temperatures, suggesting that the second monolayer of methanol is mixing and reacting as the first monolayer is sputtered away. It is possible that even greater coverages of methanol would show an interfacial peak if the ESD was extended to longer times to allow for greater mixing.

The interfacial signal calculated previously was used to determine the total D contribution from D<sub>2</sub>O, by adding the DmDw signal to twice the Dw<sub>2</sub> signal. The Dw contribution from capped methanol/water films was compared to the Dw signal from pure

D<sub>2</sub>O using two integration ranges, the first three seconds of irradiation (no mixing effects) and the full scan (~100 seconds, and affected by mixing). Although the peak Dw signal occurs at different coverages due to mixing during the 100s integration, in both cases the addition of small quantities of methanol increased the Dw contribution (Figure 3.12). At 80K, this increase compared to a pure D<sub>2</sub>O film was approximately 8% when mixing effects were minimal, and approximately 20% when they were considered. Larger increases were observed when the experiment was repeated at 50 K, with a 40% increase seen over the full, mixed scan integral (100s); however this may be due to the fact that the basis of comparison, a D<sub>2</sub>O film irradiated at 50K, has a smaller signal than when irradiated at 80K. The presence of methanol causes a greater number of deuterium atoms in D<sub>2</sub>O to react than would be seen in a pure D<sub>2</sub>O film. This result has broad implications, especially if it holds true at higher temperatures. If so, it could lead to another route to H<sub>2</sub> production for a future hydrogen economy, and may be a hazard in nuclear waste tanks where the presence of well-mixed organics exposed to radiation over long periods could lead to excess H<sub>2</sub>. Dw production is maximized when there is 0.5 ML methanol on the surface when using a 3 s integration period. At this point, the methanol/water interface is presumably half complete, allowing water to be at the surface and creating a methanol/water/vacuum interface. This complex interface allows both water and methanol to have a high number of dangling bonds exposed to many available electrons, excitons, and ions to drive the D<sub>2</sub> producing reactions. Water molecules may react at this interface through multiple reaction paths (water-water, water-vacuum, and water-methanol). At lower methanol coverages, only the water-water and water-vacuum

reactions are available, and at higher coverages only the water-methanol reactions. As the integration time increases and radiative mixing occurs, we see that the peak Dw signal shifts to higher coverages.

*Production of  $H_2$ , HD, and  $D_2$  from layered water/methanol films: Sandwich films*

Data from capped films suggests that the methanol/water interface promotes the formation of  $D_2$  in a manner similar to substrates such as Pt(111) and  $TiO_2(110)$ . To determine the nature of the buried methanol/water interface, the ability of methanol to act as a substrate, and the opacity of the methanol layer to excitons or electrons, we use sandwich structures.

While it is clear that the methanol/water interface is reactive, it is unclear if both sides of the interface are equally so. The “opacity” of the methanol layer is a consequence of its ability to reduce the  $D_2$  signal from the lower methanol/water interface, either by blocking the formation of  $D_2$  in buried layers or the diffusion of  $D_2$  from those layers to the vacuum surface. To determine this opacity and find if any detectable  $D_2$  was formed at the lower interface, 8 ML of  $D_2O$  were placed either above or below 6 ML of  $CH_3OH$  on an 80 ML  $H_2O$  base. These structures were then capped with varying amounts of  $H_2O$  to determine how much  $H_2O$ , alone or with the addition of  $CH_3OH$ , would reduce detectable  $D_2$  (Figure 3.13). Not surprisingly,  $D_2O$  at the vacuum interface had the highest initial  $D_2$  signal. Placing  $H_2O$  atop the  $D_2O$  decreased the prompt  $D_2$  signal and shifted peak signal intensity to later times as the  $D_2O$  layer was moved away from the vacuum interface and received fewer excitations. The addition of a water capping layer

reduced the prompt signal with a  $1/e$  constant of 5.6 ML, twice that in a pure water film [Note: this value integrated over 3 s; 2.7 ML value integrated over 17.2 s. Each used different amounts of  $D_2O$ , 8 ML vs. 2 ML.],<sup>3</sup> suggesting that the methanol interface beneath the  $D_2O$  may actually promote  $D_2$  production in the  $D_2O$  layer. This idea is supported by the increase in total  $D_2$  production that is observed when the  $H_2O$  capping layer is increased from 0 to 4 ML (Figures 3.13 and 3.14). In a pure water film, moving the  $D_2O$  layer away from the vacuum interface strictly decreases the total signal, as the more distant layer both receives less energy/excitations, and any excited  $D_2O$  must move to the reactive interface. Therefore, the 20% increase seen in  $D_2$  production of the 4 ML  $H_2O$ /8 ML  $D_2O$ /6 ML  $CH_3OH$  film compared to the 0 ML  $H_2O$ /8 ML  $D_2O$ /6 ML  $CH_3OH$  film indicates that the  $D_2O$ / $CH_3OH$  interface promotes  $D_2$  production. However, this total increase is due to increased  $D_2$  production at later times, suggesting that the  $D_2$  may form at the  $D_2O$ / $CH_3OH$  interface, and then diffuse to the surface. The lower signal seen at 0 ML  $H_2O$ / $D_2O$ / $CH_3OH$  may also be the result of most of the  $D_2$  reacting at the vacuum interface and a higher flux of desorbing D atoms from the interface, reducing the  $D_2O$  reservoir available to react at the  $CH_3OH$  interface. Future work using the direct measurements of desorbing  $D_2O$  and examining the HD signal from the system may help to resolve the observed increase.

If  $D_2O$  is placed beneath  $CH_3OH$ , the prompt  $D_2$  signal is completely quenched (Figure 3.13). As expected, no  $D_2$  forms at the vacuum interface. The appearance of the  $D_2$  signal is slowed in time by the presence of a  $CH_3OH$  capping layer, and when it does recover, remains small by comparison. The largest  $D_2$  signal observed, when 6 ML of

CH<sub>3</sub>OH and 0 ML of H<sub>2</sub>O capped the D<sub>2</sub>O, is comparable to 16-18 ML of H<sub>2</sub>O capping D<sub>2</sub>O. The addition of H<sub>2</sub>O to the 6 ML CH<sub>3</sub>OH capping layer serves to reduce the D<sub>2</sub> signal further, but not as strongly as the original 6 ML CH<sub>3</sub>OH. It appears that the majority of the D<sub>2</sub> signal reduction is caused the presence of the methanol layer, which either does not permit D<sub>2</sub> formed beneath it to diffuse to the vacuum surface, or effectively quenches D<sub>2</sub> formation reactions, perhaps by trapping excitons.

When 6 ML CH<sub>3</sub>OH are deposited between  $n$  and  $80-n$  ML of D<sub>2</sub>O at 50 K and then irradiated, we observe that the total D<sub>2</sub> signal has two components, prompt and late, as before (Figure 3.15). The prompt portion, reflecting D<sub>2</sub> produced at the water/vacuum interface, of the signal rapidly increases, with an early peak occurring within 10 seconds of turning on the electron beam. Early production of D<sub>2</sub> saturates once  $n = 10$ , as it does in pure water, suggesting that production of D<sub>2</sub> in this earliest regime occurs at the vacuum/water interface (Figure 3.16). As the upper water dose of  $n$  ML increases, the time of peak signal shifts to later ranges as D<sub>2</sub> products from greater depths increase. Notably, late-stage production of D<sub>2</sub> rises steadily as more water is deposited but peaks at  $n = 20$ , decreasing with greater capping layer thickness until  $n = 30$ , at which point late-stage D<sub>2</sub> production saturates and the signal is similar to that seen from a pure D<sub>2</sub>O film (e.g., Figure 3.6). This saturation at  $n \geq 30$  suggests that the D<sub>2</sub> produced in this region is due to reactions occurring within the first 30 layers of the surface, but not directly at the vacuum interface. The difference between late stage D<sub>2</sub> production at  $n = 20$  and  $n = 30$  suggests that when the methanol/water interface is in this region, it plays some role in D<sub>2</sub> production, in a manner similar to the role played by Pt(111) in thin

films of pure water. Future experiments will test this idea by examining  $D_2$  production from films of n ML  $H_2O$ /2 ML  $D_2O$ /18-N ML  $H_2O$ /6 ML  $CH_3OH$ /60 ML  $H_2O$ .

## Conclusions and Future Work

The addition of a methanol layer to an ASW film increases the total electron-driven hydrogen production during ESD. Part of this increase is due to contributions from the H-rich methanol, as similar to one capping monolayer of methanol can produce as much  $H_2$  as a thick pure water film. The increase is not solely due to contributions from methanol, however, as isotopic labeling showed that coverages of less than 0.6 ML methanol on ASW at the vacuum interface increase  $D_2$  production occurring strictly in the amorphous  $D_2O$  film (that is, both D atoms come from a water source). At these submonolayer coverages the production of  $D_2$  from ASW at the vacuum interface is initially reduced, while later  $D_2$  production is increased. This later increase (and overall) suggests that the methanol may disrupt the hydrogen-bonding network of the ASW as it is radiatively mixed and sputtered, creating more dangling bonds that can react.

Thicker capping layers of  $CH_3OH$  decrease the  $D_2$  formed exclusively in the labeled water film because the water layer is located deeper in the film, where it receives a lower electron flux. Isotopic labeling shows that as the methanol/water interface becomes more complete, more molecular hydrogen is formed at the interface. This  $H_2$  ( $D_2$ ) has two sources, with one atom coming from the methanol layer and one from the water layer. Increasing quantities of this interfacially produced hydrogen are observed with increasing methanol coverage until the prompt (unaffected by mixing or sputtering)



signal peaks at 1 ML, when the interface is complete, nearest the desorbing surface, and receiving the highest electron flux. Greater coverages of methanol do not increase the prompt interfacial signal, but do increase the signal at later times, when mixing effects become important. Radiatively driven mixing in the film effectively increases interfacial contact between methanol and ASW, as more layers of ASW are penetrated by a methanol molecule that can disrupt its H-bonding network. The addition of methanol in these films, while decreasing the  $H_2$  produced only in the water layer, increased the measured total H contribution from water due to interfacially formed  $D_2$ .

The reactivity of the methanol-water interface was confirmed by growing  $H_2O/D_2O/CH_3OH/H_2O/TiO_2$  “sandwich” films. In thick films of pure water,  $H_2$  is produced only in the 10 ML closest to the vacuum interface. In constructing these sandwich films, a methanol layer was placed in this non-reactive region, creating a  $D_2O/CH_3OH$  interface. The  $D_2$  signal was found to be 20% larger when this interface was placed 12 ML away from the vacuum interface than when it was only 8 ML distant. The increase was due to  $D_2$  production at later times, which is associated with production at a buried interface where  $D_2$  must diffuse to the vacuum surface. However, thick layers of methanol were found to effectively block  $D_2$  production from buried  $D_2O$  layers, so the methanol layer is semi-opaque to either diffusing  $D_2$ , or more likely, to excitons. Therefore, the methanol-water interface is both opaque and reactive, similar to a buried Pt-water or  $TiO_2$ -water interface. This result suggests that to maximize electron-driven  $H_2$  production in water films at long times, a mixed film will be most effective.

Additional work with pure methanol films of varying thickness will enable us to isolate any existing methanol/substrate reactions in Figures 3.2, 3.3, and 3.4. If methanol acts as water does in these thin films, doing such experiments may enable us to determine the contribution of methanol and water to the prompt D<sub>2</sub> signal in mixed films. We also plan to find the “length” of the methanol/water interface, that is, how close a layer of water must be to a layer of methanol in order to see the methanol-induced results discussed above. These experiments will primarily involve isotopically labeling 1-2 water layers with D<sub>2</sub>O, and separating the labeled layers from CH<sub>3</sub>OH with spacer layers of H<sub>2</sub>O. For example, the length of a methanol-water interface placed 30 ML from the vacuum interface would be studied by irradiating a film of 28-n ML H<sub>2</sub>O/2 ML D<sub>2</sub>O/n ML H<sub>2</sub>O/1 ML CH<sub>3</sub>OH/50 ML H<sub>2</sub>O/TiO<sub>2</sub>. The ideal depth of a buried methanol interface for increasing D<sub>2</sub> production, and the relationship between a methanol layer’s thickness and its opacity, will also be explored.

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## **Chapter 4: Suppression of electron stimulated O<sub>2</sub> production from amorphous solid water by CH<sub>3</sub>OH**

### **Introduction**

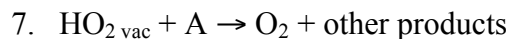
Most recent work on supercooled thin water films has focused on amorphous solid water (ASW) due that material's importance in multiple fields. Radiation-driven processes in pure ASW and pure methanol have been described elsewhere,<sup>1</sup> but these processes in mixed and layered films have not. However, such mixes are common in many settings where ASW research has applications, including comets and icy bodies, clouds, cells, and retired nuclear reactors and waste tanks.<sup>1-8</sup> Such mixed and layered films also have applications on a broader scale, by clarifying energy transfer, leading to new synthetic processes, and clarifying mechanisms in water-based reactions. Our understanding of H-bonding networks, interfacially controlled reactions, and mixing at low temperatures needs to be improved by studying such combinations.

In pure ASW, the major molecular products of non-thermal processes are H<sub>2</sub> and O<sub>2</sub>, although H<sub>2</sub>O<sub>2</sub> and atomic products have also been described.<sup>9-12</sup> Our focus in this chapter is limited to O<sub>2</sub> production in the layered CH<sub>3</sub>OH/H<sub>2</sub>O films. Sieger, Simpson, and Orlando examined the production of O<sub>2</sub> from ASW and determined that the threshold energy required for production was ~10 eV.<sup>13</sup> As they found that O<sub>2</sub> production was not immediate, but required an initial dose, they determined that the O<sub>2</sub> production mechanism must require the formation of a stable precursor molecule, implying a two-step process. While the precursor-forming step was found to be temperature dependent,

the reaction of the precursor to form O<sub>2</sub> is temperature independent. The behaviors of both the precursor formation step and the precursor → O<sub>2</sub> step are inconsistent with older interpretations requiring thermal diffusion of radicals. Sieger *et al.* proposed instead that O<sub>2</sub> production begins with reactions of excited water molecules, and that the observed temperature dependency of O<sub>2</sub> production is accounted for by the lifetimes of excited water molecules.

Petrik, Kavetsky, and Kimmel<sup>14</sup> further characterized radiation-driven O<sub>2</sub> production in ASW. In films that were not previously irradiated (also called “unprocessed” or “raw” films), O<sub>2</sub> production grew with time until production was saturated. When the electron beam was stopped after saturation, the sample was allowed to “rest” at the same temperature, and the electron beam was restarted, O<sub>2</sub> production resumed immediately at the previous saturation level, regardless of the length of resting time. Using isotopically labeled water (H<sub>2</sub><sup>16</sup>O and H<sub>2</sub><sup>18</sup>O), Petrik *et al.* determined that O<sub>2</sub> production was localized at the water-vacuum interface and ultimately resulted from HO<sub>2</sub> after a series of reactions:

1.  $e^- + \text{H}_2\text{O}_{\text{bulk}} \rightarrow \text{H}_2\text{O}^+ + 2e^-$
2.  $\text{H}_2\text{O}^+ + e^- \rightarrow \text{H}_2\text{O}^*_{\text{bulk}}$
3.  $\text{H}_2\text{O}^*_{\text{bulk}} \rightarrow \text{H}_2\text{O}^*_{\text{vac}}$
4.  $\text{H}_2\text{O}^*_{\text{vac}} \rightarrow \text{H}_{\text{des}} + \text{OH}_{\text{vac}}$
5.  $2 \text{OH}_{\text{vac}} \rightarrow \text{H}_2\text{O}_{2 \text{ vac}}$
6.  $\text{H}_2\text{O}_{2 \text{ vac}} + \text{OH}_{\text{vac}} \rightarrow \text{HO}_{2 \text{ vac}} + \text{H}_2\text{O}$



In reaction 7, A is unknown, and may be another precursor molecule, an exciton, or an impinging electron. The surface coverage of  $\text{HO}_2$  and other precursors ( $\text{H}_2\text{O}_2$ , OH) at saturation was found by modeling the reaction series to be  $\sim 0.01$  to  $0.03$  ML relative to the water coverage ( $1$  ML). Here we present the results of a study of the effects of  $\text{O}_2$  production in  $\text{H}_2\text{O}$  by the addition of methanol, focusing on reactions at the vacuum interface.

## Methods

### *Chamber Set Up*

Experiments were done in an ultrahigh vacuum (UHV) chamber, equipped with a closed cycle helium cryostat, low-energy electron gun, quadrupole mass spectrometer, and a molecular beam line. Median base pressure for the system was  $\sim 1.1\text{E-}10$  torr and base sample temperature was  $\sim 22\text{K}$ . Films were grown on a clean  $\text{TiO}_2$  (110) crystal approximately  $10$  mm in diameter and  $0.5\text{mm}$  thick. The crystal was cleaned by neon ion sputtering, followed by annealing at  $850$  K in vacuum, to yield a consistent  $\text{TiO}_2$  (111) surface. The sample was resistively heated, and the temperature measured by a type K thermocouple spot-welded to the back of the sample.

### *Deposition and Growth Conditions*

High-Pressure Liquid Chromatography-grade CH<sub>3</sub>OH, distilled, deionized H<sub>2</sub>O, and their isotopologues (CD<sub>3</sub>OH, CD<sub>3</sub>OD, D<sub>2</sub>O, and H<sub>2</sub><sup>18</sup>O) were freeze-pump-thawed prior to use to remove dissolved gases and to ensure purity. All films were dosed at temperatures colder than 100 K by molecular beams at normal incidence to the sample, creating a dense non-porous film.<sup>15, 16</sup> The films did not cover the entire substrate surface, but were centered on the TiO<sub>2</sub>. Water coverage calibration was based on previous calculations using a coverage of  $1 \times 10^{15}$  molecules\*cm<sup>-2</sup>.<sup>14</sup> Direct measurements of methanol saturation coverage on ASW for calibration purposes are difficult due to mixing processes during desorption. Instead, methanol coverage was calibrated based on the integration of the first monolayer peak in the temperature programmed desorption spectra from a *bare* TiO<sub>2</sub> crystal. Based on the relative coverage of methanol on bare TiO<sub>2</sub> (110),  $3.2 \times 10^{14}$  molecules cm<sup>-2</sup>,<sup>17</sup> one monolayer of methanol on ASW was defined to be roughly three times the exposure needed for one monolayer on methanol on TiO<sub>2</sub>. This definition of a CH<sub>3</sub>OH monolayer on ASW has a comparable coverage to that of a water monolayer on ASW,  $1 \times 10^{15}$  molecules\*cm<sup>-2</sup>. The same exposure definition (in torr s) was used for each of the isotopically labeled varieties of methanol used, CH<sub>3</sub>OH, CD<sub>3</sub>OH, and CD<sub>3</sub>OD, although the calibration was performed only for CH<sub>3</sub>OH. We must emphasize that our monolayer definition is strictly to make comparing the effects of a monolayer of methanol with those of a water monolayer easier on a per-molecule basis, and is not based on any measurement of the actual coverage of CH<sub>3</sub>OH on ASW.

Estimates of CH<sub>3</sub>OH coverage on crystalline ice surfaces (none are available for ASW surfaces) range in value, but are comparable to its coverage on TiO<sub>2</sub> (110).<sup>18-20</sup>

Underlying foundation water films (in contact with the TiO<sub>2</sub> surface) were grown at 80K, conditions known to produce consistently dense and smooth ASW surfaces.<sup>15, 16</sup> Surfaction, or the phase separation and resulting movement of methanol to the vacuum interface, was observed during deposition of upper water layers in “sandwich” experiments. In these experiments, layers of water are dosed atop methanol to isolate it from the vacuum interface, creating a layered film with a sandwich-like structure of water/methanol/water/TiO<sub>2</sub>. When the upper layers were deposited at 80K, the methanol promptly appeared on the surface in subsequent electron stimulated desorption (ESD) experiments. When the upper layers were dosed at 50K or less, it eliminated the prompt appearance of methanol from subsequent ESD experiments, even if the film was heated to 80 K from the lower dose temperature. Heating gently to 80K and irradiating had no effect on the ESD signal structure compared to irradiation at 50 or 25K. (For details, see Chapter 2.) To eliminate the effects of such surfaction, all upper films were grown at 80K or less, depending on their position in the final film structure. Capping water layers, or layers dosed atop methanol, were grown at 50K or less to minimize the surfactant properties of methanol. Methanol films were grown at 80K or less if their final position was located at the vacuum interface (i.e., an “open-faced” sandwich structure, also referred to in this paper as a methanol-capped film), and at 50K or less if in the interior (i.e., in a “sandwich” experiment).



### *Radiation Conditions*

To eliminate the effects of thermal mixing and focus on radiative mixing and reaction products, all irradiation was performed at 80 K or colder; changes in the ESD temperature do not change the signal structure, although it may affect the signal intensity (See Chapter 2). Any irradiation performed at 80K was done to methanol dosed at the vacuum interface, when the surfactant properties of methanol could be neglected. The electron beam was incident at 35° to the sample normal. The films were irradiated with 100 eV electrons at a current of ~2  $\mu$ A for 100 scan cycles (for a total exposure of ~97 s) unless otherwise noted. A scan-averaging mode was used that samples the signal repeatedly within a single cycle, rastering across the film sample to generate “pixels.” The pixels were then averaged to generate a single data point per cycle with a very high signal-to-noise ratio, as described in detail in Petrik *et al.*<sup>14</sup>

## **Results and Discussion**

### *Capped films*

Consisting of one methanol-water interface, a capped film, one layer atop the other, is the simplest case for a layered film and the logical starting point. To study the effects of CH<sub>3</sub>OH on the formation of O<sub>2</sub> from water at the vacuum interface, H<sub>2</sub><sup>18</sup>O was capped by increasing amounts of CH<sub>3</sub>OH and irradiated. The 36 amu signal, for <sup>18</sup>O<sub>2</sub>, was measured during irradiation. The addition of CH<sub>3</sub>OH to the surface of ASW leads to a delay in the radiation-driven production of O<sub>2</sub> from water (Figure 4.1). For a specified threshold level of O<sub>2</sub> production (e.g., a signal intensity of 0.03 a.u.), this delay is

approximately linearly dependent on the amount of CH<sub>3</sub>OH dosed on the surface (Figure 4.2). The greater the O<sub>2</sub> threshold, the longer the delay, indicating that O<sub>2</sub> production rates are slowed, and ruling out the possibility that all CH<sub>3</sub>OH and byproducts were eliminated from the system and the remaining O<sub>2</sub> comes from a pure water film. Further, when the O<sub>2</sub> rate is measured for a given remaining amount of methanol remaining on the surface, as measured by methanol desorption, it is not constant. Dosing amounts of methanol greater than 0.5 ML also suppresses O<sub>2</sub> production; at amounts greater than about 0.65 ML of CH<sub>3</sub>OH, O<sub>2</sub> production does not recover within 97 seconds, the length of the radiation exposure.

The suppression of O<sub>2</sub> was measured by integrating the O<sub>2</sub> ESD signal over time, and plotting its dependence on the initial methanol dose. Two integration ranges were used to capture two different behaviors. Integration over the first three seconds of irradiation exposure (i.e., the first three data points collected after the electron beam was turned on) reflects the initial suppression/retardation of early O<sub>2</sub> production and eliminates any radiative mixing or sputtering effects. Integration was also performed over the full radiation exposure (that is, from when the electron beam was turned on until it was turned off, or ~97 s) to reflect total O<sub>2</sub> suppression as a function of CH<sub>3</sub>OH dose. Full-exposure integration includes the effects of mixing and any CH<sub>3</sub>OH byproducts, such as CO, CH<sub>2</sub>OH, or CH<sub>2</sub>O, on the O<sub>2</sub> signal. The time-integrated O<sub>2</sub> signals' dependence on CH<sub>3</sub>OH dose was fitted to an exponential decay where the 1/e constant reflects the amount of methanol needed to reduce the O<sub>2</sub> signal (Figure 4.3). In the initial region, O<sub>2</sub> production is quickly suppressed by methanol, with a 1/e constant of 0.05 ML,

indicating that CH<sub>3</sub>OH interrupts the O<sub>2</sub>-producing reactions even at very low concentrations. However, it may appear to be more sensitive to CH<sub>3</sub>OH than it actually is as the signal is small even when no methanol is dosed (Figure 4.1, Inset). The full cycle is less sensitive, with 0.2-0.28 ML CH<sub>3</sub>OH needed. This latter value reflects late stage O<sub>2</sub> production as methanol is removed from the vacuum interface by mixing with the film, reacting with the water, and desorbing from the surface, and as O<sub>2</sub> production reaches saturation. While O<sub>2</sub> production increases as methanol signal decreases, there does not appear to be a threshold CH<sub>3</sub>OH surface concentration above which O<sub>2</sub> production is suppressed and below which it recovers. Partial isotopic labeling of the water films so that the upper 10ML are H<sub>2</sub><sup>18</sup>O and the bottom 70ML are H<sub>2</sub><sup>16</sup>O confirms that O<sub>2</sub> production is concentrated at the surface as it is in pure water films. In this case, the <sup>18</sup>O<sub>2</sub> signal intensity was roughly 70% that seen from a pure H<sub>2</sub><sup>18</sup>O film.

### *Sandwiched films*

To examine the nature of a buried water-methanol interface, as opposed to one located at the vacuum interface, “sandwich” films of  $n$  ML H<sub>2</sub>O over 1 ML CH<sub>3</sub>OH over 120- $n$  ML H<sub>2</sub>O on TiO<sub>2</sub> (110) were grown and irradiated at 50K. Thinner films of  $n$  ML H<sub>2</sub>O over 1 ML CH<sub>3</sub>OH over 80- $n$  ML H<sub>2</sub>O were also grown under the same conditions. In both cases, O<sub>2</sub> production resumed as the capping layer thickness  $n$  reached 10-12 ML H<sub>2</sub>O (Fig. 4.4a). Total integrated O<sub>2</sub> production saturated as the capping layer reached a thickness of  $n = 30$  ML (Fig 4.4b), meaning that the methanol layer was separated from the O<sub>2</sub> producing vacuum interface by 30 ML H<sub>2</sub>O. Thinner capping layers, where the

methanol interface was not buried as deeply, had reduced signals as a result of delays in O<sub>2</sub> production and lower final production levels. However, total levels of O<sub>2</sub> production in these CH<sub>3</sub>OH-containing films were about 10-20% lower than O<sub>2</sub> production levels in pure water, even when 80 ML of water over 1 ML CH<sub>3</sub>OH was compared to 80 ML H<sub>2</sub>O over TiO<sub>2</sub> (plotted as n=200 and labeled as “pure water” in Figure 4.4b). It is clear that the methanol is acting as an internal interface and is able to suppress O<sub>2</sub> production even when the interface is buried.

To determine the nature of the interface and the source of O<sub>2</sub> in the interface, labeled sandwiches of *n* ML H<sub>2</sub><sup>18</sup>O over 1 ML CH<sub>3</sub>OH over 80-*n* ML H<sub>2</sub><sup>16</sup>O were grown at 25 K and irradiated at 50K. The 32, 34, and 36 amu signals were monitored to measure the CH<sub>3</sub>OH/<sup>16</sup>O<sub>2</sub>, <sup>16</sup>O<sup>18</sup>O, and <sup>18</sup>O<sub>2</sub> desorption rates respectively. In sandwich films of H<sub>2</sub><sup>16</sup>O and CH<sub>3</sub>OH, the 32 amu signal is a composite of desorbing CH<sub>3</sub>OH, which begins desorbing immediately after the electron beam is turned on, and <sup>16</sup>O<sub>2</sub> that forms from H<sub>2</sub><sup>16</sup>O. In these films, O<sub>2</sub> production is observed only at later times and reaches an intensity of ~0.12 units (Figure 4.4a). In contrast, the 32 amu signal from the isotopically labeled sandwich shows prompt desorption characteristic of CH<sub>3</sub>OH desorption at low capping thicknesses, and is near zero at higher capping thicknesses (10 ML H<sub>2</sub><sup>18</sup>O or more, Figure 4.5). Any <sup>16</sup>O<sub>2</sub> that is produced in the water layer trapped beneath the CH<sub>3</sub>OH does not appear in the signal, even at shallow depths where the bottom layer is within the penetration depth of the electrons. The <sup>16</sup>O<sup>18</sup>O signal shows a slow increase characteristic of O<sub>2</sub> production in pure water, but even at its greatest intensity (for a 30 ML H<sub>2</sub><sup>18</sup>O layer over 1 ML CH<sub>3</sub>OH and 50 ML H<sub>2</sub><sup>16</sup>O) the signal is at most 5% of the

$^{18}\text{O}_2$  signal intensity for the same film (Figure 4.6). This minor signal indicates that very little mixing of oxygen isotopes occurs between water and methanol or  $\text{H}_2^{18}\text{O}$  and  $\text{H}_2^{16}\text{O}$ , and that there is minimal transfer of labeled water through the  $\text{CH}_3\text{OH}$  layer. Meanwhile, the  $^{18}\text{O}_2$  signal grows with increasing amounts of  $\text{H}_2^{18}\text{O}$ , as expected for  $\text{O}_2$  production, to a saturation intensity of  $\sim 0.12$  units (Figure 4.7), equal to that seen in the non-isotopically labeled film (Figure 4.4a). The maximum level of  $\text{O}_2$  production occurs when the  $\text{CH}_3\text{OH}$  layer is at about the same depth in both films, under  $\sim 20\text{-}30$  ML of water. The absence of the  $^{16}\text{O}_2$  and  $^{16}\text{O}^{18}\text{O}$  signals, combined with the  $^{18}\text{O}_2$  signal observed, indicates that all of the observed  $\text{O}_2$  is generated in the capping water layers. Methanol is acting as an internal interface in much the same way that Pt or  $\text{TiO}_2$  acts as one; the  $^{18}\text{O}_2$  signal is similar to that seen from dosing similar quantities of water on the bare  $\text{TiO}_2$  substrate. The combination of these signals also suggests that  $\text{CH}_3\text{OH}$  is an effective barrier at these temperatures to either the movement of  $\text{O}_2$  produced in the bottom portion of the sandwich, or to the production of  $\text{O}_2$  in these lower layers, possibly as a result of exciton trapping or side reactions. Experiments where the methanol/water interface was increased by growing films with greater numbers of thinner layers of methanol also suggest that the desorption products are from only the upper layer, and that lower methanol/water interfaces have little impact on  $\text{O}_2$  production.

To determine the amount of  $\text{CH}_3\text{OH}$  needed to form this interface,  $\text{O}_2$  production levels were measured from films of 6 ML  $\text{H}_2\text{O}$  over  $n$  ML  $\text{CH}_3\text{OH}$  over 80 ML  $\text{H}_2\text{O}$  on  $\text{TiO}_2$  (110).  $\text{O}_2$  production was dramatically suppressed by just 0.1 ML  $\text{CH}_3\text{OH}$ , and was near full suppression with the addition of 0.5 ML  $\text{CH}_3\text{OH}$  (Figure 4.8). If  $\text{O}_2$  or excited

$\text{H}_2^{16}\text{O}$  produced below the  $\text{CH}_3\text{OH}$  layer is being physically blocked by the presence of  $\text{CH}_3\text{OH}$ , this effect cannot be due to a separate continuous phase of methanol acting as an opaque film, as it occurs even at very low coverages. Blocking could be the result of long-range disruptions or restructuring of the H-bonding network near the methanol/water interface to prevent excited water from moving to the vacuum interface, or of efficient electron or exciton trapping that would prevent any excited bulk  $\text{H}_2^{16}\text{O}$  from being formed.

#### *Pre-irradiated films*

To determine if methanol was destroying existing precursors, interrupting reactions with existing precursors, or preventing new precursors from forming, a series of experiments using pre-irradiated films of water was done. In these experiments, a thick pure water layer was deposited and irradiated at 80K to build up a large  $\text{O}_2$  precursor molecule population. Previous work by Petrik *et al.*<sup>14</sup> showed that such precursors are stable over time at temperatures  $\leq 80\text{K}$ . When the sample was irradiated a second time after resting,  $\text{O}_2$  production in these pure water films resumed immediately at or near the saturation level of the first irradiation cycle.

In our experiments, we added a thin (0.01 to 0.5 ML) capping layer of methanol to the processed water film as it rested, and then resumed irradiation. The addition of  $\text{CH}_3\text{OH}$  led to a significant drop in the “prompt” (observed in the first 3 s) portion of the  $\text{O}_2$  signal that results from reactions of existing precursors (Figure 4.9), and a boost in the prompt CO signal as methanol reacts on the precursor-laden film (not shown). Fitting the

integrated prompt signals to an exponential decay indicates that only 0.1-0.2 ML  $\text{CH}_3\text{OH}$  is needed to quench the prompt response; as little as 0.01 ML  $\text{CH}_3\text{OH}$  suppresses the prompt portion of the response by 20%. The saturation coverages of the  $\text{O}_2$  precursors  $\text{H}_2\text{O}_2$  and  $\text{HO}_2$  were previously estimated to be  $\sim 0.01$ - $0.03$  ML, and the OH concentrations were estimated to be lower.<sup>14</sup> The effectiveness of this low  $\text{CH}_3\text{OH}$  coverage on  $\text{O}_2$  production, considered with the low concentration of  $\text{O}_2$  precursors, suggests that the quenching effects of  $\text{CH}_3\text{OH}$  are long-range and not due to direct reaction with a precursor molecule. The effect at low coverages shows that methanol is a much more effective suppressant than additional layers of water, indicating that the quenching is not due to some sort of physical blocking.

Increasing the methanol dose primarily serves to increase the delay before  $\text{O}_2$  production recovery, as the quenching process appears to saturate (dark and light blue traces, Figure 4.9). Prompt  $\text{O}_2$  production levels are similar for 0.2, 0.25, and 0.5 ML  $\text{CH}_3\text{OH}$ . Preliminary results suggest that even at methanol coverages of 2 ML, prompt  $\text{O}_2$  production is still measurable, at  $\sim 15\%$  of  $\text{O}_2$  production in pure water. However, at coverages greater than 0.5 ML  $\text{CH}_3\text{OH}$ , the suppression of  $\text{O}_2$  shows a linear correlation with  $\text{CH}_3\text{OH}$  coverage, rather than an exponential one. This change in correlation suggests that we must consider two processes in the suppression of prompt  $\text{O}_2$ . The first, occurring at low coverages (less than or equal to  $\sim 0.25$  ML  $\text{CH}_3\text{OH}$ ), is the result of long-range effects that interrupt some part of the reaction chain. For example,  $\text{CH}_3\text{OH}$  could react with an exciton in step 7, preventing  $\text{HO}_2$  from forming  $\text{O}_2$ . The remaining  $\text{O}_2$  production could be explained by some  $\text{HO}_2$  reacting with an impinging electron instead

of an exciton, suggesting that step 7 should be labeled as step 7a and 7b. Alternately,  $\text{CH}_3\text{OH}$  could interrupt the formation of  $\text{H}_2\text{O}^*$ , which would then stop production of OH and  $\text{H}_2\text{O}_2$ , leaving  $\text{HO}_2$  to be consumed in  $\text{O}_2$  production. However, this latter process requires that preexisting OH and  $\text{H}_2\text{O}_2$  fully convert to  $\text{HO}_2$  within the first second of irradiation to explain  $\text{O}_2$  signals at this first data point. The second  $\text{O}_2$  suppression process, which correlates linearly with  $\text{CH}_3\text{OH}$  dose, occurs at coverages greater than  $\sim 0.25$  ML  $\text{CH}_3\text{OH}$ . It is less sensitive to  $\text{CH}_3\text{OH}$  dose, indicating that most of the suppression effect is caused by the long-range effects observed at very low coverages. This second process may be the result of adding more methanol to act as a physical barrier, preventing any remaining precursors from moving to the surface to react and desorb, rather than interrupting  $\text{O}_2$ -producing reactions via scavenging  $\text{HO}_2$  or other precursors.

We also consider the recovery of  $\text{O}_2$  production at later times in these capped pre-irradiated films. As in the capped films, increased methanol doses lead to a longer recovery time for  $\text{O}_2$  production, indicating that the  $\text{O}_2$  precursor population must be reestablished. However, in the preirradiated films recovery appears to take longer than in the equivalent raw film (compare 0.5 ML coverages in Figure 4.1 and Figure 4.9), suggesting that a precursor deficiency is created by the presence of methanol, perhaps through OH scavenging. Another possibility is that the increased reaction of methanol with  $\text{O}_2$  precursors generates methanol byproducts that suppress  $\text{O}_2$  production. The  $\text{O}_2$  recovery in a processed film strongly depends on the surface methanol concentration and  $\text{O}_2$  production does not resume until nearly all the methanol is gone. Fitting the  $\text{O}_2$  signal



to the methanol signal indicates that less than 0.007 ML  $\text{CH}_3\text{OH}$  remains on the surface before  $\text{O}_2$  production recovers (Figure 4.10).

To eliminate the possibility that methanol directly reacts with  $\text{O}_2$  precursors such as OH and  $\text{H}_2\text{O}_2$  in the film, three experiments using layers of water as a physical barrier were performed (Figure 4.11). In each experiment, 80 ML  $\text{H}_2^{18}\text{O}$  were deposited and irradiated at 80K to saturate the precursor concentration. In Figure 4.11A, the processed film was then covered with  $n$  ML unprocessed  $\text{H}_2^{16}\text{O}$  at 50K. In Figure 4.11B, the processed film was covered by  $n$  ML unprocessed  $\text{H}_2^{16}\text{O}$  and then 0.5 ML  $\text{CH}_3\text{OH}$  at 50K, to place a physical barrier between the precursor concentration and the methanol/water interface. In Figure 4.11C, the processed film was covered first by 0.5 ML  $\text{CH}_3\text{OH}$  and then by  $n$  ML unprocessed  $\text{H}_2^{16}\text{O}$  at 50K, placing the methanol in direct contact with the concentrated precursors. Each film was irradiated a second time at 50K and the  $^{18}\text{O}_2$  signal measured. Film A, composed only of water, shows the expected trend that less  $^{18}\text{O}_2$  desorbs from the films with thicker capping layers. There is a small reduction in prompt  $\text{O}_2$  production as precursors must move to the vacuum interface, but recovery is quick and ultimately rises to a value greater than the initial value. Films B and C are nearly identical with each other and contrast with film A. The addition of the methanol in films B and C greatly reduces the peak  $\text{O}_2$  production signal and delays  $\text{O}_2$  production recovery in comparison to film A. The similarity of films B and C indicates that methanol is not reacting with the  $\text{O}_2$  precursors at the interface, but is blocking  $\text{O}_2$  production by other long-range means. The only difference in films B and C occurs near the end of the radiation exposure, when the recovering  $\text{O}_2$  signal is slightly smaller in

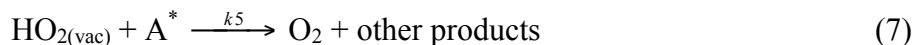
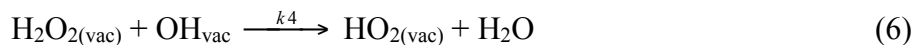
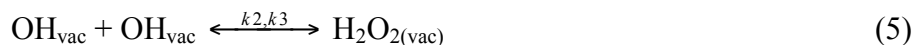
film C, where methanol and precursors are in direct contact. The slightly reduced signal of film C compared to film B suggests that any reduction in O<sub>2</sub> signal due to direct reactions at the interface is of minor importance and primarily affects O<sub>2</sub> recovery when new precursors are forming at the CH<sub>3</sub>OH-H<sub>2</sub><sup>18</sup>O interface.

Clarification of the mechanism comes from data on water desorption (Figure 4.12). The addition of methanol decreases the water desorption signal, indicating that fewer excited water molecules form. Methanol suppresses H<sub>2</sub>O desorption less effectively than O<sub>2</sub> production, with a 1/e constant of ~0.5 ML CH<sub>3</sub>OH, perhaps because of the bulk water reservoir and fewer steps required to desorb H<sub>2</sub>O than to form O<sub>2</sub>. The role of the bulk water reservoir may be tested in future experiments of 1-3 ML H<sub>2</sub><sup>18</sup>O over 80 ML H<sub>2</sub><sup>16</sup>O. Methanol shows long-range effects on electron stimulated water desorption as well. A single monolayer of methanol in a water-methanol-water sandwich will also suppress the desorption of water, even if buried under 20-30 ML H<sub>2</sub>O, when fewer electrons should be reaching the water/methanol interface.

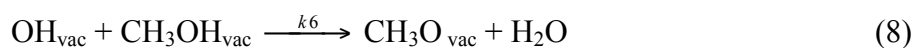
### *Modeling*

Using the simple kinetic model from Petrik *et al.*<sup>14</sup> as a starting point, the methanol-water system was modeled. The previous model, which we will call Model 1, included seven reactions:

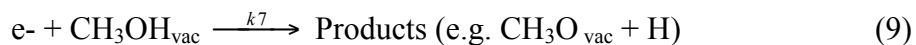




An additional reaction was added to account for the reaction of CH<sub>3</sub>OH with precursors, creating Model 1A:



This reaction scheme (Model 1A) was fitted to data from the ESD of *n* ML CH<sub>3</sub>OH on 80 ML H<sub>2</sub><sup>18</sup>O shown in Figure 4.1. This model is adequate up to a methanol coverage of ~0.1 ML but overestimates <sup>18</sup>O<sub>2</sub> suppression by CH<sub>3</sub>OH at higher coverages. To correct this overestimation, an additional reaction was added to reflect destruction of methanol by radiation, creating Model 2:



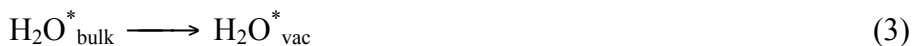
Model 2 fits the data over a broader range of methanol coverages (Figure 4.13) and correctly predicts the observed methanol signals. These results suggest that methanol interferes with the formation of O<sub>2</sub> by reacting with OH radicals at the vacuum surface,

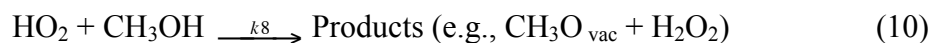
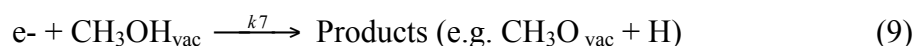
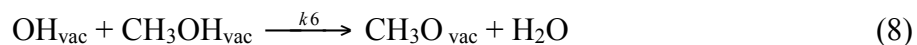
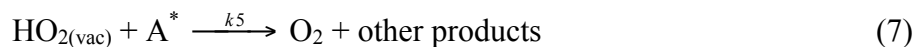
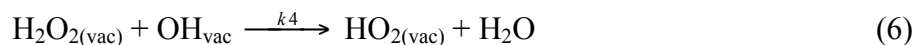
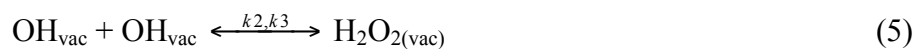
interrupting the latter half of the reaction chain. At the lowest coverages, less than 0.1 ML CH<sub>3</sub>OH, reaction 8 is sufficient to predict the observed data, and the destruction of CH<sub>3</sub>OH by impinging electrons is not significant.

The products of reaction 8, CH<sub>3</sub>O and CH<sub>2</sub>OH, do not appear to play a major role in subsequent reactions with OH<sub>vac</sub>, especially at lower coverages where they are likely to be quickly desorbed or react to form CH<sub>2</sub>O or CO. However, they may react at higher coverages, longer times, or with other precursors (e.g., HO<sub>2</sub> and H<sub>2</sub>O<sub>2</sub>). As can be seen in Figure 4.13, the model predicts the observed data for 0.5 ML CH<sub>3</sub>OH well until ~80 s, when it underestimates the suppression of O<sub>2</sub> formation by CH<sub>3</sub>OH, likely because later reactions are not included.

Predictions by Model 2 of O<sub>2</sub> suppression in pre-irradiated films yield similar results. There are two main components to the O<sub>2</sub> signal from these films—a prompt and a late portion. The prompt O<sub>2</sub> signal is the result of O<sub>2</sub> reacting from pre-formed precursors. The late portion reflects the recovery of O<sub>2</sub> production as new precursors form. The prompt portion shows a rapid decrease from the saturation signal observed in pure water films, reaching minimum O<sub>2</sub> production at 15-20 s. Therefore, the suppression of prompt O<sub>2</sub> indicates that methanol is reacting with HO<sub>2</sub> and including such a reaction to create Model 3 accounts for this portion of the signal.

**Model 3:**





However, the recovery portion of the signal is more difficult to model. Model 3 adequately describes the observed results at low coverages (Figure 4.14) but underestimates the suppression of  $\text{O}_2$  by  $\text{CH}_3\text{OH}$  in these cooked films at higher coverages and longer irradiation times, where the reaction processes are yet more complex.

## Conclusions and Future Work

Methanol is an effective suppressant of  $\text{O}_2$  production from water during irradiation.  $\text{CH}_3\text{OH}$  added to the surface of an unprocessed water film delays  $\text{O}_2$  production by scavenging  $\text{OH}$ , with  $\sim 0.2$  ML  $\text{CH}_3\text{OH}$  sufficient to reduce  $\text{O}_2$  production by  $\sim 63\%$ . The delay in  $\text{O}_2$  production from capped films is not due to the destruction or desorption of methanol followed by a prompt recovery of  $\text{O}_2$ , but instead to a simultaneous recovery of  $\text{O}_2$  as methanol is desorbed, mixed with water, and reacted, resulting in a decreased  $\text{O}_2$  production rate compared to that of pure water. Similar results

are found in processed films, where normally prompt O<sub>2</sub> production is reduced as methanol reacts with HO<sub>2</sub> precursors. O<sub>2</sub> production recovery appears to be slower than in an unprocessed film as it does not resume in processed films until effectively all of the methanol is removed from the film. O<sub>2</sub> suppression in both types of films occurs over long ranges (30 ML) and does not appear to require contact with the precursor-rich interface in the case of processed films. This result suggests that methanol interferes with exciton production/electron capture in water, and that such capture is a key process in reaction 7 ( $\text{HO}_{2(\text{vac})} + \text{A}^* \xrightarrow{k_5} \text{O}_2 + \text{other products}$ ). While it is clear that methanol disrupts the formation of excitons, the exact mechanism is yet to be determined and requires further study.

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## Chapter 5: Closing Remarks

### Summary

Water and methanol mixes are common in many environments, including various astronomical ices such as comet nuclei, interstellar dust grain mantles, asteroids, and moons/planetary bodies. Mixes of water with methanol or other simple organics are not limited to astrophysical regions; they are ubiquitous, found in every biological system, Earth's atmosphere, and nuclear power plant waste. When these systems are exposed to energetic radiation, large quantities of low-energy electrons are generated that can drive later reactions.<sup>1</sup> To mitigate the effects of such reactions, or to use them to our advantage, we must understand the processes involved, including the reaction mechanism, energy transport within the water, energy transport between the water and the organic molecule, and the role of the water/organic interface in promoting or retarding non-thermal reactions.

To this end, we have studied these low-energy electron-driven reactions in methanol/amorphous solid water (ASW) films at cryogenic temperatures. The use of ASW allows us to create structured films where the number and extent of water/methanol interfaces can be controlled, and processes such as mixing can be slowed and measured. These processes in layered methanol-water films were examined using ultra-high vacuum (UHV) and molecular beam techniques, electron stimulated desorption (ESD), and temperature programmed desorption (TPD). In each of the experiments described in this dissertation, a TiO<sub>2</sub> (110) crystal was used as the growth substrate. However, some of the



experiments reference ASW films grown on a Pt (111) crystal under the same conditions. In very thin films (40 ML or less), the substrate does play a role in determining reaction products and promoting reactions. In our work, we used thick films of 80 ML or more, rendering the nature of the substrate irrelevant, and allowing us to focus on the water/vacuum, water/methanol, and methanol/vacuum interfaces. Experiments with thick ASW films on TiO<sub>2</sub> (110) and Pt (111) yield very similar ESD spectra and are comparable. TPD peaks from these experiments are not compared to those using a Pt (111) substrate, although the basic shape of the water desorption peak is similar. All of the water and methanol films were grown at 80 K or less using a molecular beam at normal incidence to the substrate, conditions known to create non-porous smooth ASW films.<sup>2,3</sup>

Chapter 2 comprises an overview of the results from these experiments, which we believe to be the first to examine low-energy electron-induced reactions between methanol and ASW. ESD and TPD spectra were analyzed to determine major products and consequences of irradiation. Pure methanol, methanol-capped water films (methanol / water / TiO<sub>2</sub> structures), and methanol-sandwiched films (water / methanol / water / TiO<sub>2</sub> structures) are discussed and compared.

These experiments show that methanol is quite mobile during deposition at 80 K, moving to remain at the surface, but immobile at 50 K. This mobility exists only during deposition; heating a film deposited at 25 K to 80 K does not lead to an increased concentration of methanol at the surface. We also find that the methanol-water films, even for 30 ML thick methanol layers, produce fewer product species during irradiation

than pure methanol films (also 30 ML thick). From a pure methanol film, these include  $\text{H}_2$ ,  $\text{CH}_2\text{O}$ ,  $\text{CO}$ ,  $\text{CO}_2$ ,  $\text{H}_2\text{O}$ ,  $\text{CH}_4$ ,  $\text{C}_2\text{H}_6$ ,  $\text{C}_2\text{H}_4$ , and heavier species such as  $\text{HCOOH}$ ,  $\text{CH}_3\text{OCH}_3$ ,  $\text{CH}_3\text{OOCH}_3$ ,  $\text{CH}_3\text{CH}_2\text{OH}$ , and  $(\text{CH}_2\text{OH})_2$ , many of which are detected during the TPD. From a layered methanol/water film, fewer products are seen, with  $\text{CH}_3\text{OH}$  and  $\text{H}_2\text{O}$  dominating TPDs. Observed products from these films included  $\text{H}_2$ ,  $\text{O}$ ,  $\text{CH}_2\text{O}$ ,  $\text{C}_2\text{H}_6$ ,  $\text{CO}$ ,  $\text{CO}_2$ ,  $\text{CH}_3\text{CH}_2\text{OH}$ ,  $\text{CH}_3\text{OCH}_3$ , and  $\text{O}_2$ . The variety and quantity of product species increase as the total energy deposited increases; no species besides methanol were observed when the samples were not irradiated.

The TPD data indicate that methanol and water co-desorb over a broad temperature range, and are mixed by radiative processing during the ESD. The kinetics of desorption from the layered films are not discussed, as up to four peaks overlap during desorption. Surface area measurements suggest that water-dominated surfaces are marginally rougher than methanol-dominated surfaces. Confirmation of these products by spectroscopic methods (e.g., infrared spectroscopy), improved surface area measurements, and the effects of extended irradiation exposures will be included in future work.

Extra attention was given to the generation and destruction of the main radiolytic water products, molecular hydrogen and molecular oxygen, due to the importance of these species in major environments of interest: nuclear waste tanks, nuclear reactors, and astronomical ices. For example, the presence of  $\text{H}_2$  in waste tanks poses a serious hazard to attempts to clean up contaminated sites, and increases the risks associated with long-term storage of nuclear waste. Previous studies have found greater quantities of  $\text{H}_2$

present in these tanks than predicted by theory.<sup>1</sup> Our research shows that this excess H<sub>2</sub> could be due to the presence of small quantities of organic compounds, a factor that must be included in future models of nuclear waste storage and treatment. The formation of O<sub>2</sub> from water present in these tanks increases the combustion and containment hazards posed by H<sub>2</sub> build up, and consequently must be considered. O<sub>2</sub> production and the associated radicals also increase corrosion rates in water-cooled nuclear reactors.<sup>1</sup> The production and destruction in ASW of both O<sub>2</sub> and H<sub>2</sub> are also important for astrophysical models that explain the evolution of stars and planets, and for interpreting spectroscopic signals.

Chapter 3 discusses how methanol changes electron-driven H<sub>2</sub> production from water films, focusing on the role played by the new methanol/water interface. The addition of a methanol layer to an ASW film increases the total electron-driven hydrogen production during ESD. Part of this increase is due to contributions from the H-rich methanol, and supports the hypothesis that excess H<sub>2</sub> in waste storage results from the presence of organic compounds. However, at low methanol coverages, part of the increase also appears to be the result of increased H contributions from water. Isotopic labeling showed that coverages of less than 0.6 ML methanol on ASW at the vacuum interface increase D<sub>2</sub> production occurring strictly in the amorphous D<sub>2</sub>O film (that is, both D atoms come from a water source). At these sub-monolayer doses, methanol increases the ability of water to generate D<sub>2</sub> by increasing D<sub>2</sub> production later. This increase appears to be due to the creation of an extended methanol/water/vacuum

interface. This effect is lost as methanol capping layer thickness increases, blocking the D<sub>2</sub>-forming water/vacuum interface.

Similar results were seen with buried methanol/water interfaces, where the H contribution from water was observed to increase by as much as 40%. This increase is due to the creation of a reactive methanol/water interface in regions of the bulk water that are typically unreactive, and to interfacial reactions between methanol and water. When the effect of mixing between the water and methanol layers is considered, i.e., at longer irradiation exposures, the increase is greatest. We propose that these new interfaces increase the number of dangling bonds, more easily trapping the excitons that drive the reaction. Mixing during the ESD, leading to the observed increase at later times, would enhance this effect. The disruption of ASW's H-bonding network by methanol may also increase the mobility of water molecules near the interface and aid H<sub>2</sub> production.

The reactivity of the buried methanol-water interface was confirmed by growing H<sub>2</sub>O/D<sub>2</sub>O/CH<sub>3</sub>OH/H<sub>2</sub>O/TiO<sub>2</sub> “sandwich” films. In thick films of pure water, H<sub>2</sub> is produced only in the 10 ML closest to the vacuum interface. In constructing these sandwich films, a methanol layer was placed in this non-reactive region, creating a D<sub>2</sub>O/CH<sub>3</sub>OH interface. The D<sub>2</sub> signal was found to be 20% larger when this interface was placed 12 ML away from the vacuum interface than when it was only 8 ML distant, despite receiving a lower electron flux. The increase was again due to D<sub>2</sub> production at later times, which is associated with production at a buried interface where D<sub>2</sub> must diffuse to the vacuum surface. However, thick layers of methanol were found to effectively block D<sub>2</sub> production in H<sub>2</sub>O/CH<sub>3</sub>OH/D<sub>2</sub>O/H<sub>2</sub>O/TiO<sub>2</sub>, so the methanol layer is

semi-opaque to either diffusing  $D_2$ , or more likely, to excitons. Therefore, the methanol-water interface is opaque and reactive, somewhat similar to a buried Pt-water or  $TiO_2$ -water interface.

Chapter 4 covers the suppression of electron-driven  $O_2$  production from water and explores the mechanisms by which methanol interrupts this multi-step reaction process. In water,  $O_2$  is known to form at the vacuum interface during irradiation.<sup>4</sup> We find that placing methanol at this interface efficiently suppresses  $O_2$  production, even at very low (0.05 ML) coverages. Unlike  $H_2$  production, in which hydrogen formed at the methanol/water interface could come from either source, the  $O_2$  that was observed to form is almost exclusively (more than 95%) from water.

Kinetic modeling shows that  $CH_3OH$  added to the surface of an unprocessed water film delays  $O_2$  production by scavenging OH as it is produced, with  $\sim 0.2$  ML  $CH_3OH$  sufficient to reduce  $O_2$  production by  $\sim 63\%$ .  $O_2$  production does eventually recover as methanol is removed from the surface by desorption, mixing with water, and reacting to form other (non-OH-scavenging) species. While  $O_2$  suppression is most easily observed when methanol is placed at the vacuum interface, a monolayer of methanol buried in the upper 30 ML of a water film also suppresses  $O_2$  production. In these sandwich films, we found that methanol was opaque to  $O_2$  produced below the methanol layer, with nearly all of the detected  $O_2$  resulting from water capping layers. Greater suppression is observed as the methanol is placed closer to the vacuum interface, and fewer capping layers of water are available to produce  $O_2$ . No  $O_2$  was produced during the 97 s radiation cycle when the methanol layer was placed in the most reactive

uppermost 10 ML of H<sub>2</sub>O. Clearly, scavenging OH at the vacuum interface is not the only mechanism by which methanol interrupts the O<sub>2</sub>-forming process.

Similar results are seen in pre-processed films, where an ASW film has been pre-irradiated to saturate the O<sub>2</sub>-precursor population. Normally immediate O<sub>2</sub> production is quickly reduced as methanol reacts with HO<sub>2</sub> precursors, and O<sub>2</sub> production recovery does not resume until effectively all methanol is removed from the film. Again, the scavenging of the O<sub>2</sub> precursor HO<sub>2</sub> by CH<sub>3</sub>OH, although it fits the kinetic model very well, is not the only mechanism causing O<sub>2</sub> reduction. O<sub>2</sub> suppression in both types of films occurs over long ranges (30 ML) and does not appear to require contact with the precursor-rich interface in the case of pre-processed films. This result suggests that methanol also interferes with exciton production/electron capture in water, and that such capture is a key process in the final O<sub>2</sub>-forming reaction step ( $\text{HO}_{2(\text{vac})} + \text{A}^* \xrightarrow{k_5} \text{O}_2 + \text{other products}$ ).

## Future Work

A number of important questions remain, including fundamental ones about mobility at low temperatures and energy transport within the ASW film. To better describe the water/methanol system, future studies will better characterize methanol surfaction and confirm the products identified so far. We will also examine the effects of longer radiation exposures on mixing and reactions in the layered methanol/water films.

More study is needed to confirm the observed increases in H<sub>2</sub> production in these layered films, and the mechanisms responsible. For example, the role of H-exchange

between CH<sub>3</sub>OH and H<sub>2</sub>O at the interface, and any effect it might have on the apparent increases in H<sub>2</sub>, was not examined in this dissertation. The data suggest that other factors, such as increased exposure time and increased mixing, will positively affect H<sub>2</sub> production. However, we did not study the effects of long irradiation times, pre-processing, or co-dosed (truly mixed, as opposed to layered) films on H<sub>2</sub> production. It is possible that this increase may not be observed at greater exposures, as the sample can undergo radiative annealing that could reduce the reactivity of the water/vacuum interface.

Related experiments should study the nature of the methanol/water interface. The methanol layer appears to be opaque and to increase H<sub>2</sub> production when buried. However, previous experiments with H<sub>2</sub> production from ASW on Pt (111) showed that H<sub>2</sub> production at the Pt interface was significant only when the Pt interface was within 50 ML of the vacuum interface.<sup>5</sup> Future experiments must determine the mechanism responsible for the observed increase in D<sub>2</sub> production from a D<sub>2</sub>O layer at the methanol interface (ASW H-bonding network disruption, exciton trapping and transfer by CH<sub>3</sub>OH, or H-D exchange between the D<sub>2</sub>O and CH<sub>3</sub>OH), and find if there is a depth that maximizes this increase. Finding the “length” of the water/methanol interface, or how close the water must be to the methanol to be affected by its presence, will inform us about some of the mechanisms involved.<sup>a</sup>

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<sup>a</sup> Films of m ML H<sub>2</sub>O / 2 ML D<sub>2</sub>O / n-m ML H<sub>2</sub>O / 1 ML CH<sub>3</sub>OH / 50 ML H<sub>2</sub>O / TiO<sub>2</sub> can help answer both questions about H-D exchange between CH<sub>3</sub>OH and D<sub>2</sub>O, and the length of the interface.

The most pressing and interesting questions remaining are in regard to the observed long-range effects of methanol. While our expanded kinetic model accounts for the observed data on O<sub>2</sub> production very well, especially at low methanol coverages, it does not describe the observed long-range interruption caused by CH<sub>3</sub>OH shown in Figure 4.11. The mechanism of this long-range effect is unknown, although we posit that it is the result of electron or exciton trapping by methanol. We expect that determining this mechanism will reveal basic information about how energy and matter are transferred between molecules in the condensed phase, to interfaces, and through interfaces. We will continue to use methanol/water interfaces to probe this question.

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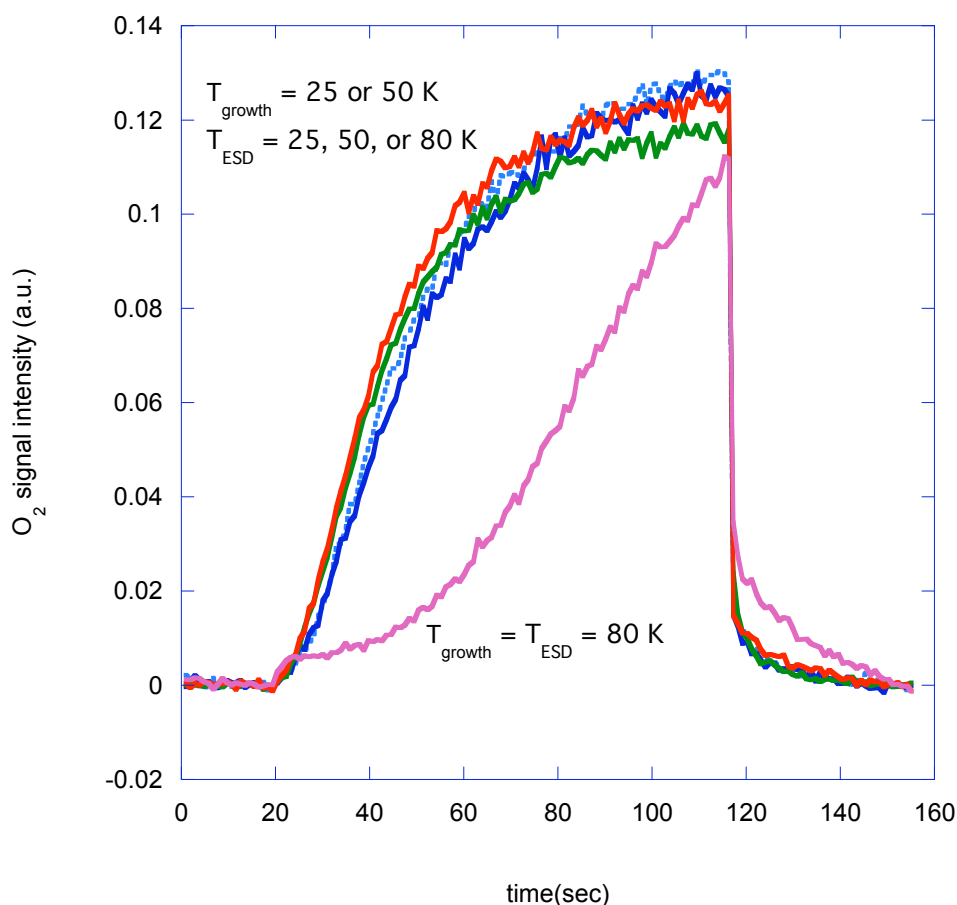


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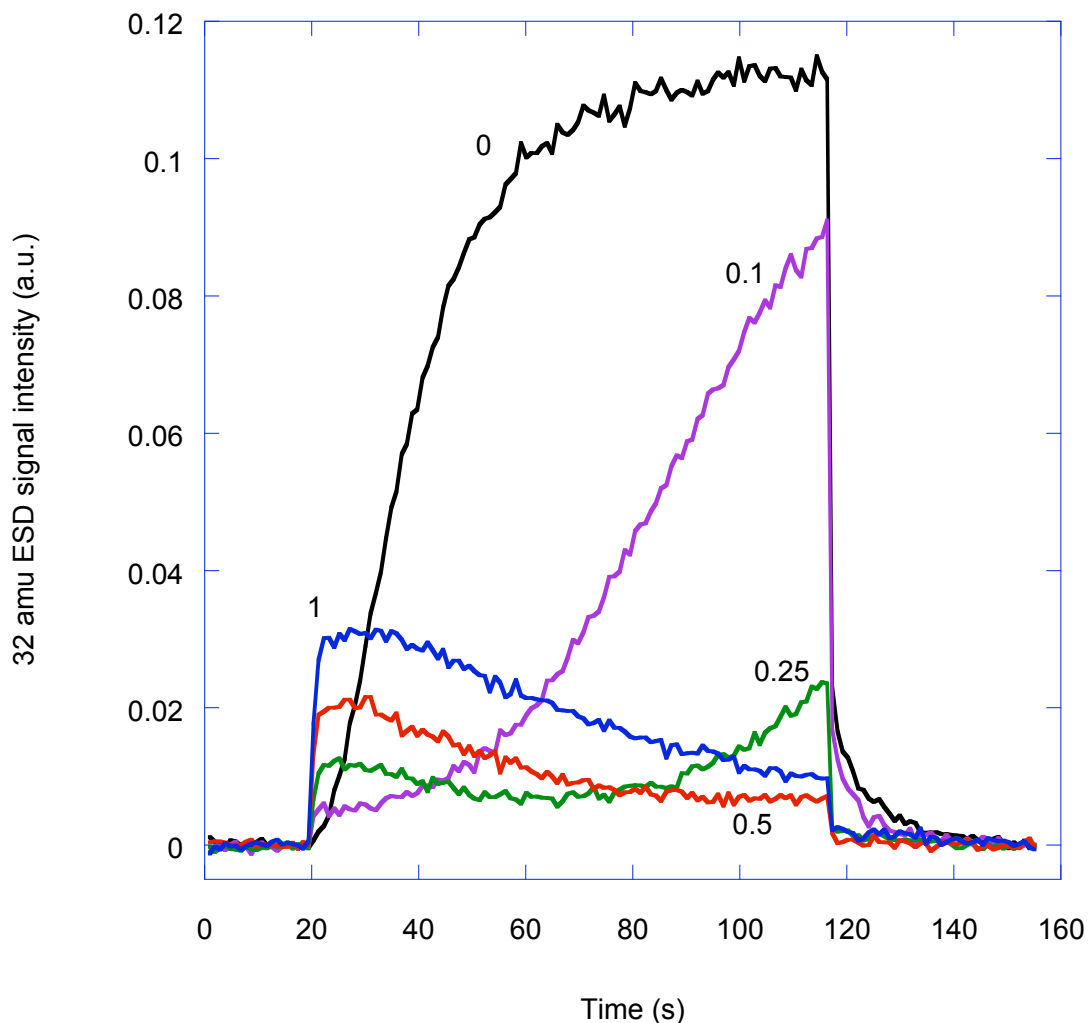
## Tables and Figures

**Table 2.1: Experimental cracking fractions for CH<sub>3</sub>OH.**

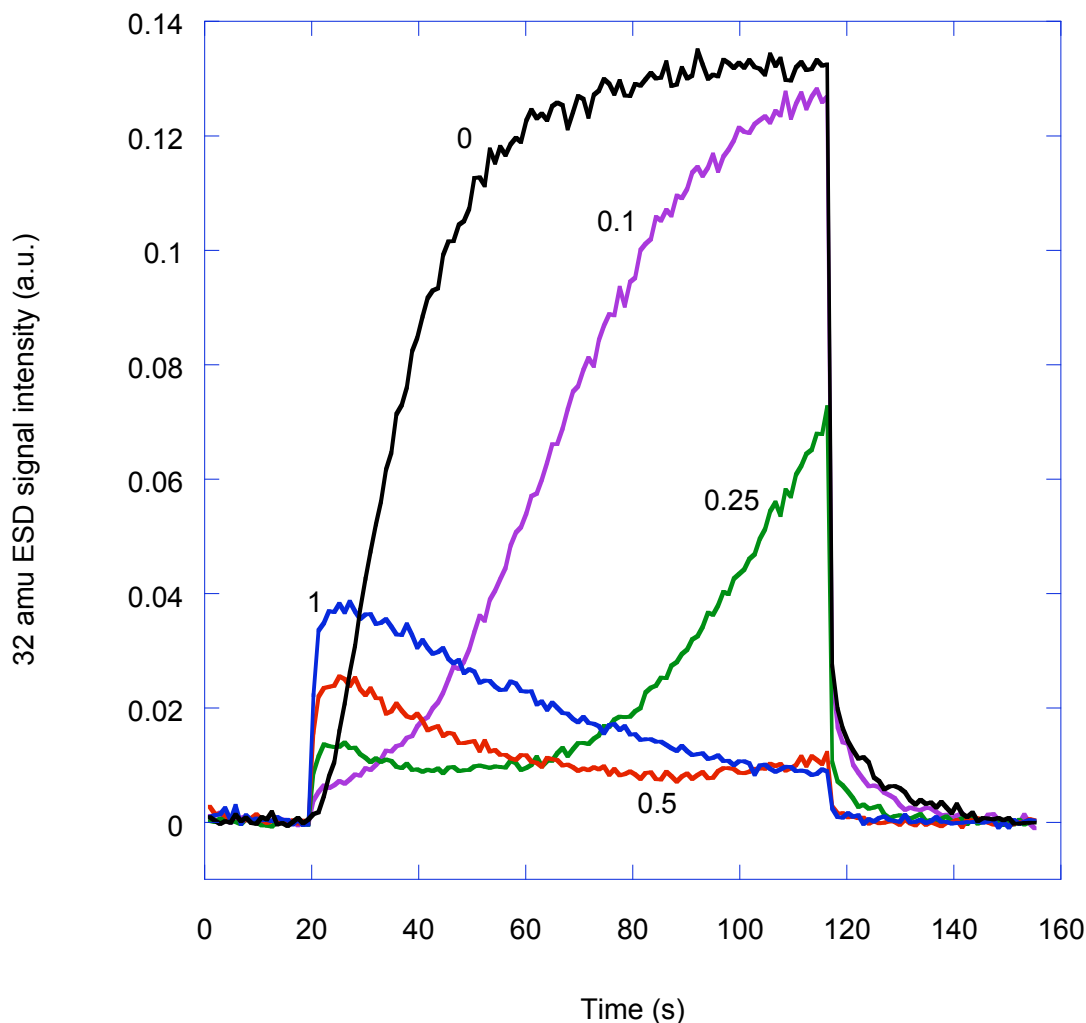
M/Z	Relative intensity, Isothermal measurements	Relative Intensity, During TPD
2	.056	
12	.032	
13	.040	
14	.093	
15	.451	.317
16	.039	.018
17	.028	
18	.064	.026
27		.002
28	.396	.176
29	.744	.679
30	.158	.103
31	1	1
32	.691	.591
33	.023	.016
44	.003	.001



**Figure 2.1: Deposition of ASW over CH<sub>3</sub>OH at T=80K leads to an increased concentration of CH<sub>3</sub>OH at the sample surface.** Films of 30 ML H<sub>2</sub>O over 1 ML CH<sub>3</sub>OH over 50 ML H<sub>2</sub>O / TiO<sub>2</sub> (110) were grown at various temperatures. The sandwich film was then irradiated at various temperatures and the 32amu ESD was measured. The different irradiation temperatures ( $T_{\text{ESD}}$ ) lead to slightly different signal intensities. To compensate, all data were scaled to  $\sim 0.12$  units for easier comparison. The appearance of methanol at the surface leads to a delay in the onset of O<sub>2</sub> production as seen when the deposition temperature ( $T_{\text{growth}}$ ) = 80K, which determines the degree of surfaction. No such delay is observed when the film is grown at 25 or 50 K, regardless of the irradiation temperature.



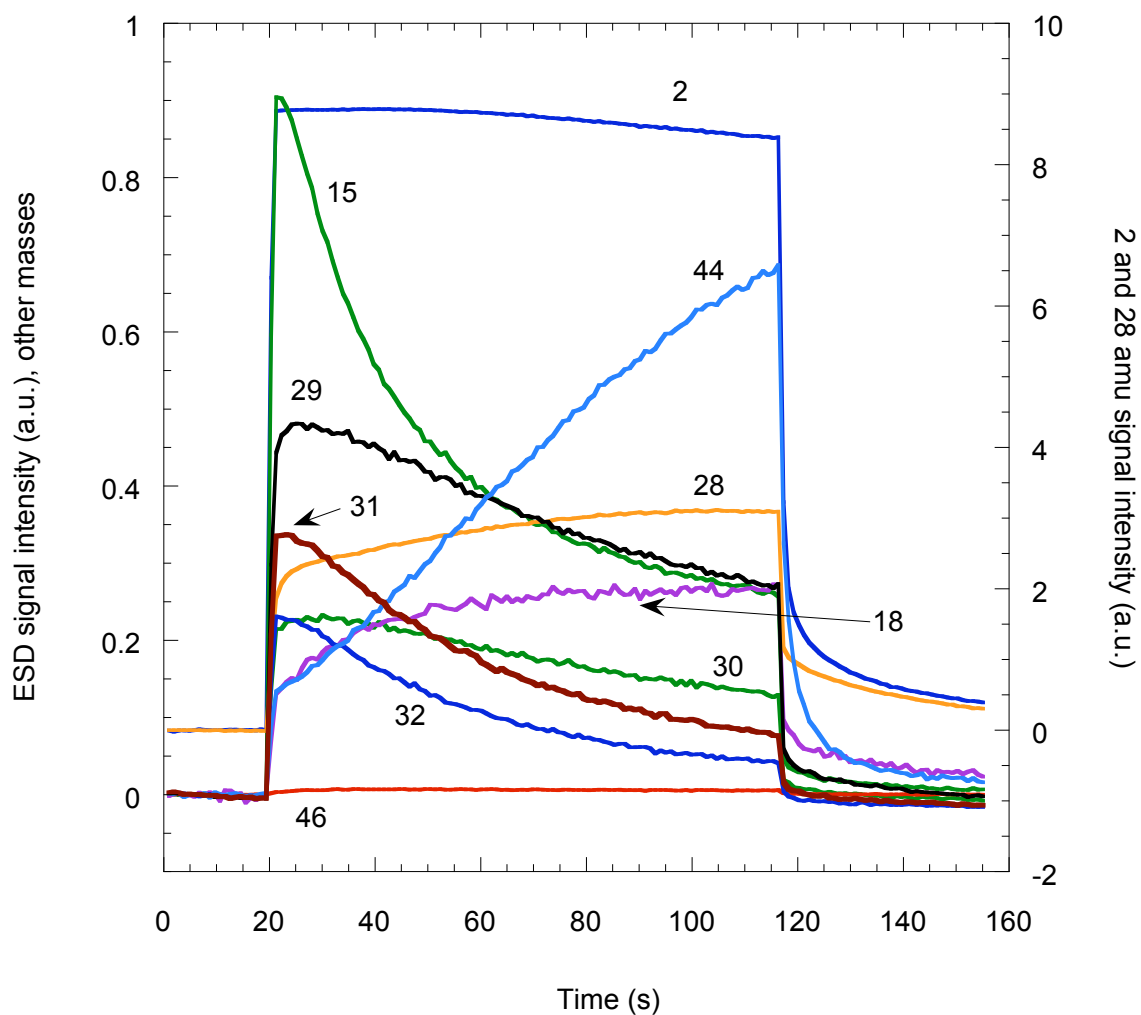
**Figure 2.2: O<sub>2</sub> production from a methanol-capped water film deposited at 50 K and irradiated at 80K.** n ML CH<sub>3</sub>OH were deposited at 50 K on 80 ML H<sub>2</sub>O. The film was irradiated beginning at 20 s and continuing until 117 s using 100 eV electrons at ~2  $\mu$ A current. Mass 32 was monitored, measuring the CH<sub>3</sub>OH and O<sub>2</sub> signals. The rapid rise at 20 s (observed for all coverages except 0 ML CH<sub>3</sub>OH) is the result of desorbing CH<sub>3</sub>OH. The O<sub>2</sub> signal is only observed at later times when CH<sub>3</sub>OH is deposited; in the case of 0.5 ML CH<sub>3</sub>OH and 1 ML CH<sub>3</sub>OH, the O<sub>2</sub> signal is not observed.



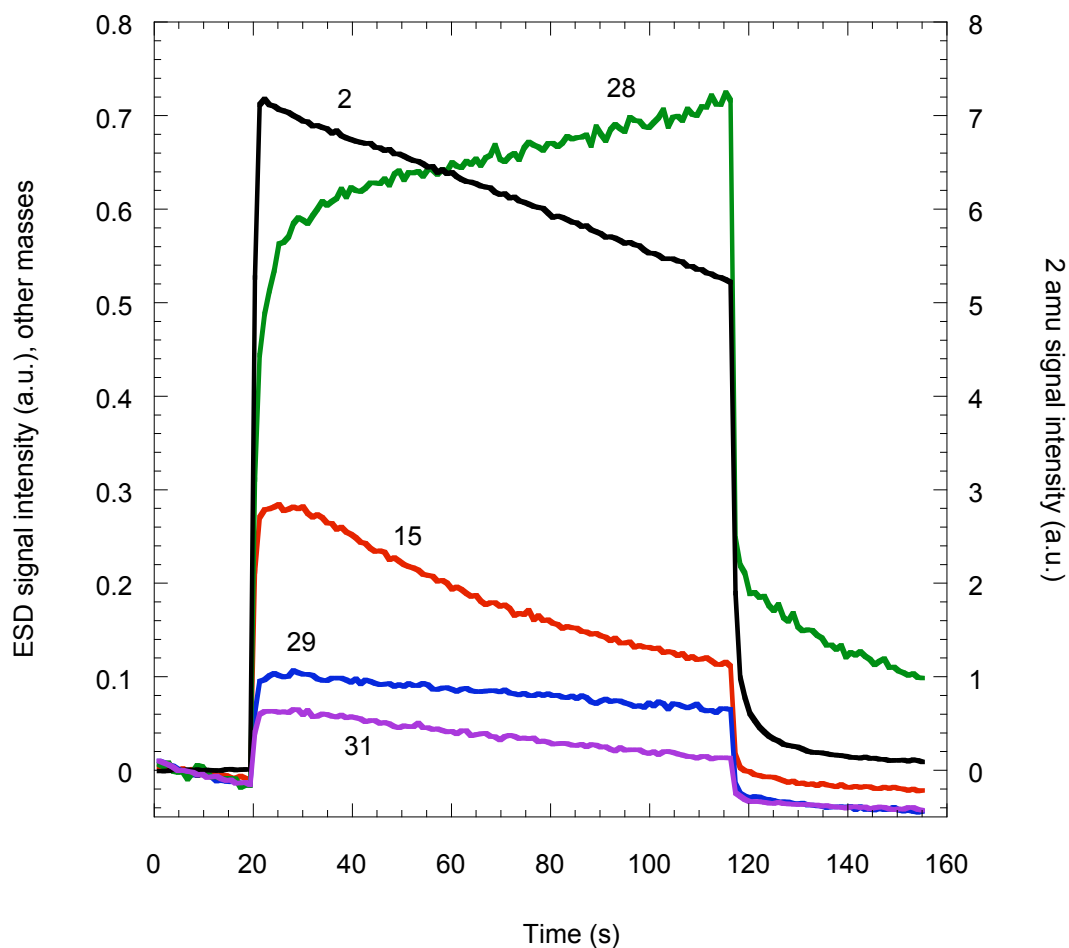
**Figure 2.3: O<sub>2</sub> production from a methanol-capped water film deposited and irradiated at 80 K.** n ML CH<sub>3</sub>OH were deposited at 80 K on 80 ML H<sub>2</sub>O. The film was irradiated beginning at 20 s and continuing until 117 s using 100 eV electrons at ~2  $\mu$ A current. Mass 32 was monitored, measuring the CH<sub>3</sub>OH and O<sub>2</sub> signals. The rapid rise at 20 s (observed for all coverages except 0 ML CH<sub>3</sub>OH) is the result of desorbing CH<sub>3</sub>OH. The O<sub>2</sub> signal is only observed at later times when CH<sub>3</sub>OH is deposited; in the case of 1 ML CH<sub>3</sub>OH, the O<sub>2</sub> signal is not observed. In comparison to Figure 2.2, the O<sub>2</sub> signal recovers sooner. Both films were irradiated at 80 K, so this result is not due to higher desorption rates. Instead, it is likely due to greater mobility of CH<sub>3</sub>OH during deposition at 80 K than at 50 K.

**Table 2.2: Major desorption peaks during TPD from 30 ML unprocessed CH<sub>3</sub>OH.**

M/Z	Temperature at peak (K)	Peak Intensity (a.u.)	notes
44	173	.045	
45	173	.005	
46	173	.003	
30	557	.039	On tail
32	315	.124	On tail
32	~170	Saturated; estimate ~54	
33	172	5.417	
33	172	.831	
18	275	.01	Convolutd with tail of 172K peak
15	317	.02	Convolutd with tail of 172K peak

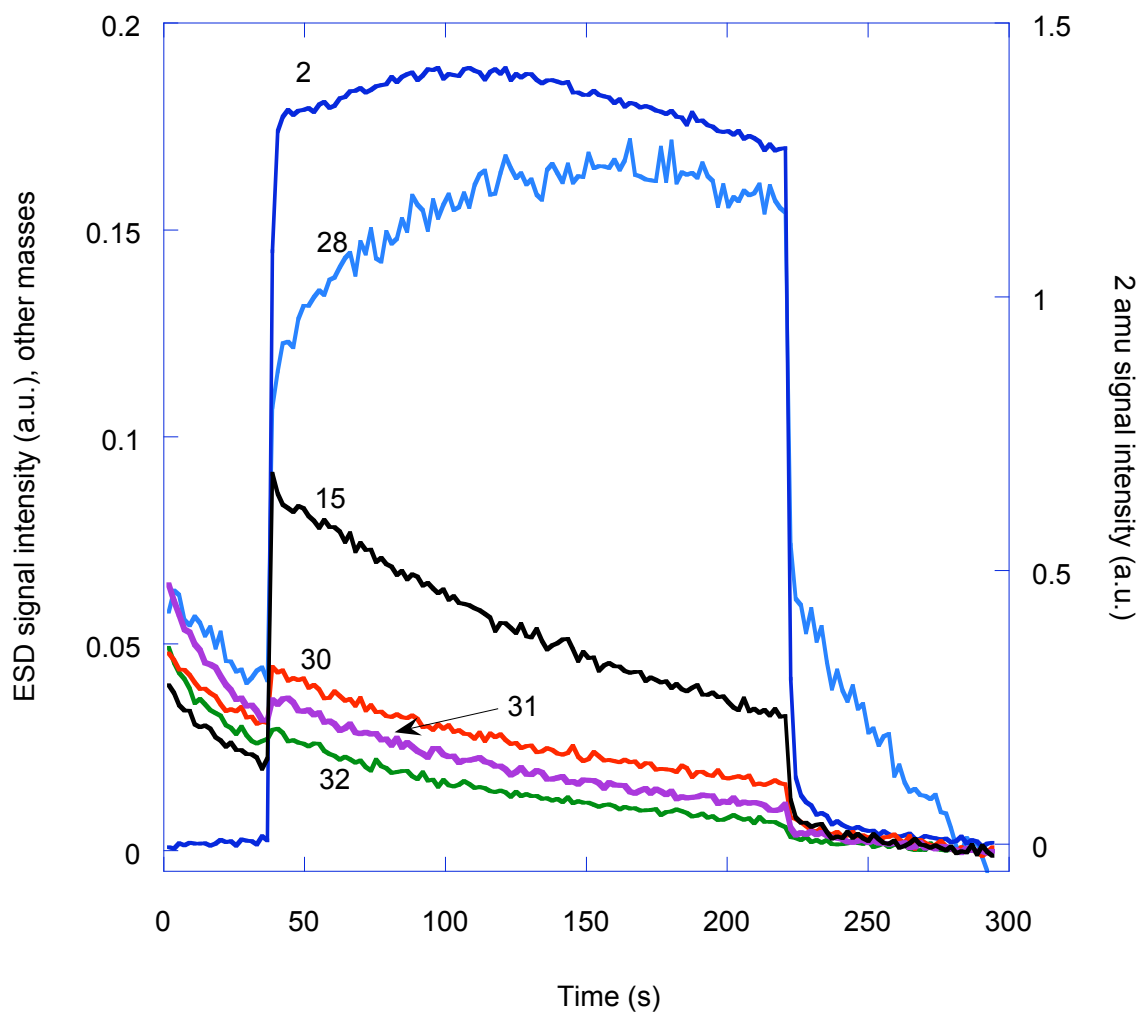


**Figure 2.4: ESD products of 30 ML CH<sub>3</sub>OH.** 30 ML CH<sub>3</sub>OH were deposited and irradiated at 80 K, beginning at 20 s and continuing until 117 s. 100 eV electrons were used at a current of  $\sim 5\mu\text{A}$ . ESD products are shown above; major products include H<sub>2</sub> and CO, plotted on the right-hand axis.

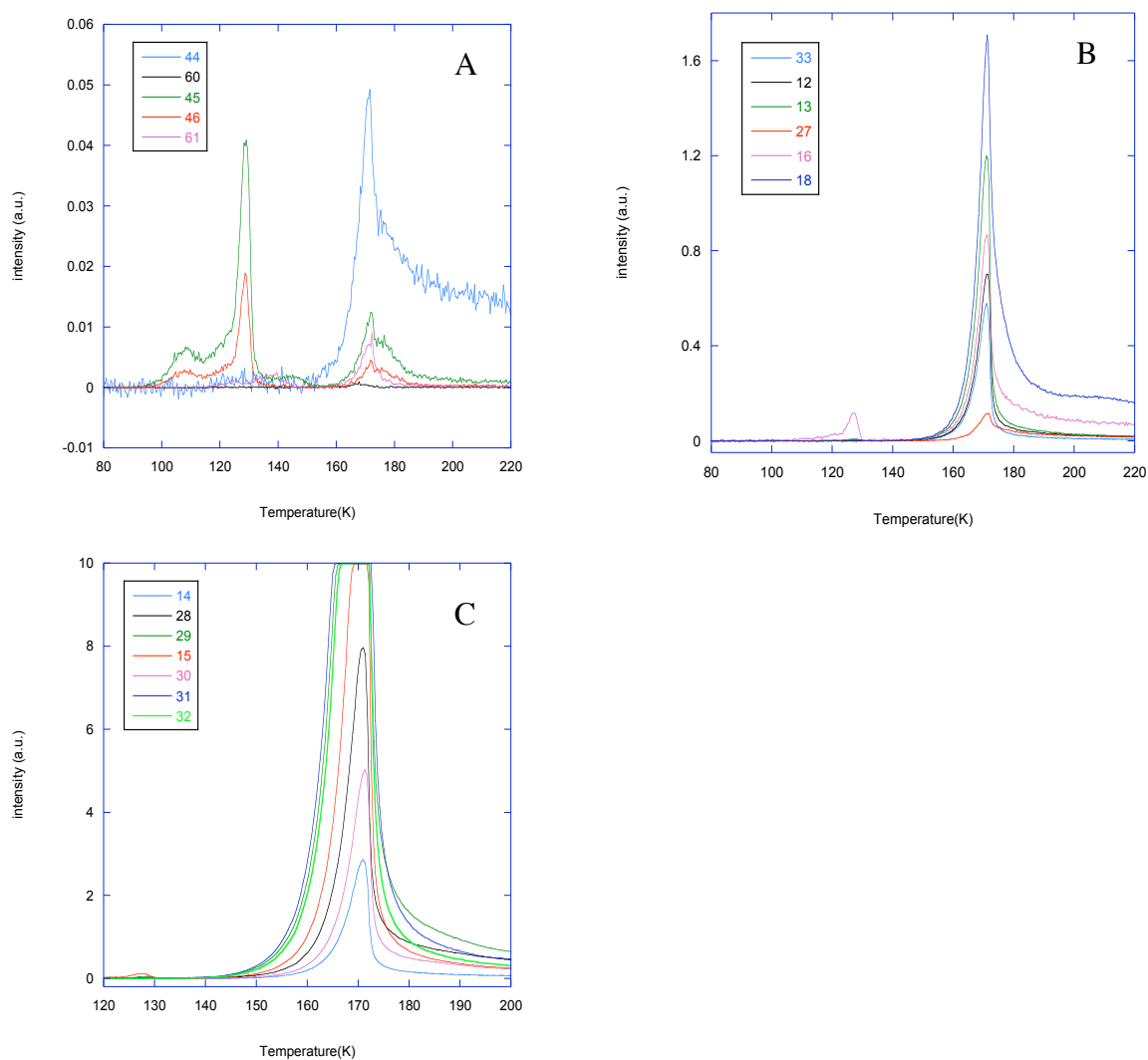


**Figure 2.5: Selected ESD products of 30 ML  $\text{CH}_3\text{OH}$ ,  $2\mu\text{A}$ .** 30 ML  $\text{CH}_3\text{OH}$  were deposited and irradiated at 80 K, beginning at 20 s and continuing until 117 s. 100 eV electrons were used at a current of  $\sim 2\mu\text{A}$ . Selected ESD products are shown above; major products include  $\text{H}_2$ , plotted on the right-hand axis. The reduced electron current leads to a reduced overall signal.

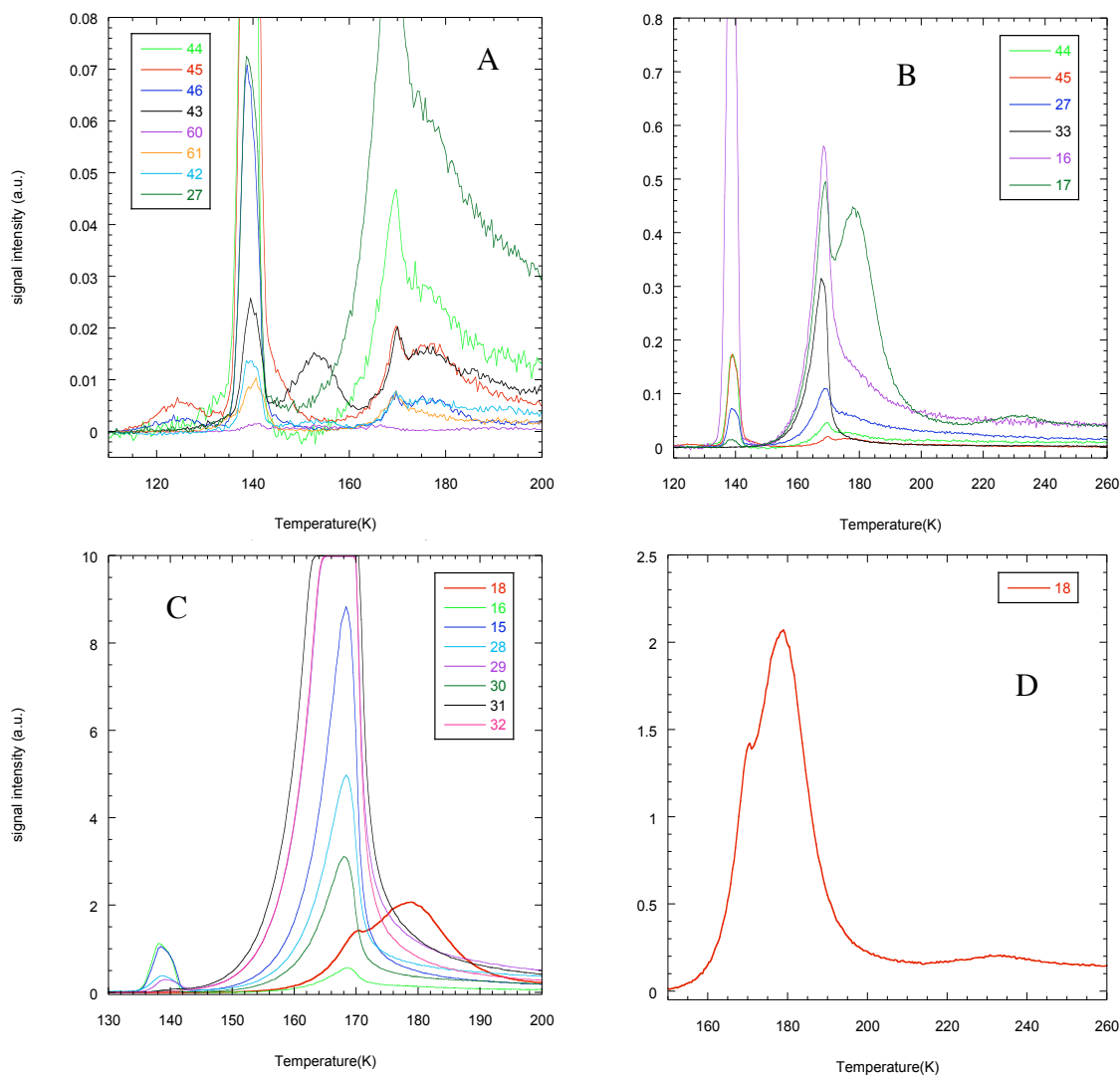




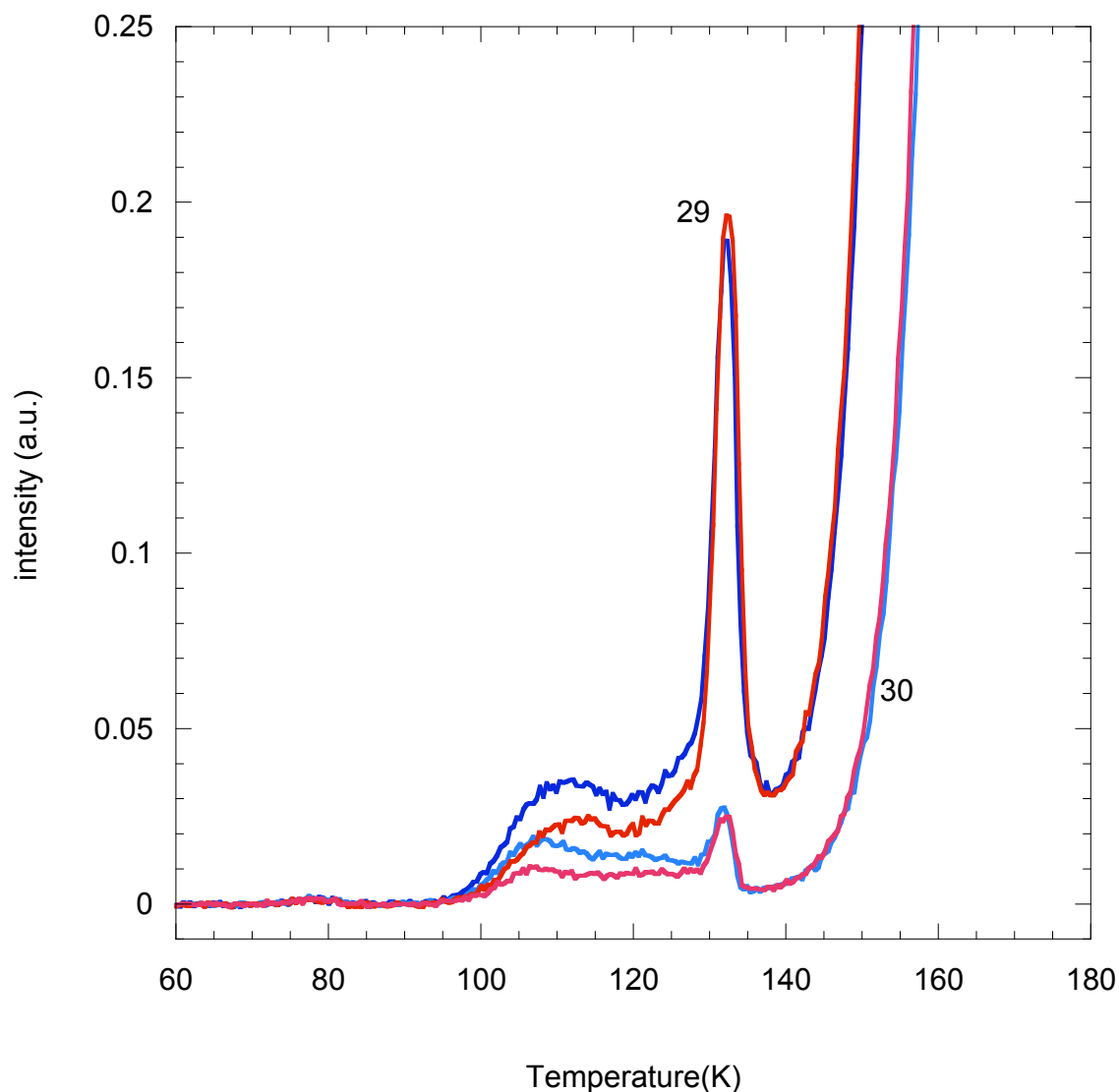
**Figure 2.6: ESD products of 30 ML CH<sub>3</sub>OH, 20eV.** 30 ML CH<sub>3</sub>OH were deposited and irradiated at 80 K, beginning at 20 s and continuing until 117 s. 20 eV electrons were used at a current of  $\sim 2\mu\text{A}$ . Selected ESD products are shown above; major products include H<sub>2</sub>, plotted on the right-hand axis. The reduced electron energy leads to a greatly reduced overall signal; almost no CH<sub>3</sub>OH is observed to desorb.



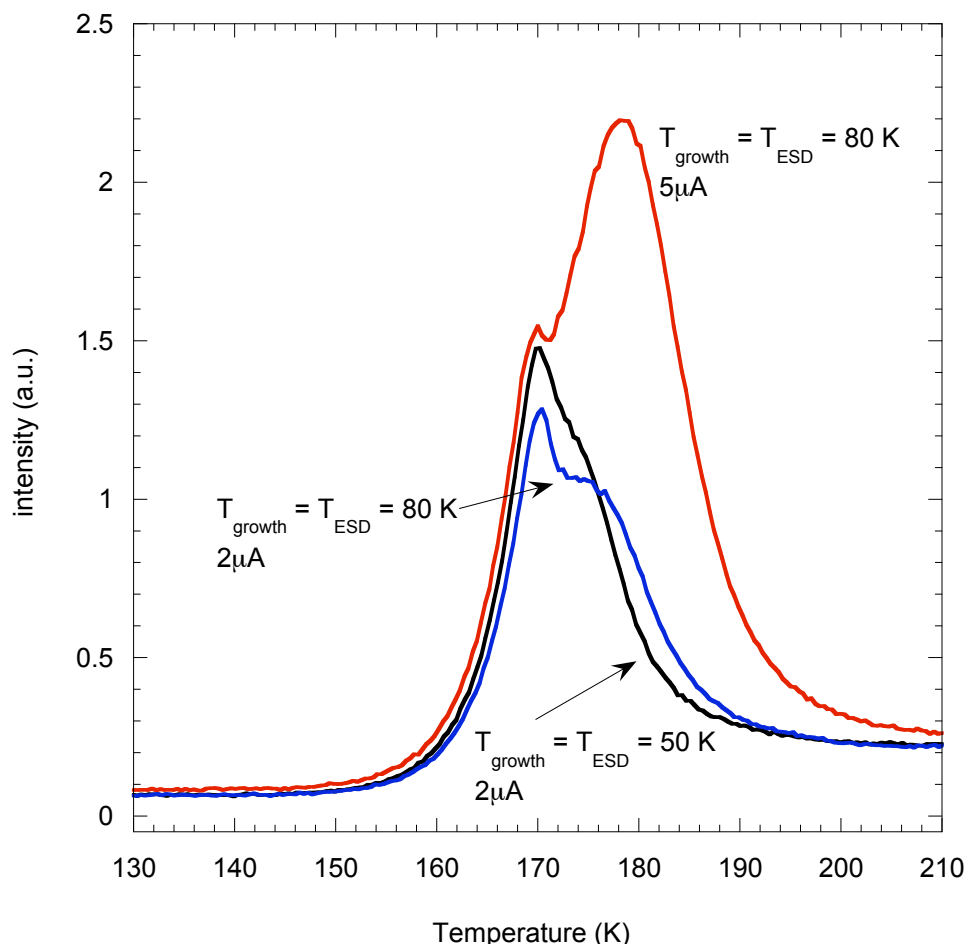
**Figure 2.7: TPD products after irradiation of 30 ML  $\text{CH}_3\text{OH}$  using 20 eV electrons.** 30 ML  $\text{CH}_3\text{OH}$  were deposited and irradiated at 80 K for 97 s. 20 eV electrons were used at a current of  $\sim 2\mu\text{A}$ . TPD products are shown above. Minor peaks are shown in panel A. Moderate peaks are shown in panel B. The major  $\text{CH}_3\text{OH}$  desorption peak occurs at  $\sim 170$  K (panel C).



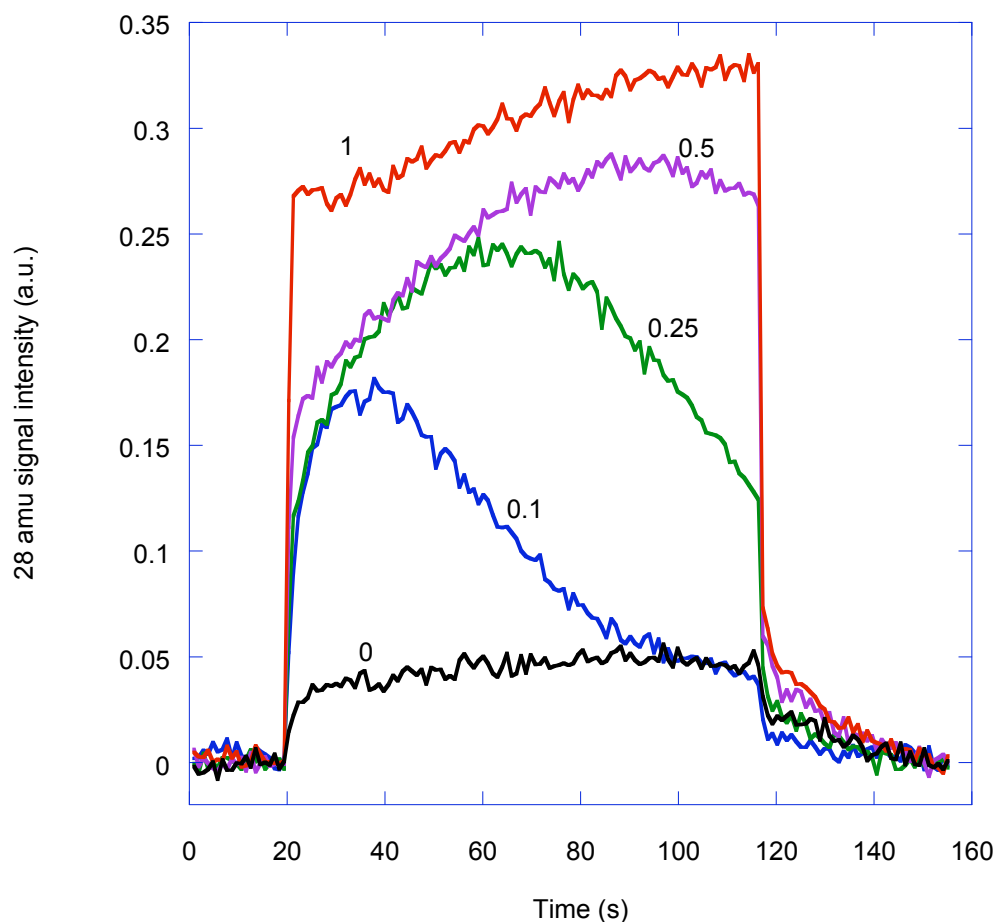
**Figure 2.8: TPD spectra of 30 ML  $\text{CH}_3\text{OH}$  following irradiation with 100 eV electrons.** 30 ML  $\text{CH}_3\text{OH}$  were deposited and irradiated at 80 K for 97 s. 100 eV electrons were used at a current of  $\sim 5\mu\text{A}$ . TPD products are shown above. Minor peaks are shown in panel A, moderate peaks in panel B. The major  $\text{CH}_3\text{OH}$  desorption peak occurs at  $\sim 170$  K (panel C). Panel D highlights the effect of increasing the energy deposited on the production of  $\text{H}_2\text{O}$ .



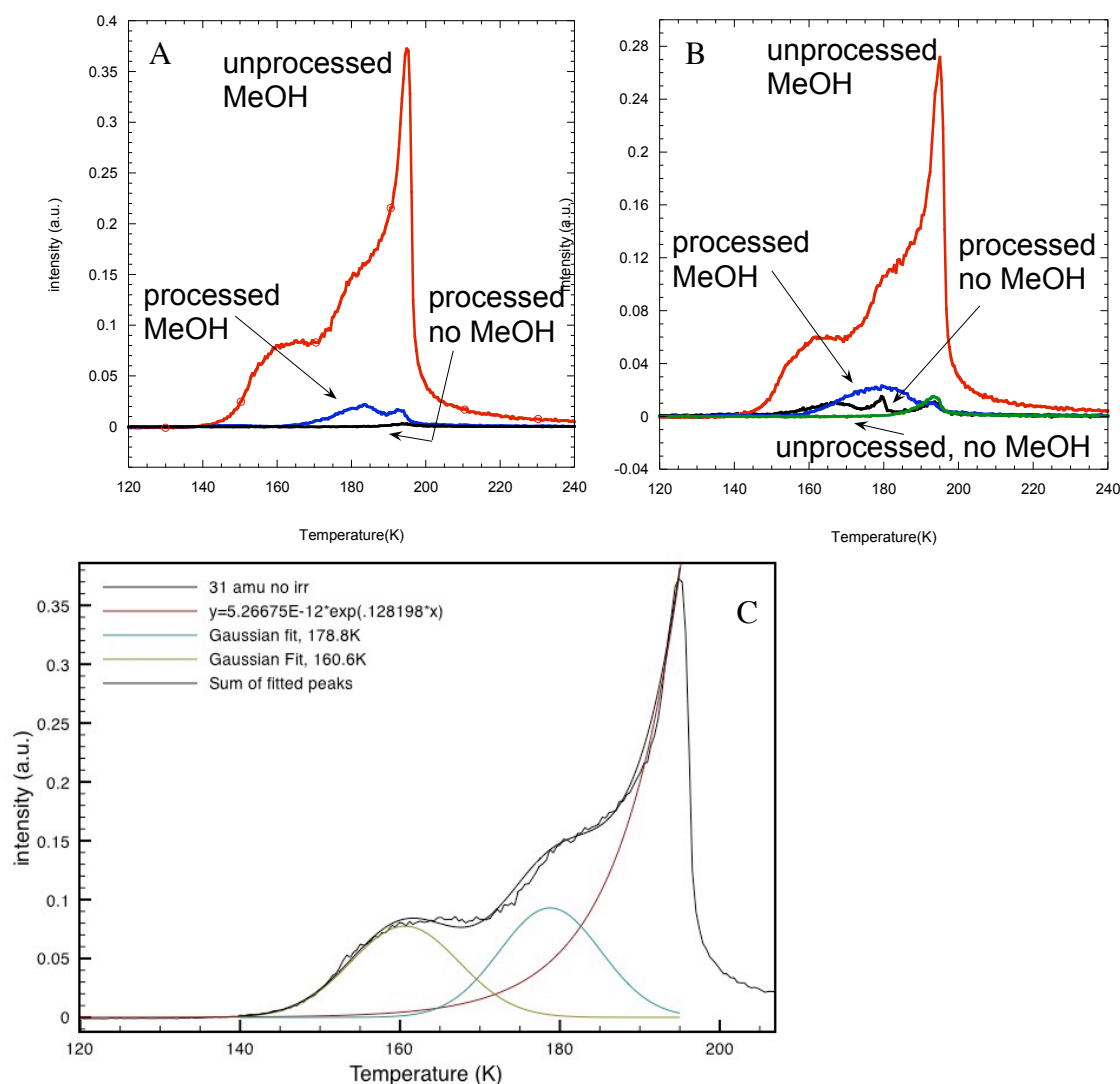
**Figure 2.9: TPD products after irradiation of 30 ML CH<sub>3</sub>OH at different temperatures.** 30 ML CH<sub>3</sub>OH were deposited and irradiated at either 25 K (blue) or 50 K (red) for 97 s. 100 eV electrons were used at a current of  $\sim 2\mu\text{A}$ . Little difference is observed in these signals (due to CH<sub>2</sub>O; the CH<sub>3</sub>OH signal is negligible at  $T < 40$  K) due to their different growth and irradiation temperatures. The 29 and 30 amu peaks at  $\sim 135$  K are also present when MeOH is irradiated at 80 K, but the peak present here at 110 K is absent.



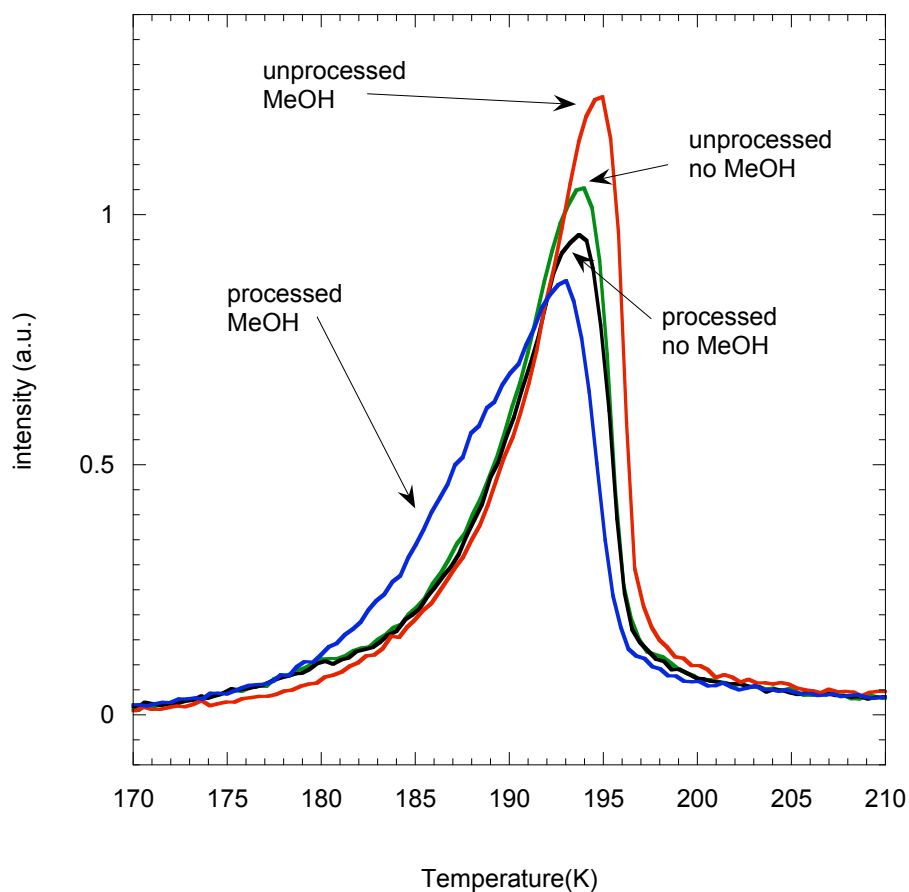
**Figure 2.10: Increasing the irradiation temperature to 80K increases the pure water signal.** 30 ML  $\text{CH}_3\text{OH}$  were deposited and irradiated at either 25 K (not shown), 50 K, or 80 K for 97 s. Little difference was observed in TPDs following irradiation at 25 and 50 K, so the 25 K signal is not included to increase clarity. Irradiations used 100 eV electrons at a current of either  $\sim 2\mu\text{A}$  or  $\sim 5\mu\text{A}$ , as indicated. Increasing the irradiation temperature from 50 K (black) to 80 K (blue), while holding the current constant, increased the high-temperature shoulder of the water signal associated with major water desorption. However, a much greater increase is seen when the electron current is raised (red). Increasing the current, and total energy deposited in the film, led to a large increase in the water signal, primarily at 180 K. Methanol desorbs at  $\sim 170$  K while water in a pure water film and in later mixed films desorbs at higher temperatures. The growth in the 180 K peak suggests the formation of large quantities of  $\text{H}_2\text{O}$  during ESD.



**Figure 2.11: CO desorption during ESD from  $n$  ML  $\text{CH}_3\text{OH}$  on 80 ML  $\text{H}_2\text{O}$ .**  $n$  ML  $\text{CH}_3\text{OH}$  were deposited at 80 K on 80 ML  $\text{H}_2\text{O}$ . The film was then irradiated beginning at 20 s and continuing until 117 s using 100 eV electrons at  $\sim 2\mu\text{A}$  current. Mass 28 was monitored to measure CO desorption. As more  $\text{CH}_3\text{OH}$  is deposited, the CO signal increases. At low coverages the CO signal rises and then drops off as the  $\text{CH}_3\text{OH}$  is consumed (for comparison, an examination of the  $\text{O}_2$  signals from this film show that  $\text{O}_2$  signals increase as the CO signals fall for coverages less than 0.5 ML  $\text{CH}_3\text{OH}$ ). At coverages greater than 0.5 ML  $\text{CH}_3\text{OH}$ , the CO continues to rise with time as more CO is generated from the thicker  $\text{CH}_3\text{OH}$  layer ( $\text{O}_2$  signals are not detected during the 97 s ESD in these films).

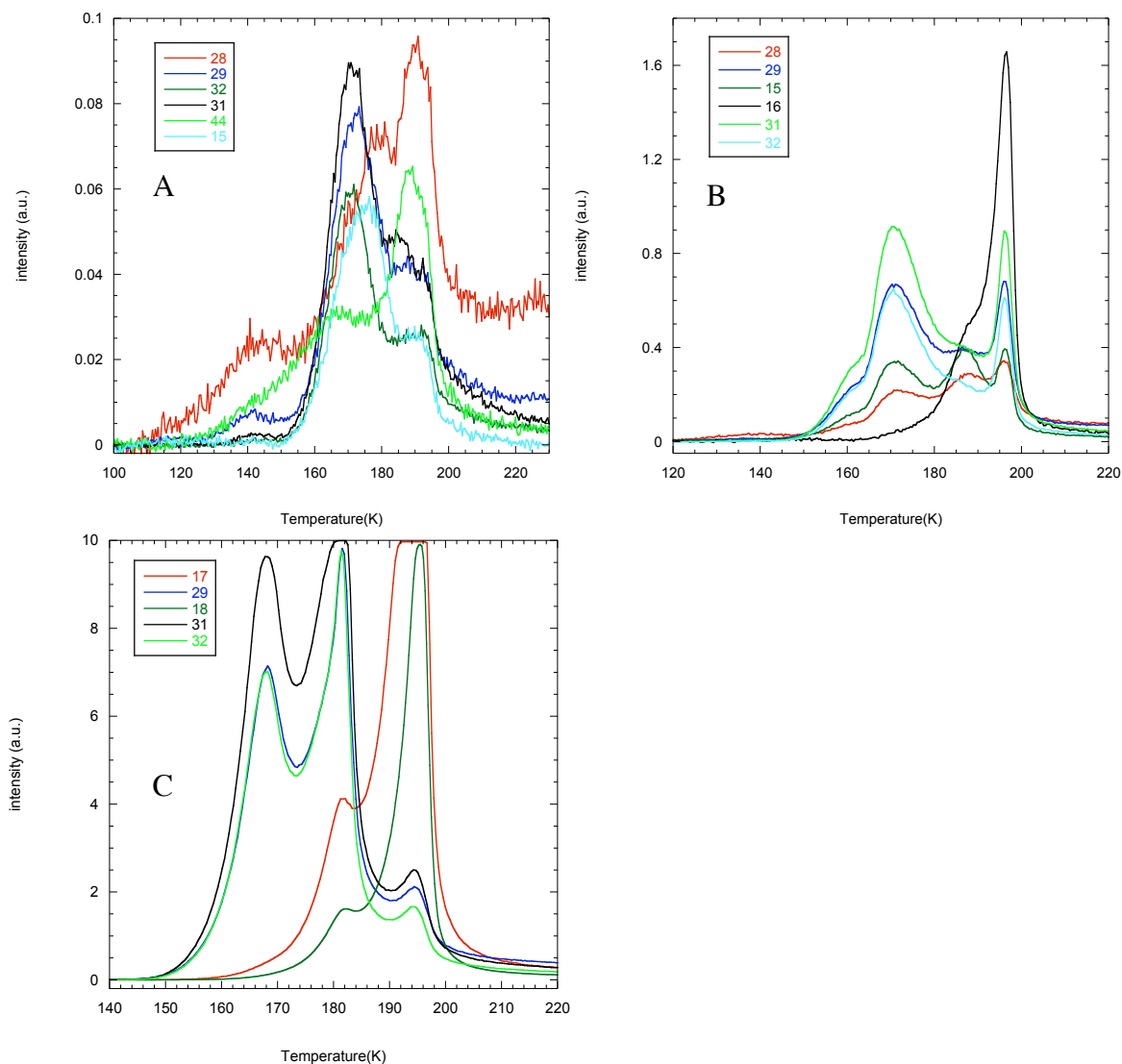


**Figure 2.12: Methanol desorption from a water film before and after irradiation,** compared to 31 amu (methanol, panel A) and 32 amu (methanol + O<sub>2</sub>, panel B) signals from a pure water film. Films of 80 ML ASW (“no MeOH”) and 1 ML CH<sub>3</sub>OH on 80 ML ASW (“MeOH”) were grown at 80 K. “Unprocessed” films were not irradiated; “processed” films were irradiated for 97 s using 100 eV electrons at ~2  $\mu$ A current at 80 K. In pure water films, the 31 amu signal is negligible, but the 32 amu signal has a small peak in both processed and unprocessed films at ~193 K. Upon irradiation, two additional peaks appear in the pure water film at ~165K and 180K, the result of O<sub>2</sub> formation. In CH<sub>3</sub>OH-capped films, the main effect of processing is the removal of methanol by desorption. Panel B shows that the addition of CH<sub>3</sub>OH to the film eliminates the O<sub>2</sub> signal seen in processed pure water films. Panel C shows the deconvolution of the three peaks composing the methanol signal from an unprocessed 1 ML CH<sub>3</sub>OH/80 ML ASW film.

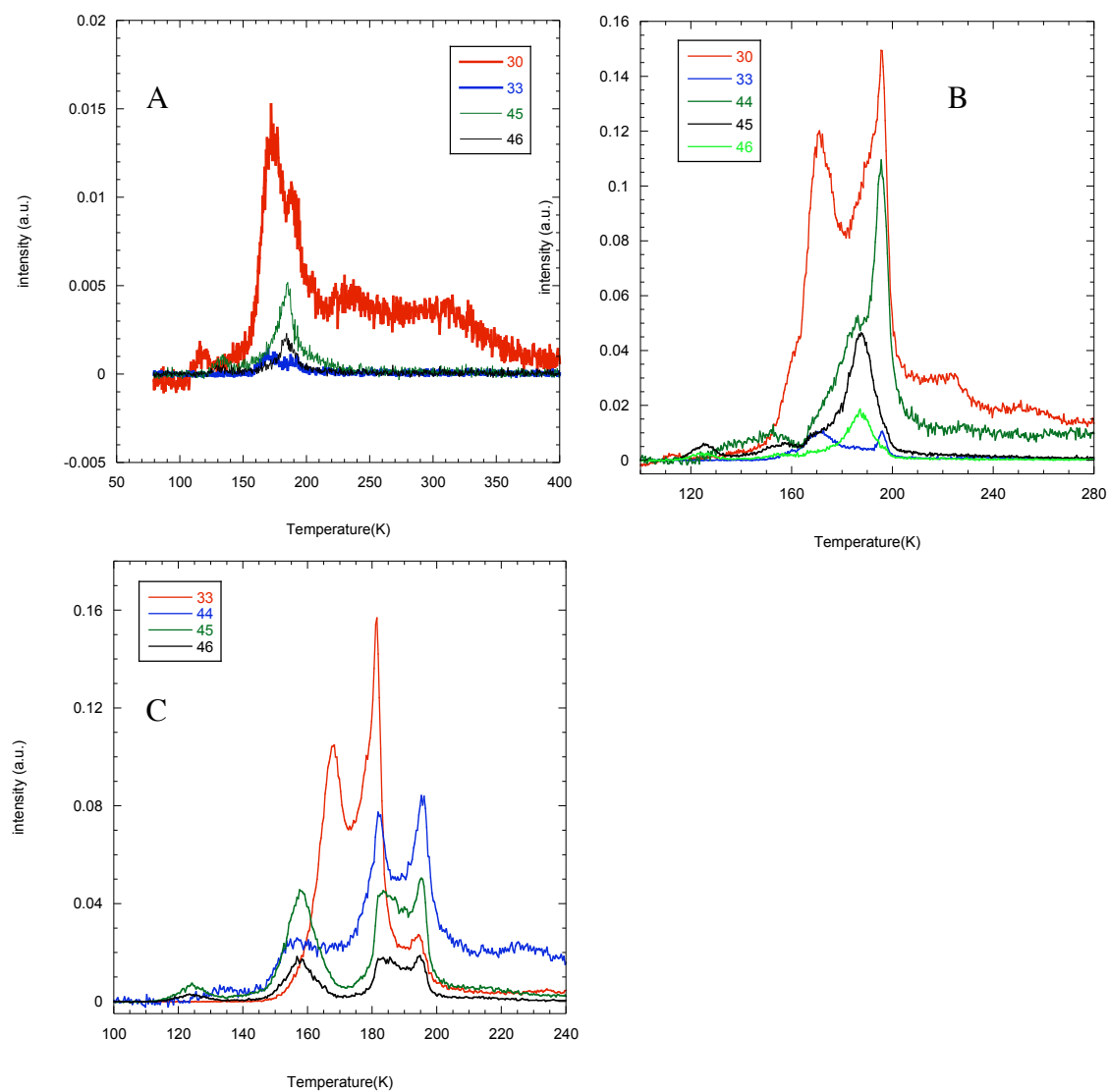


**Figure 2.13: The addition of methanol to a water film creates additional atomic oxygen, detected in the TPD.** Films of 80 ML ASW (“no MeOH”) and 1 ML CH<sub>3</sub>OH on 80 ML ASW (“MeOH”) were grown at 80 K. “Unprocessed” films were not irradiated; “processed” films were irradiated for 97 s using 100 eV electrons at ~2  $\mu$ A current at 80 K. The 16 amu signal shown above indicates that processed and unprocessed pure water films and unprocessed CH<sub>3</sub>OH/H<sub>2</sub>O films produce similar quantities of O. Processed CH<sub>3</sub>OH-capped films produce additional O (not CH<sub>4</sub>, as the 15 amu signal is very small) at ~185 K.

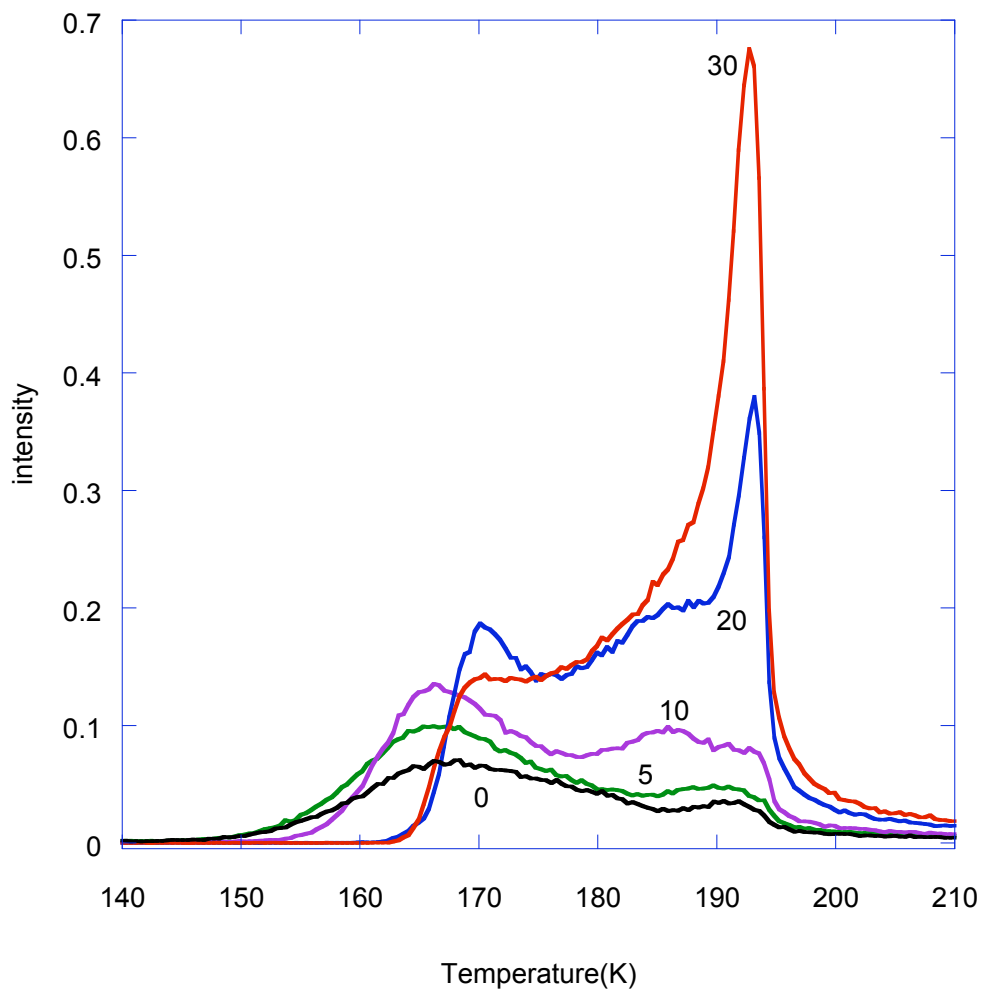




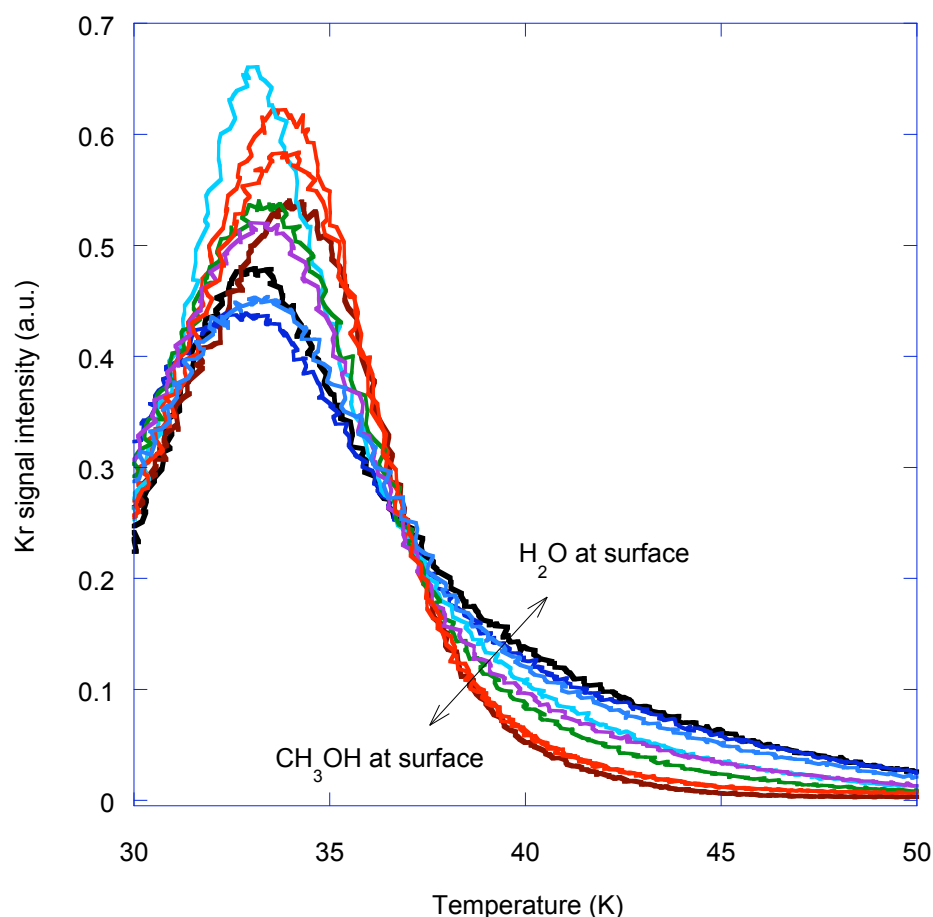
**Figure 2.14: Major TPD peaks of a) 4 ML b) 10 ML and c) 30 ML CH<sub>3</sub>OH on 80 ML ASW after irradiation.** Films of a) 4 ML CH<sub>3</sub>OH b) 10 ML CH<sub>3</sub>OH and c) 30 ML CH<sub>3</sub>OH were grown atop 80 ML H<sub>2</sub>O at 80 K. The films were irradiated at 80 K using 100 eV electrons at a current of  $\sim 5\mu\text{A}$  for 97 s. Major TPD peaks of each film are shown above and discussed in the text.



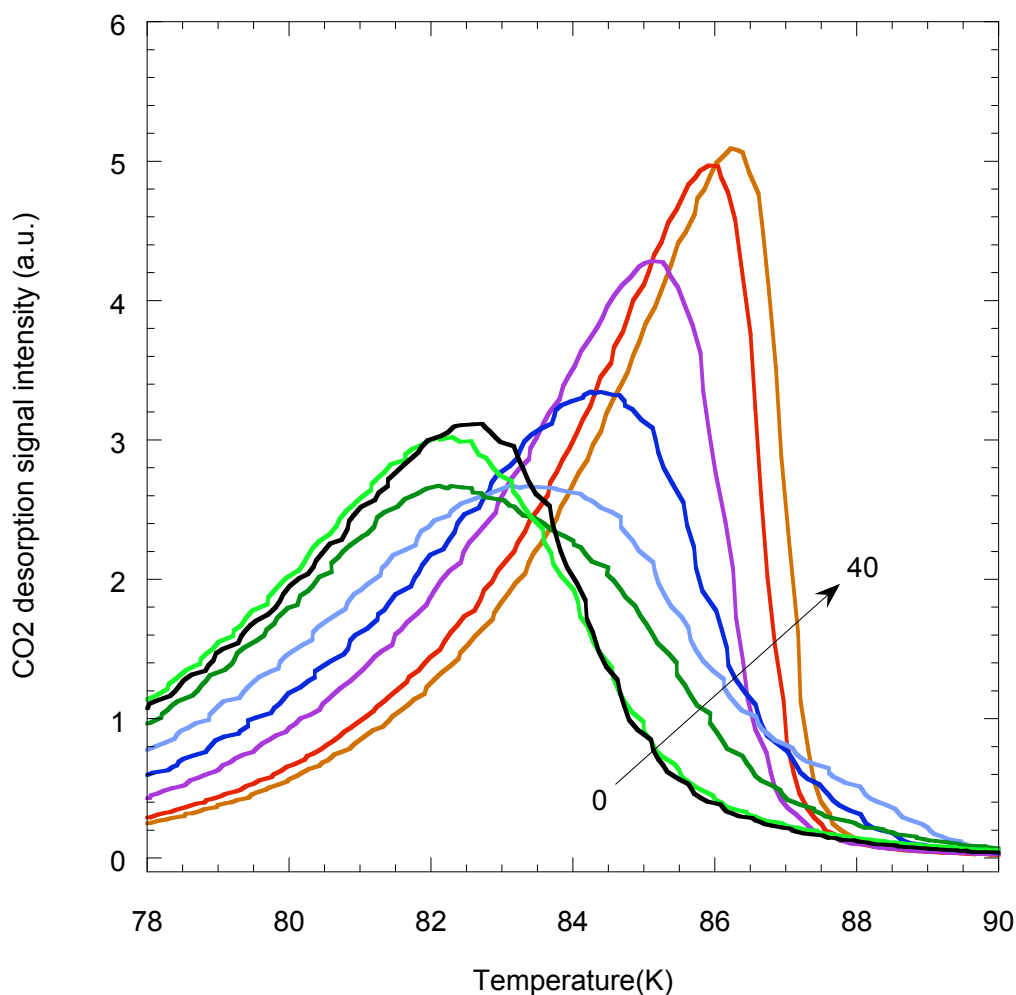
**Figure 2.15: Minor TPDs of a) 4 ML b) 10 ML and c) 30 ML  $\text{CH}_3\text{OH}$  on 80 ML  $\text{ASW}$  after irradiation.** Films of a) 4 ML  $\text{CH}_3\text{OH}$  b) 10 ML  $\text{CH}_3\text{OH}$  and c) 30 ML  $\text{CH}_3\text{OH}$  were grown atop 80 ML  $\text{H}_2\text{O}$  at 80 K. The films were irradiated at 80 K using 100 eV electrons at a current of  $\sim 5\mu\text{A}$  for 97 s.



**Figure 2.16: 31 amu TPD from selected sandwich films.**  $n$  ML  $\text{H}_2\text{O}$  were deposited atop 1 ML  $\text{CH}_3\text{OH}$  on  $80-n$  ML  $\text{H}_2\text{O}$  at 25 K. The film was then irradiated at 25 K for 97 s using 100 eV electrons at  $\sim 2\mu\text{A}$  before the TPD shown above was collected. As the capping water layer thickens, methanol desorption is delayed. No change in methanol desorption is observed for  $n \leq 2$  ML  $\text{H}_2\text{O}$ .



**Figure 2.17: Surface area measurements using Kr.** Various films were prepared at 80 K prior to being dosed with Kr at  $T$  less than 30 K. While there is no clear trend in the Kr desorption signals at  $T$  less than 37 K, at  $T$  greater than 37 K an increased surface concentration of water correlates to a longer retention of Kr. Pure water (black) and pure methanol (maroon) films show the greatest difference at  $T$  greater than 37 K. Methanol capped films are shown in red (1 ML  $\text{CH}_3\text{OH}$  cap) and purple (0.5 ML  $\text{CH}_3\text{OH}$  cap).  $n$  ML  $\text{H}_2\text{O}$ / 1 ML  $\text{CH}_3\text{OH}$ / 80- $n$  ML  $\text{H}_2\text{O}$  sandwich films were also grown at 80 K, where the effects of surfaction should leave decreasing amounts of  $\text{CH}_3\text{OH}$  at the surface as  $n$  increases; these films are shown in blue, with a darker color blue corresponding to a thicker capping water film (10, 6, and 4 ML  $\text{H}_2\text{O}$ ). An additional sandwich film of 2 ML  $\text{H}_2\text{O}$ / 1 ML  $\text{CH}_3\text{OH}$ / 78 ML  $\text{H}_2\text{O}$  was grown under the same conditions and is shown in green. Note that the 0.5 ML  $\text{CH}_3\text{OH}/\text{H}_2\text{O}$  capped film (purple) shows very similar desorption characteristics at  $T$  greater than 37 K to the  $n = 2$  and  $n = 4$  sandwich films.



**Figure 2.18: CO<sub>2</sub> surface area measurements.** Sandwich films of  $n$  ML H<sub>2</sub>O / 1 ML CH<sub>3</sub>OH/80- $n$  ML H<sub>2</sub>O were grown at 80 K and then exposed to 120 torr s of CO<sub>2</sub> at 21 K. The desorption signal of CO<sub>2</sub> was then measured. Values of  $n$  shown above include [0, 1, 5, 10, 15, 20, 30, and 40]. Because of surfaction, sandwiches with thinner water capping layers have increased surface concentrations of methanol. These films do not retain CO<sub>2</sub> as long as the water-rich surfaces, similar to the Kr desorption completion seen in Figure 2.17.

**Table 2.3: Pure methanol TPD products**

Pure methanol, unprocessed:

Peak Temperature (K)	Species
172	CH <sub>3</sub> OH
315	unassigned
550	CH <sub>2</sub> O

Pure methanol, processed, 20eV, 2μA:

Peak Temperature (K)	Species
170	CH <sub>3</sub> OH, CH <sub>2</sub> O
109,128	CH <sub>4</sub> , CH <sub>3</sub> OCH <sub>3</sub>
550	H <sub>2</sub> CO
650	C <sub>2</sub> H <sub>4</sub>

Pure methanol, processed, 100eV, 5μA:

Peak Temperature (K)	Species
170	CH <sub>3</sub> OH, CH <sub>2</sub> O
125	CH <sub>3</sub> OCH <sub>3</sub>
139	CH <sub>4</sub> , CO, CO <sub>2</sub> , CH <sub>3</sub> OOCH <sub>3</sub> , plus CH <sub>3</sub> CH <sub>2</sub> OH *
153	(CH <sub>2</sub> OH) <sub>2</sub>
180, 232, 480	H <sub>2</sub> O
585	Unassigned
610	unassigned

\*Ethanol is the presumed fifth source. On the basis of cracking patterns alone, a combination of C<sub>2</sub>H<sub>6</sub> + HCOOH + (CH<sub>2</sub>OH)<sub>2</sub> or C<sub>2</sub>H<sub>6</sub>+ CH<sub>3</sub>OCH<sub>3</sub> + (CH<sub>2</sub>OH)<sub>2</sub> fits as well as ethanol, but is treated as less likely since three species must form instead of one.

**Table 2.4: TPD products, methanol-capped films:**

1 ML Methanol –capped water films, unprocessed:

Peak Temperature (K)	Species
195	H <sub>2</sub> O + entrained CH <sub>3</sub> OH
161	CH <sub>3</sub> OH
179	CH <sub>3</sub> OH + H <sub>2</sub> O
340	CH <sub>3</sub> OH

1 ML Methanol-capped water films, processed, 100eV, ~2μA:

Peak Temperature (K)	Species
193	H <sub>2</sub> O + residual CH <sub>3</sub> OH
180	CH <sub>3</sub> OH + H <sub>2</sub> O
187	O
265	CH <sub>2</sub> O
315	CH <sub>3</sub> OH + CH <sub>2</sub> O
625	C <sub>2</sub> H <sub>6</sub>

4, 10, and 30 ML Methanol-capped water films, processed, 100eV, ~5μA:

Peak Temperature (K)	Species
195	H <sub>2</sub> O + residual CH <sub>3</sub> OH, CO, CO <sub>2</sub>
170 <sup>A</sup>	CH <sub>3</sub> OH, H <sub>2</sub> O, CO, CO <sub>2</sub>
160 <sup>A</sup>	CH <sub>3</sub> OH, CO, CO <sub>2</sub>
187 <sup>B</sup>	CH <sub>3</sub> OH + H <sub>2</sub> O, CH <sub>3</sub> CH <sub>2</sub> OH, CH <sub>3</sub> OCH <sub>3</sub>
125 <sup>C</sup>	CH <sub>3</sub> OCH <sub>3</sub>
158 <sup>D</sup>	unassigned
265	CH <sub>2</sub> O
315	CH <sub>3</sub> OH + CH <sub>2</sub> O
625	C <sub>2</sub> H <sub>6</sub>

<sup>A</sup> This peak shifts to higher temperatures by ~10K with increasing CH<sub>3</sub>OH dose.

<sup>B</sup> Not present at 4 ML CH<sub>3</sub>OH dose, this peak appears to be the result of methanol radiatively mixed with water plus trace amounts of either ethanol or dimethyl ether.

<sup>C</sup> Not present at 4 ML CH<sub>3</sub>OH dose.

<sup>D</sup> Present at 30 ML CH<sub>3</sub>OH dose. Likely due to either ethanol or dimethyl ether.

**Table 2.5: TPD products, sandwich films:**

Sandwich films: n ML H<sub>2</sub>O/1 ML CH<sub>3</sub>OH/80-n ML H<sub>2</sub>O/TiO<sub>2</sub> (110), processed, 100eV, ~2μA:

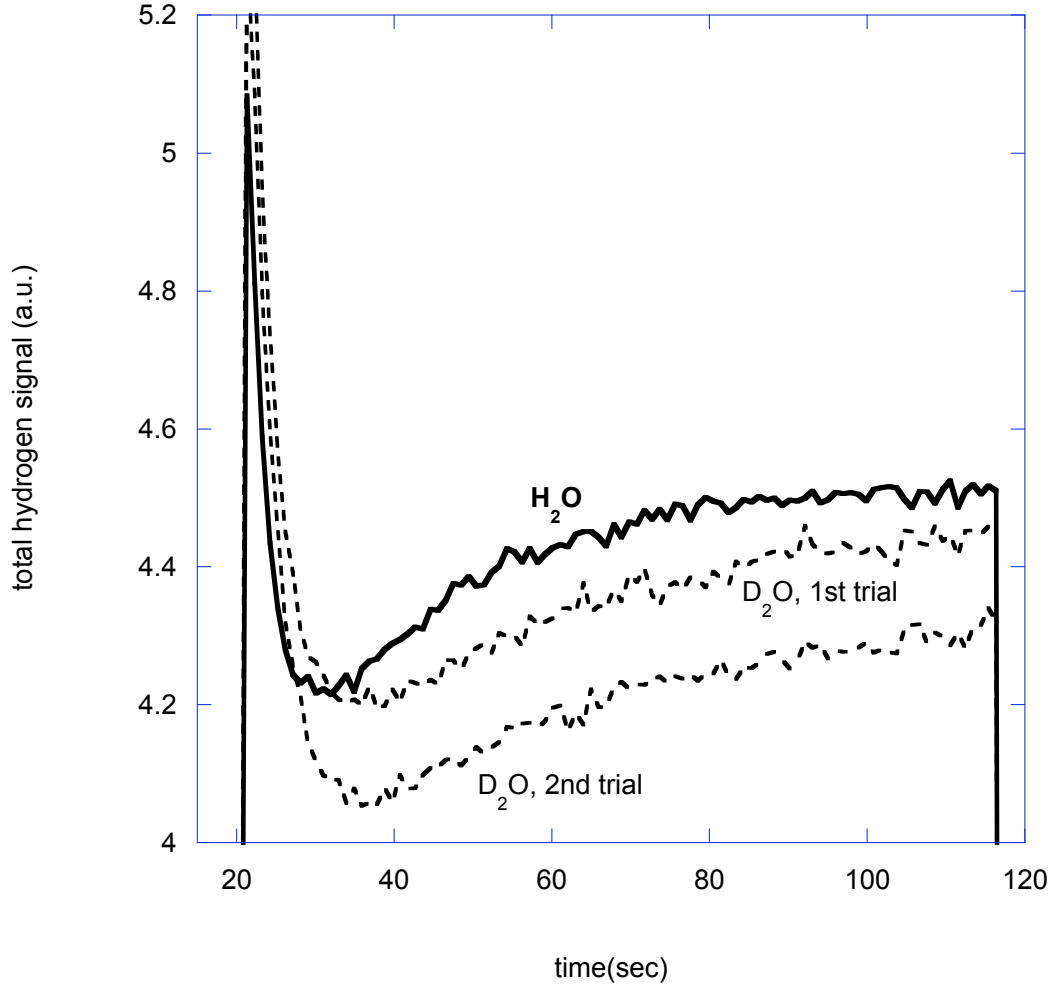
Peak Temperature (K)	Species
193	Water + CH <sub>3</sub> OH
170 <sup>E</sup>	CH <sub>3</sub> OH, H <sub>2</sub> O
270	CH <sub>2</sub> O
550	O <sub>2</sub>
90 <sup>F</sup>	Unassigned
130 <sup>F</sup>	Unassigned
160 <sup>F</sup>	Unassigned

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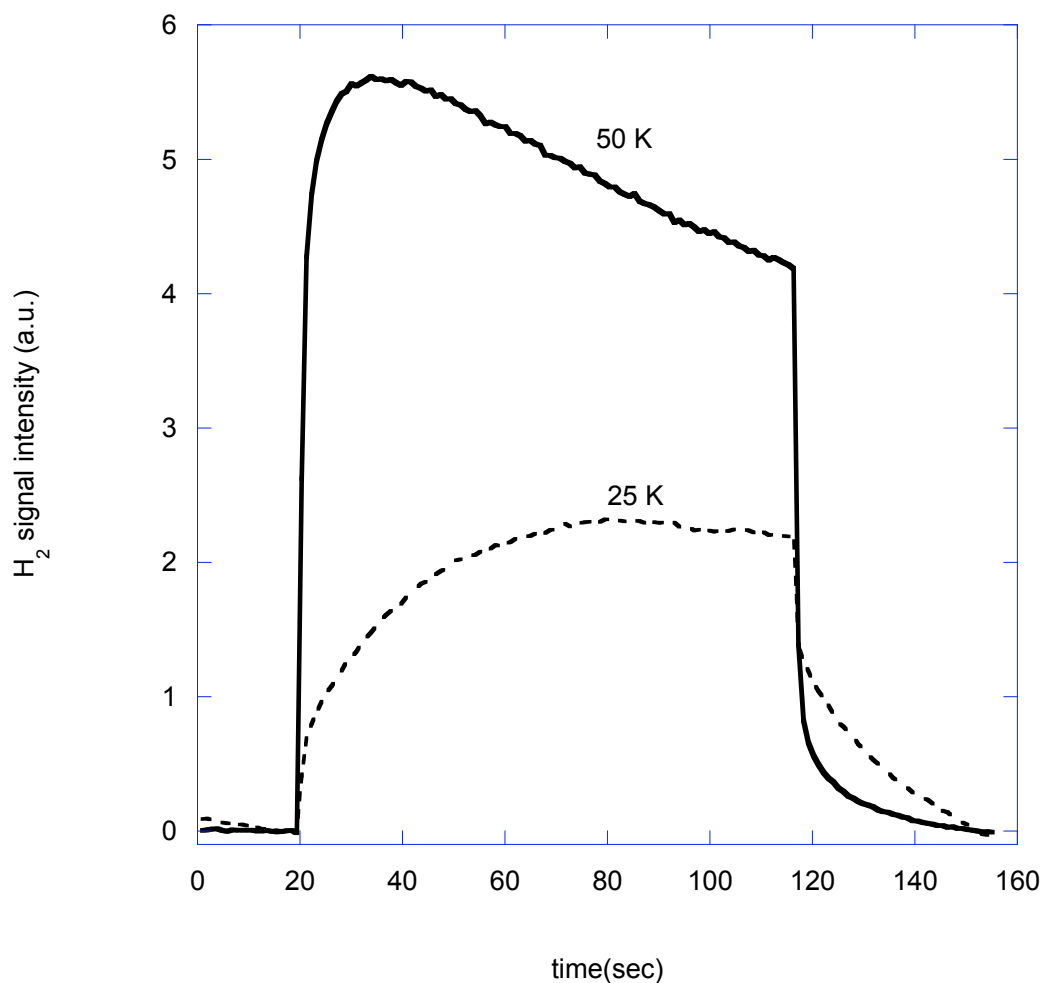
<sup>E</sup> As the water capping layer increases in thickness, this peak shifts from 165 to 170 K.

<sup>F</sup> trace quantities.

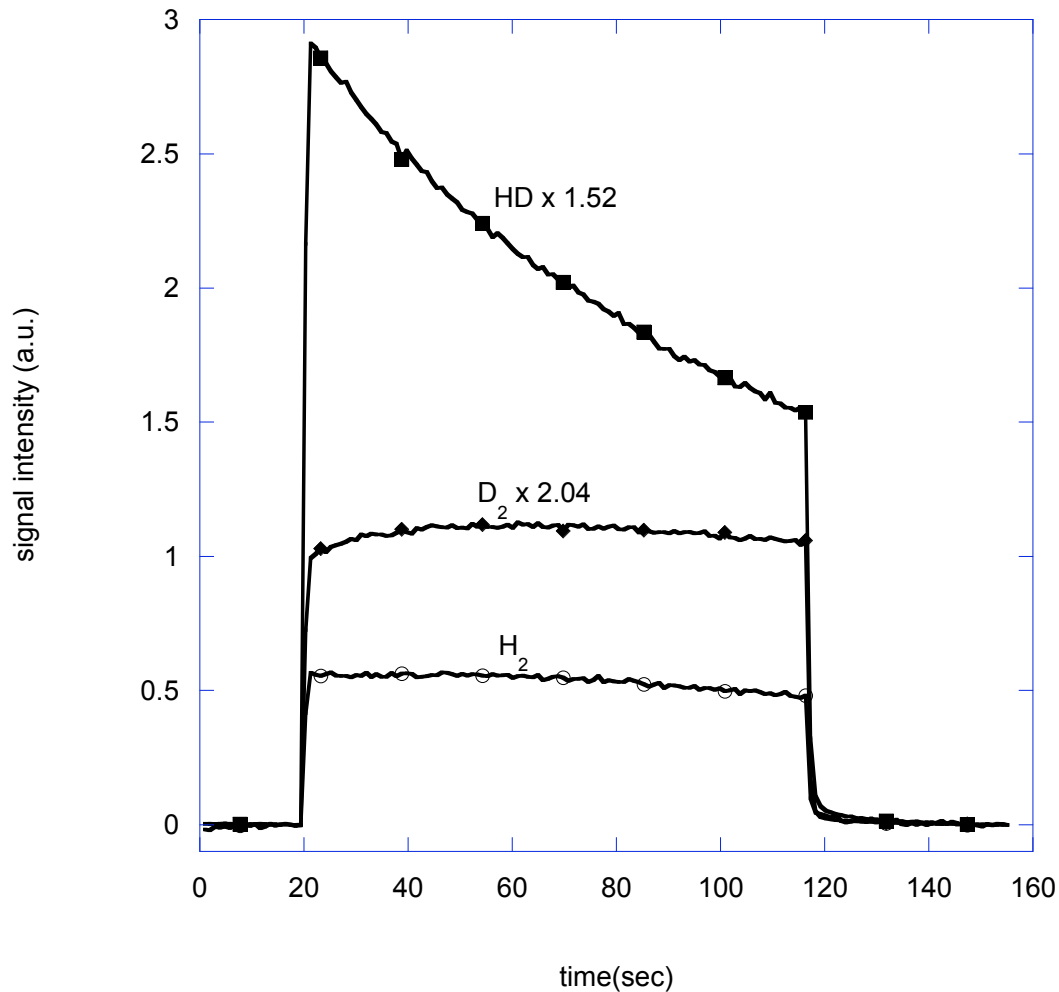




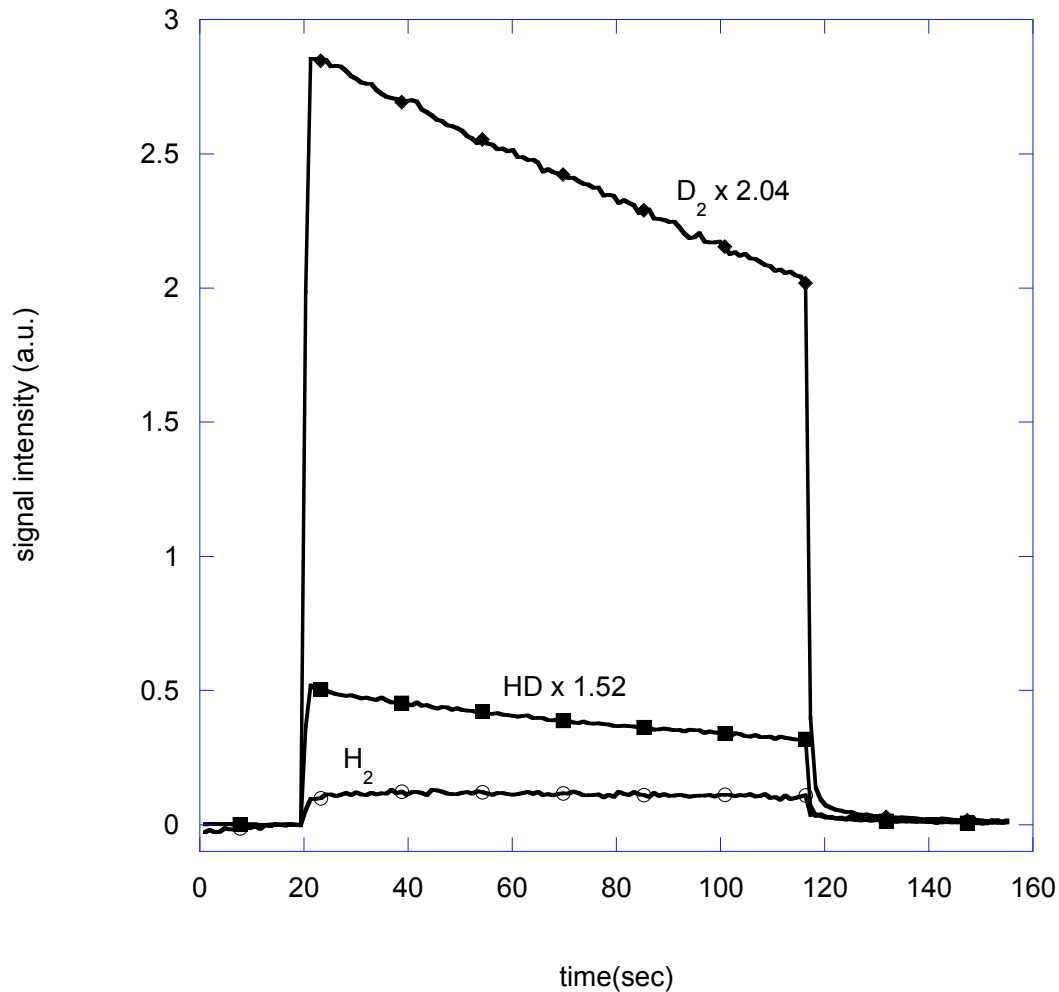
**Figure 3.1: Hydrogen production from H<sub>2</sub>O and D<sub>2</sub>O is similar.** 100 ML H<sub>2</sub>O and D<sub>2</sub>O films were irradiated beginning at 20 s and continuing until 117 s. Irradiation was performed at 80 K using 100 eV electrons at  $\sim 2\mu\text{A}$  current. Masses 2, 3, and 4 were measured. Using the relative sensitivities of  $S_{\text{H}_2} = 1$ ,  $S_{\text{HD}} = 1.52$ , and  $S_{\text{D}_2} = 2.04$ , the total hydrogen produced from the films was calculated (as described in the text). The total hydrogen signal from D<sub>2</sub>O and H<sub>2</sub>O are shown above for comparison. There is a 5-10% difference between the summed D<sub>2</sub>O signals and the H<sub>2</sub>O signal. The difference seen in the two D<sub>2</sub>O signals is largely due to changes in the background H<sub>2</sub> level during the two experiments, and is the same size as the differences seen between trials for the same reason.



**Figure 3.2: Temperature affects H<sub>2</sub> formation and desorption from CH<sub>3</sub>OH.** 30 ML CH<sub>3</sub>OH were dosed and irradiated ( $T_{\text{dose}} = T_{\text{irr}}$ ) at 25 K and 50 K to determine the effects of temperature upon the H<sub>2</sub> ESD signal. The films were irradiated beginning at 20 s and continuing until 117 s using 100 eV electrons at a current of  $\sim 2\mu\text{A}$ . Significantly more H<sub>2</sub> is produced during ESD at higher temperatures.



**Figure 3.3: Molecular hydrogen isotopologues desorbing from CD<sub>3</sub>OH.** 10 ML CD<sub>3</sub>OH were deposited and irradiated at 80 K. Irradiation began at 20 s and continued until 117 s, using 100 eV electrons at a current of  $\sim 2 \mu\text{A}$ . Signal intensities for H<sub>2</sub>, HD, and D<sub>2</sub> were measured during irradiation. HD and D<sub>2</sub> signals are corrected for decreased QMS sensitivity by scaling using sensitivity factors of 1.52 and 2.04 respectively.



**Figure 3.4: Molecular hydrogen isotopologues desorbing from CD<sub>3</sub>OD.** 10 ML CD<sub>3</sub>OD were deposited and irradiated at 80 K. Irradiation began at 20 s and continued until 117 s, using 100 eV electrons at a current of  $\sim 2 \mu\text{A}$ . Signal intensities for H<sub>2</sub>, HD, and D<sub>2</sub> were measured during irradiation. HD and D<sub>2</sub> signals are corrected for decreased QMS sensitivity by scaling using sensitivity factors of 1.52 and 2.04 respectively.

**Table 3.1: Sources of hydrogen species from each isotopologue of methanol**

	CH <sub>3</sub> OH	CD <sub>3</sub> OH	CD <sub>3</sub> OD
H <sub>2</sub>	<sup>m</sup> H <sub>2</sub> , <sup>a</sup> H <sub>2</sub> , <sup>m</sup> H <sup>a</sup> H, <sup>m</sup> H <sup>c</sup> H, <sup>a</sup> H <sup>c</sup> H, background	<sup>a</sup> H <sub>2</sub> , <sup>a</sup> H <sup>c</sup> H, background	background
HD	Background (minimal)	<sup>m</sup> D <sup>a</sup> H, <sup>m</sup> D <sup>c</sup> H	<sup>m</sup> D <sup>c</sup> H, <sup>a</sup> D <sup>c</sup> H
D <sub>2</sub>	none	<sup>m</sup> D <sub>2</sub>	<sup>m</sup> D <sub>2</sub> , <sup>a</sup> D <sub>2</sub> , <sup>m</sup> D <sup>a</sup> D

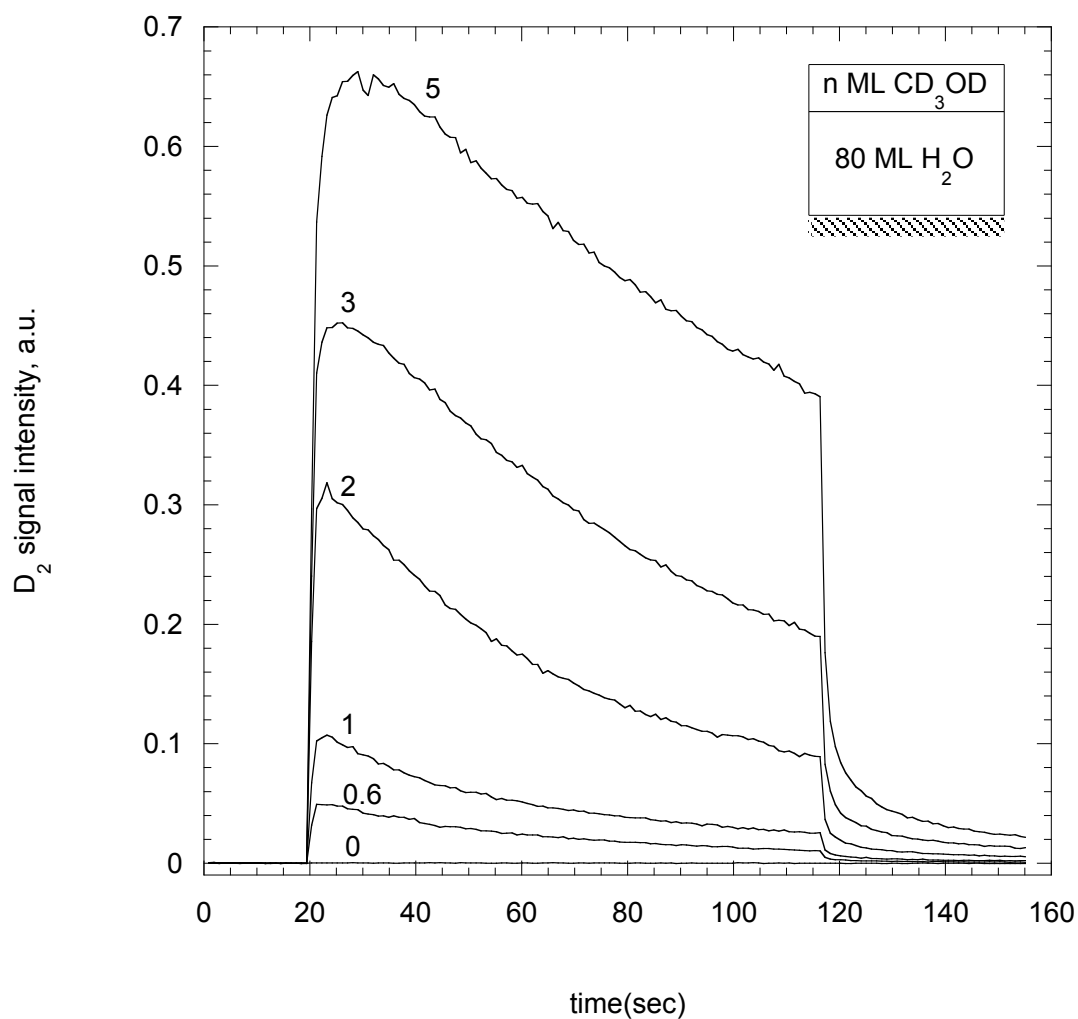
<sup>m</sup>H = methyl hydrogen

<sup>a</sup>H = alcoholic hydrogen

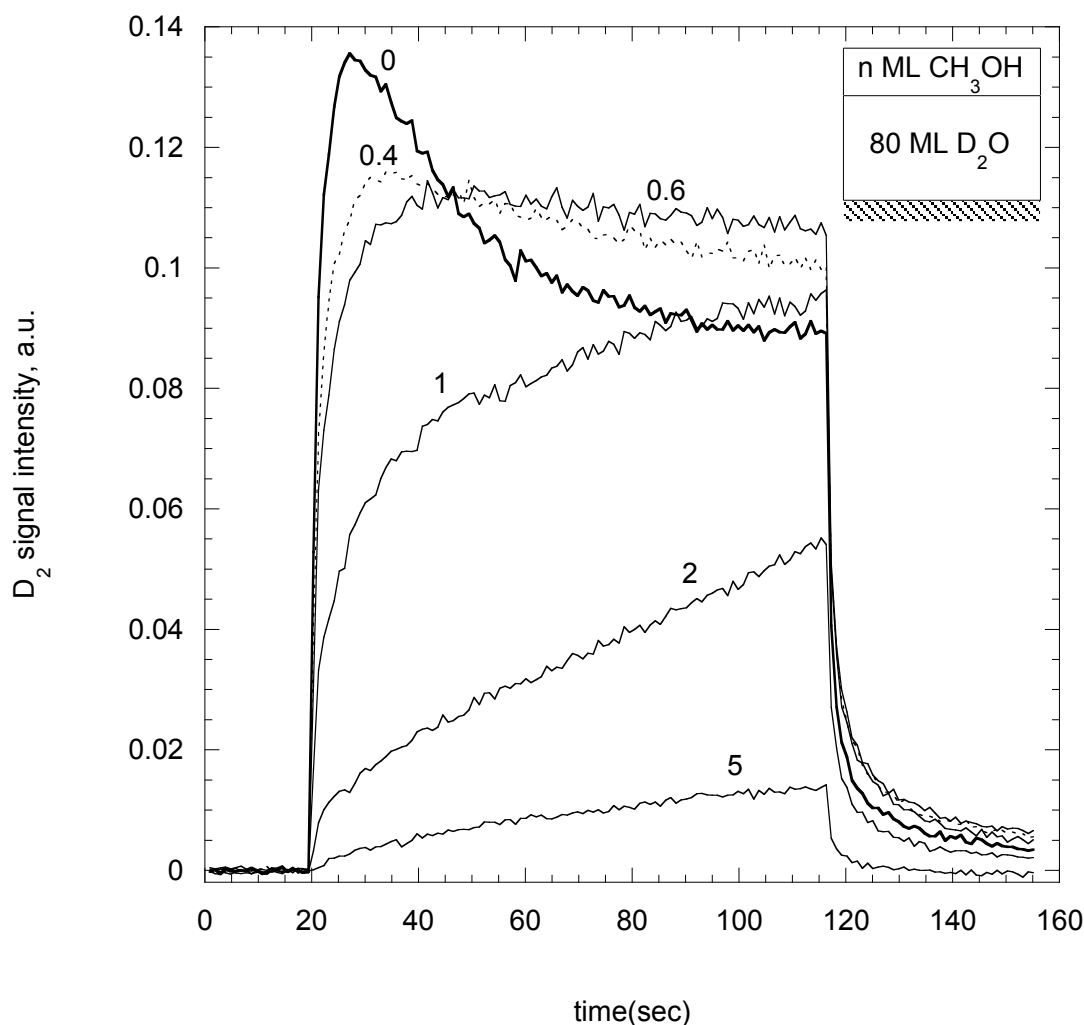
<sup>c</sup>H = hydrogen adsorbed to chamber walls

<sup>m</sup>D = methyl deuterium

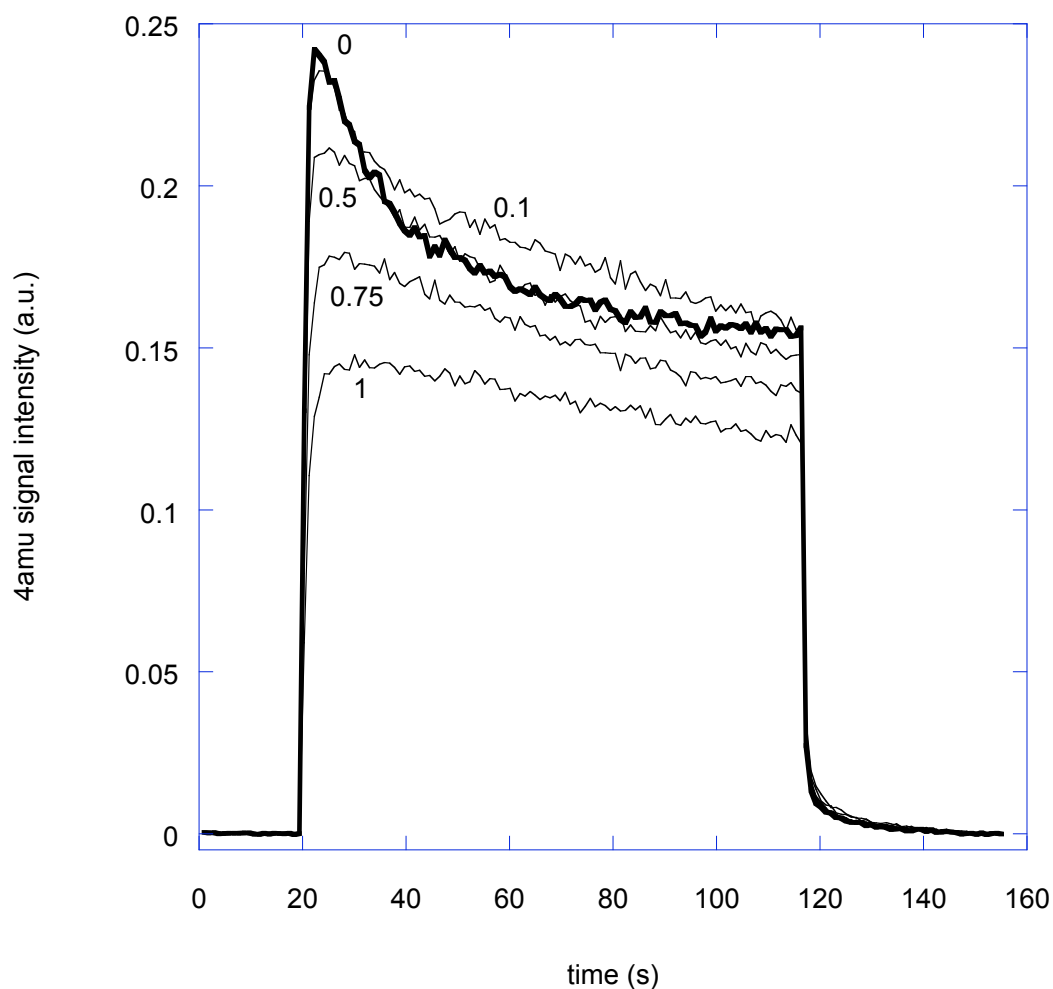
<sup>a</sup>D = alcoholic deuterium



**Figure 3.5:  $D_2$  produced in methanol ( $CD_3OD$ ) layer.**  $n$  ML  $CD_3OD$  were deposited on 80 ML  $H_2O$  at 50 K. The film was irradiated at 50 K and the  $D_2$  signal monitored, beginning at 20 s and continuing until 117 s, using 100 eV electrons at a current of  $\sim 2 \mu A$ .  $D_2$  appears promptly with the onset of the impinging electrons. Selected doses are shown above; as  $CD_3OD$  dose increased, the  $D_2$  signal also rose. Note: as these are all  $D_2$  signals with equal sensitivities, they have not been corrected for decreased QMS sensitivity to  $D_2$ .

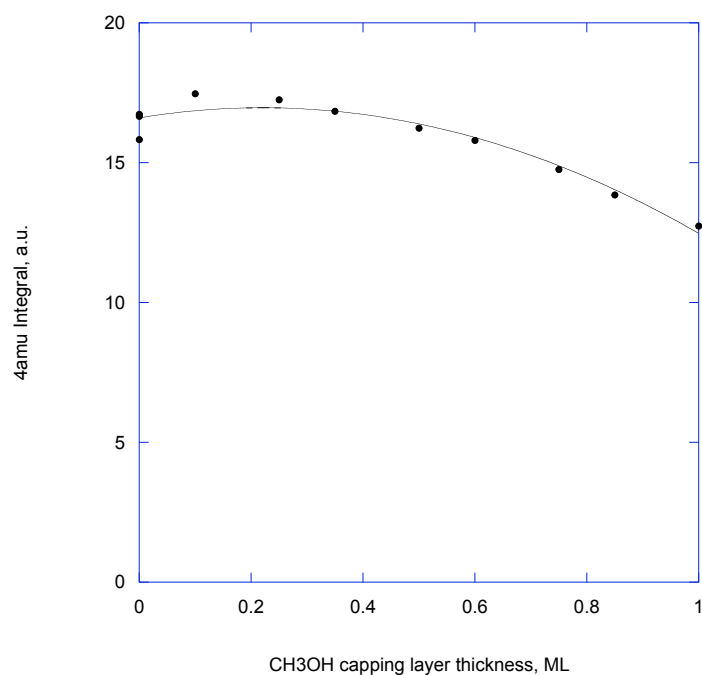


**Figure 3.6: D<sub>2</sub> produced from water beneath a methanol cap.**  $n$  ML CH<sub>3</sub>OH were deposited on 80 ML D<sub>2</sub>O at 50 K. The film was irradiated at 50 K and the D<sub>2</sub> signal monitored, beginning at 20 s and continuing until 117 s, using 100 eV electrons at a current of  $\sim 2$   $\mu$ A. Selected doses are shown above. D<sub>2</sub> appears promptly with the onset of the impinging electrons in the pure D<sub>2</sub>O film. As CD<sub>3</sub>OD coverage increased, the prompt D<sub>2</sub> signal decreased. While the late D<sub>2</sub> signal increased at low coverages of CH<sub>3</sub>OH, at coverages greater than 0.6 ML it is reduced. Note: as these are all D<sub>2</sub> signals with equal sensitivities, they have not been corrected for decreased QMS sensitivity to D<sub>2</sub>.

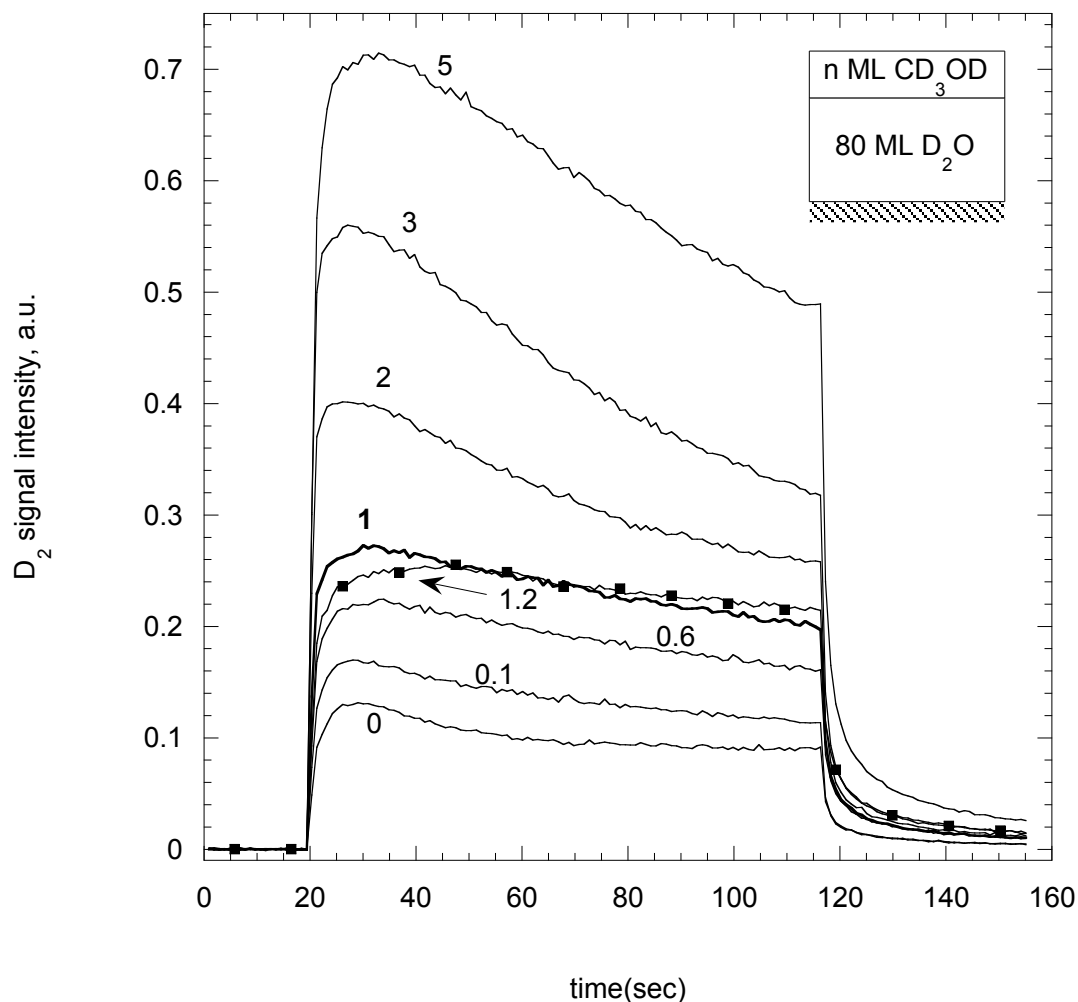


**Figure 3.7: The addition of CH<sub>3</sub>OH to the surface of D<sub>2</sub>O inhibits D<sub>2</sub> formation.** *n* ML CH<sub>3</sub>OH were deposited at 50 K on 20 ML D<sub>2</sub>O over 60 ML H<sub>2</sub>O. The film was irradiated at 80 K and the D<sub>2</sub> signal monitored, beginning at 20 s and continuing until 117 s, using 100 eV electrons at a current of ~2  $\mu$ A. D<sub>2</sub> appears promptly with the onset of the impinging electrons in the pure D<sub>2</sub>O film. As CD<sub>3</sub>OD coverage increased, the D<sub>2</sub> signal decreased, in agreement with CH<sub>3</sub>OH blocking D<sub>2</sub>O desorption and/or excitation. Note: as these are all D<sub>2</sub> signals with equal sensitivities, they have not been corrected for decreased QMS sensitivity to D<sub>2</sub>.

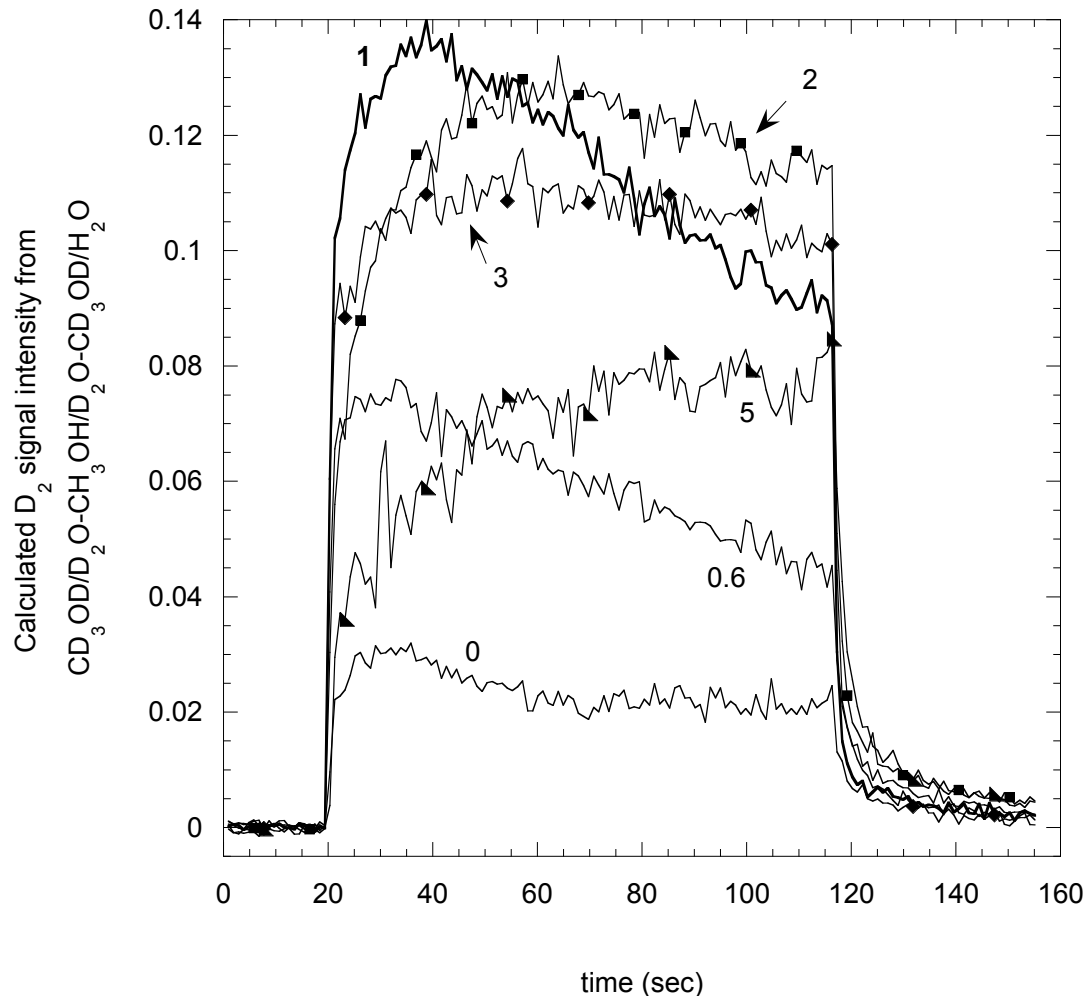




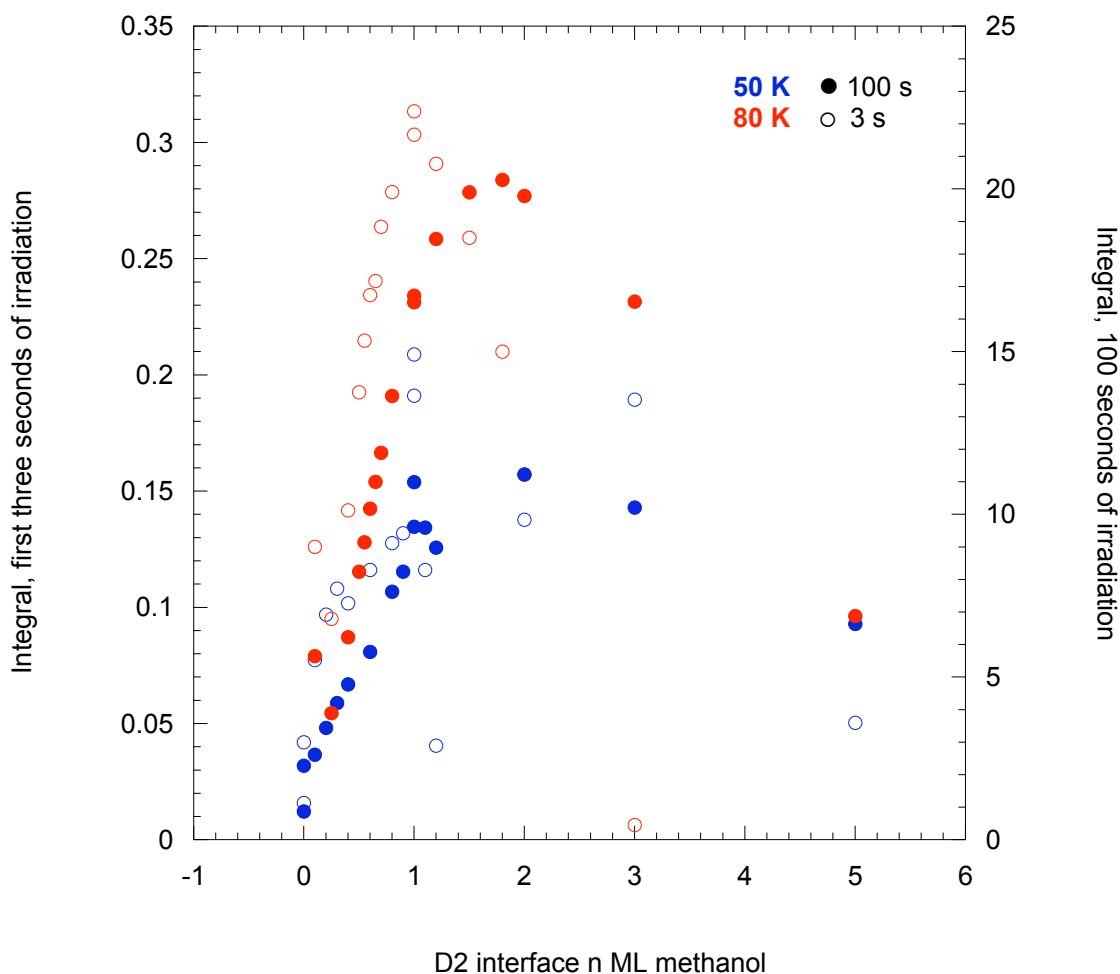
**Figure 3.8: Integral of D<sub>2</sub> signal showing reduction of D<sub>2</sub> production by CH<sub>3</sub>OH.** *n* ML CH<sub>3</sub>OH were deposited at 50 K on 20 ML D<sub>2</sub>O over 60 ML H<sub>2</sub>O. The film was irradiated for 97 s at 80 K using 100 eV electrons at a current of ~2  $\mu$ A, and the D<sub>2</sub> signal monitored. The D<sub>2</sub> signal was integrated over the 97 s irradiation exposure to determine total D<sub>2</sub> produced. While very small quantities of CH<sub>3</sub>OH (0.1 to 0.35 ML) appear to slightly increase the amount of D<sub>2</sub> produced compared to a methanol-free film, larger doses steadily decrease the D<sub>2</sub> produced, with the addition of 1 ML CH<sub>3</sub>OH reducing the signal by ~24%.



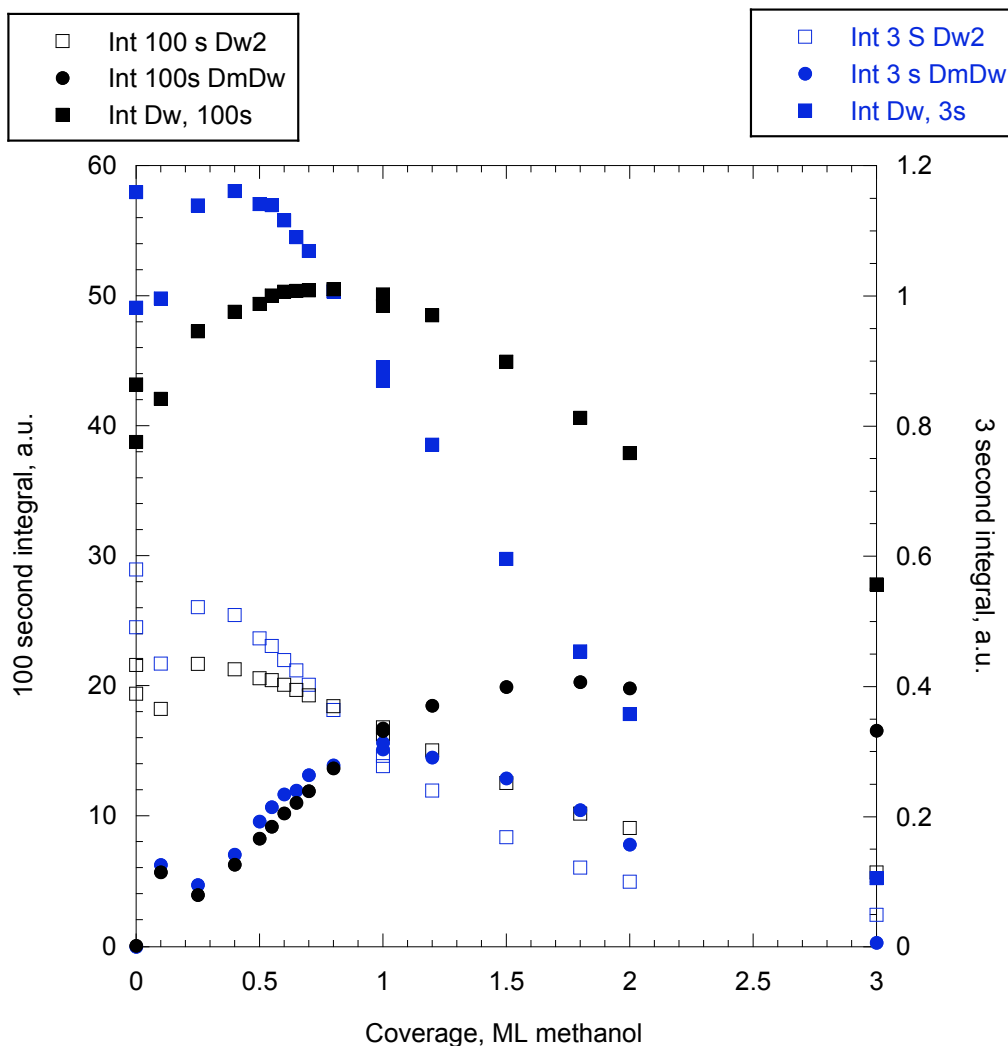
**Figure 3.9:  $D_2$  produced during ESD of  $CD_3OD$  on  $D_2O$ .**  $n$  ML  $CD_3OD$  were deposited at 50 K on 80 ML  $D_2O$ . The film was irradiated at 80 K using 100 eV electrons at a current of  $\sim 2 \mu A$ , beginning at 20 s and continuing until 117 s, and the  $D_2$  signal monitored. Selected doses are shown above. As the  $CD_3OD$  coverage increased, the total  $D_2$  signal also increased. Note that because these are all  $D_2$  signals, they have not been corrected for QMS sensitivity.



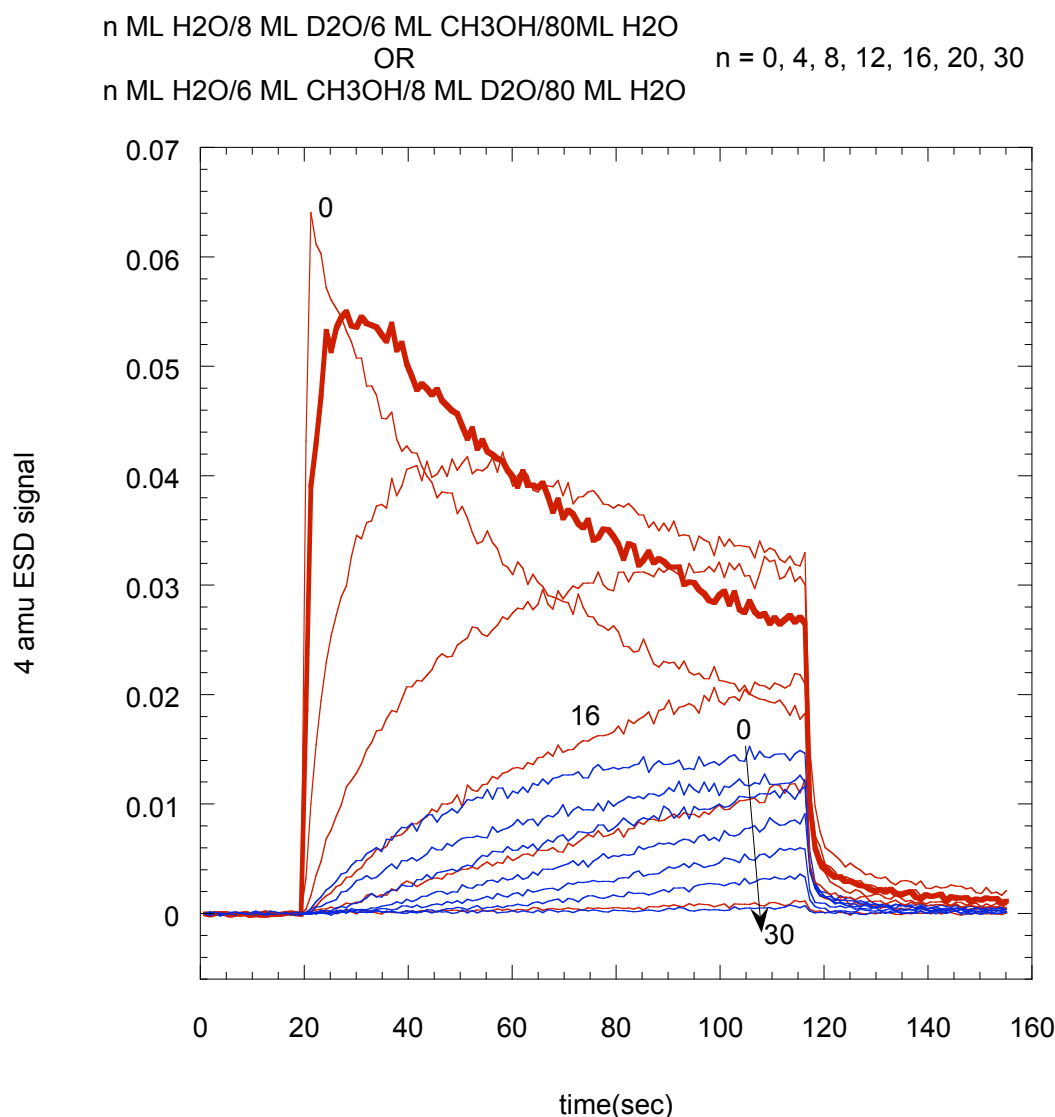
**Figure 3.10: D<sub>2</sub> produced at the methanol/water interface.** *n* ML methanol were deposited at 50 K on 80 ML water using different isotopologues: CD<sub>3</sub>OD/H<sub>2</sub>O, CH<sub>3</sub>OH/D<sub>2</sub>O, and CD<sub>3</sub>OD/D<sub>2</sub>O. The films were irradiated at 50 K using 100 eV electrons at a current of ~2 μA, beginning at 20 s and continuing until 117 s, and the D<sub>2</sub> signal monitored in each case. The D<sub>2</sub> signals from CH<sub>3</sub>OH/D<sub>2</sub>O and CD<sub>3</sub>OD/H<sub>2</sub>O were subtracted from the D<sub>2</sub> signal from CD<sub>3</sub>OD/D<sub>2</sub>O to determine the D<sub>2</sub> produced at the methanol/water interface. Selected coverages are shown above. This interfacially produced D<sub>2</sub> appears to peak when there is ~1 ML methanol at the water surface, where the water/methanol interface is maximized and receives a high electron flux. Note that because these are all D<sub>2</sub> signals, they have not been corrected for QMS sensitivity.



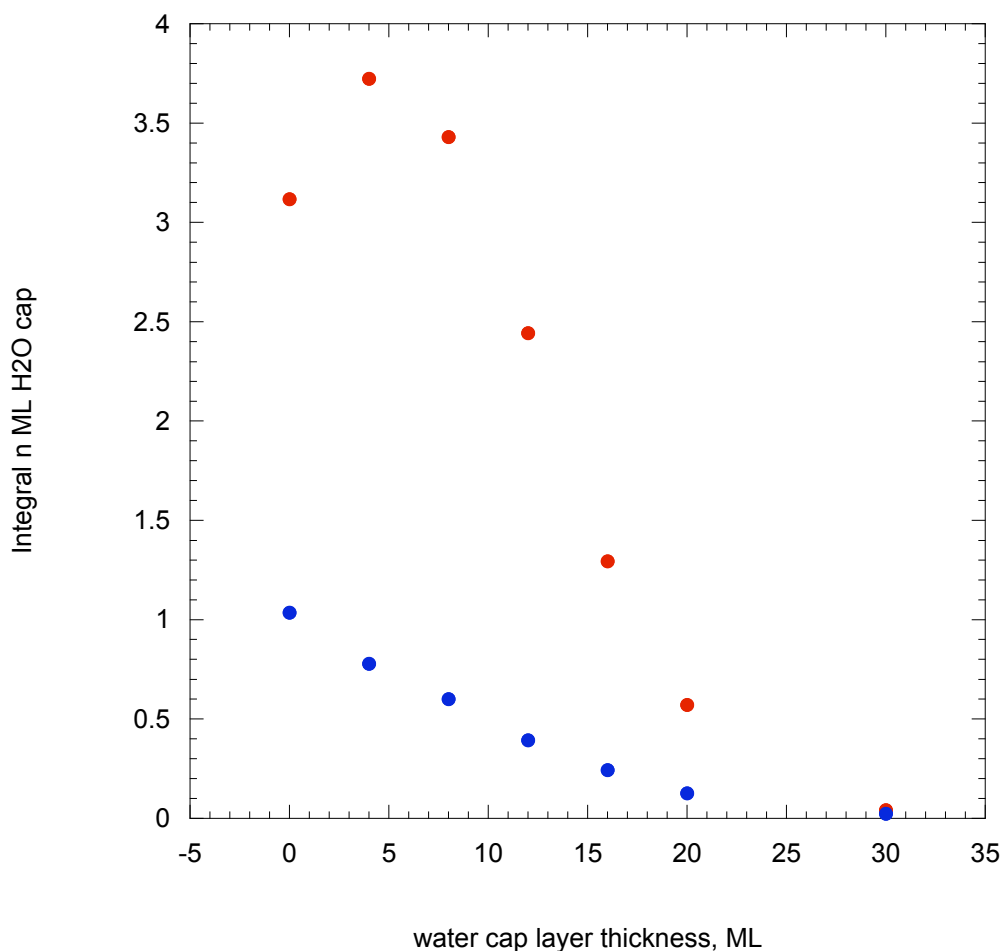
**Figure 3.11: Integrals of  $D_2$  produced at methanol/water interface, peaking at  $\sim 1$  ML methanol coverage.**  $n$  ML methanol were deposited and irradiated at either 50 K (blue) or 80 K (red) on 80 ML water using different isotopologues:  $CD_3OD/H_2O$ ,  $CH_3OH/D_2O$ , and  $CD_3OD/D_2O$ . The films were irradiated at both temperatures for 97 s with 100 eV electrons at a current of  $\sim 2 \mu A$ , and the  $D_2$  signal monitored in each case. The  $D_2$  signals from  $CH_3OH/D_2O$  and  $CD_3OD/H_2O$  were subtracted from the  $D_2$  signal from  $CD_3OD/D_2O$  to determine the  $D_2$  produced at the methanol/water interface. This interfacially produced  $D_2$  signal was integrated over two time ranges: the first 3 s of irradiation, to determine initial production dependencies, and the full 97 s exposure, to determine how additional processes such as mixing affect the yield. In the non-mixed regime, interfacial  $D_2$  yield peaks at 1 ML methanol coverage. When longer integration ranges are used to include mixing effects, the peak occurs at  $\sim 2$  ML methanol, indicating that as the second monolayer is mixed it continues to react. At the highest coverages (5 ML) little interfacial  $D_2$  is produced, as methanolic hydrogen production dominates over these time scales and the methanol/water interface receives less energy. However, if the exposure time was extended, the effects of mixing at the increasingly buried methanol/water interface (under thicker methanol capping layers) could be studied.



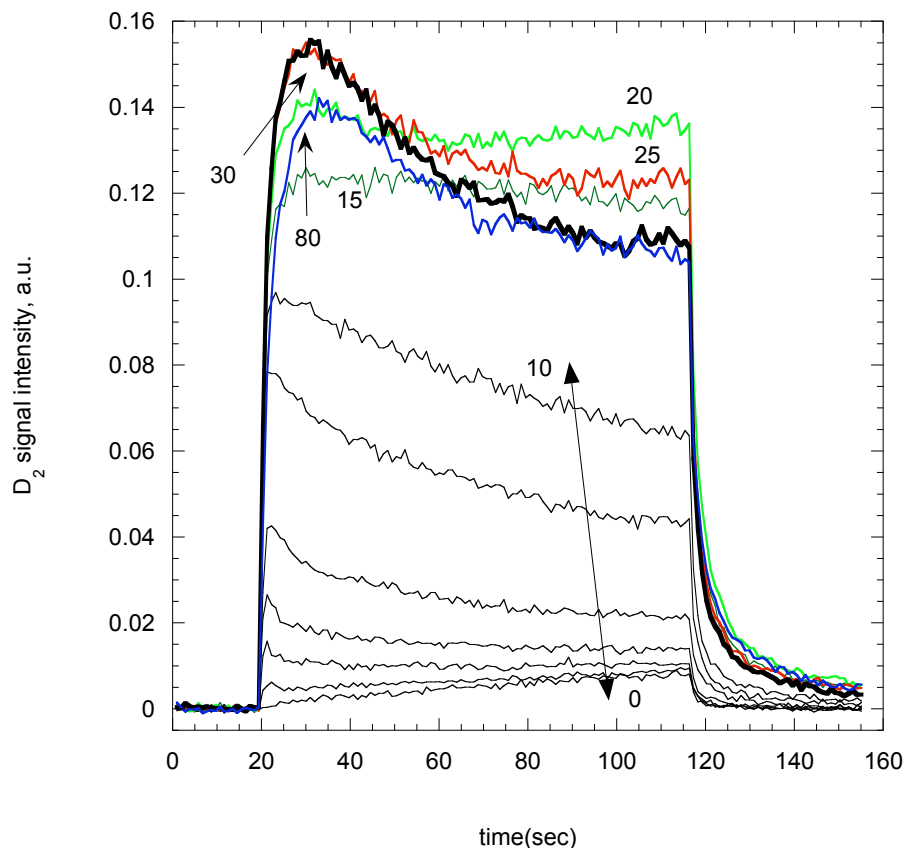
**Figure 3.12: The addition of methanol can increase the availability of D in water to form  $D_2$ .**  $n$  ML methanol were deposited and irradiated at 80 K on 80 ML water using different isotopologues:  $CD_3OD/H_2O$ ,  $CH_3OH/D_2O$ , and  $CD_3OD/D_2O$ . The films were irradiated at 80 K for 97 s with 100 eV electrons at a current of  $\sim 2 \mu A$ . The contribution of D from water ( $D_w$ ) was calculated by adding twice the  $D_2$  signal from  $CH_3OH/D_2O$  to the interfacial  $D_2$  signal ( $D_m D_w$ ) discussed in the previous two figures. The total  $D_w$  contribution is compared to that from a pure  $D_2O$  signal over two integration ranges: the first 3 s of irradiation (initial reactions, and no mixing effects), and 97 s (which includes some mixing effects). Although the peak  $D_w$  contribution occurs at different methanol coverages due to mixing during the 97 s integration, in both cases the addition of small quantities of methanol increases the  $D_w$  contribution. Similar results were seen when the experiment was repeated at 50 K.



**Figure 3.13: Methanol is a more efficient suppressant than H<sub>2</sub>O of D<sub>2</sub> production from D<sub>2</sub>O.** Two sandwich structured films were grown at 50 K:  $n$  ML H<sub>2</sub>O / 6 M CH<sub>3</sub>OH / 8 ML D<sub>2</sub>O / 80 ML H<sub>2</sub>O / TiO<sub>2</sub> (blue) and  $n$  ML H<sub>2</sub>O / 8 ML D<sub>2</sub>O / 6 M CH<sub>3</sub>OH / 80 ML H<sub>2</sub>O / TiO<sub>2</sub> (red). The films were irradiated at 50 K beginning at 20 s and continuing until 117 s using 100 eV electrons at a current of  $\sim 2\mu\text{A}$ . The D<sub>2</sub> signal was measured during the ESD. While the addition of any methanol delays and decreases D<sub>2</sub> production, placing the methanol between the D<sub>2</sub>O and the water/vacuum interface is much more effective, as seen by the greater suppression of D<sub>2</sub>O by 6 ML CH<sub>3</sub>OH than by 16 ML H<sub>2</sub>O. The difference in blocking of D<sub>2</sub> by CH<sub>3</sub>OH and H<sub>2</sub>O is less prominent as the capping layer thickness increases and the D<sub>2</sub> signal approaches zero.

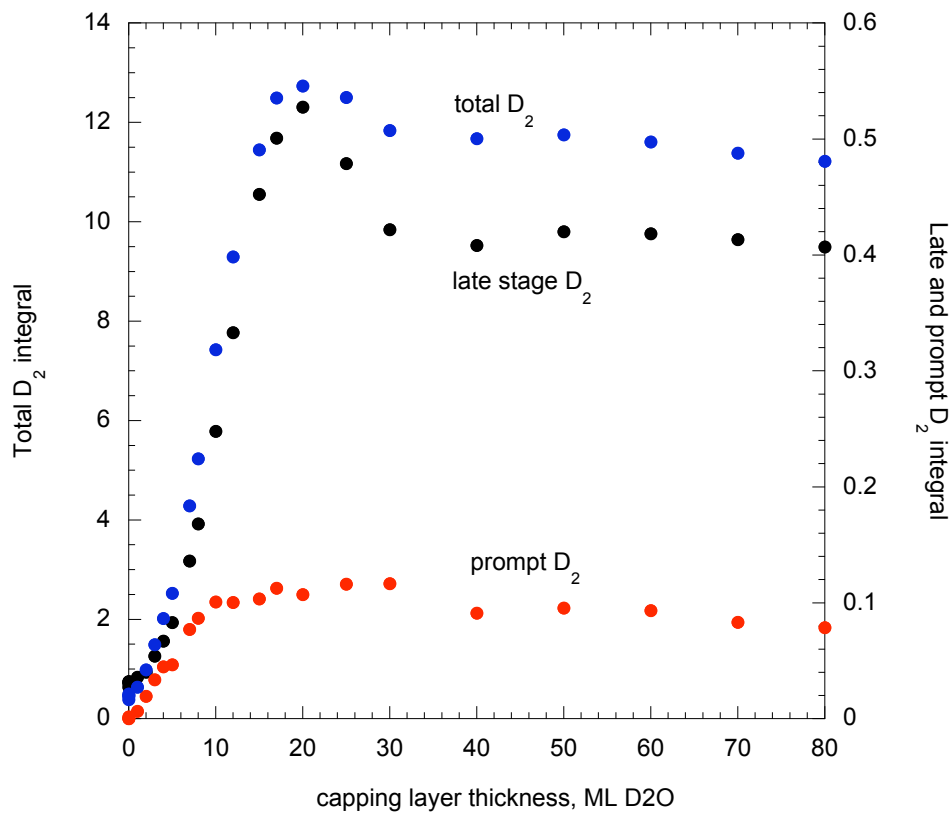


**Figure 3.14: Total  $D_2$  production from  $D_2O$  decreases greatly when the capping layer includes  $CH_3OH$ .** Two sandwich structured films were grown at 50 K:  $n$  ML  $H_2O$  / 6 M  $CH_3OH$  / 8 ML  $D_2O$  / 80 ML  $H_2O$  /  $TiO_2$  (blue) and  $n$  ML  $H_2O$  / 8 ML  $D_2O$  / 6 M  $CH_3OH$  / 80 ML  $H_2O$  /  $TiO_2$  (red). The films were irradiated at 50 K beginning at 20 s and continuing until 117 s using 100 eV electrons at a current of  $\sim 2\mu A$ . The  $D_2$  signal was measured during the ESD. The integrals of the  $D_2$  produced from each film during irradiation are shown above. If any  $D_2$  is produced beneath the methanol layer, very little of it is able to escape through the methanol to be detected.

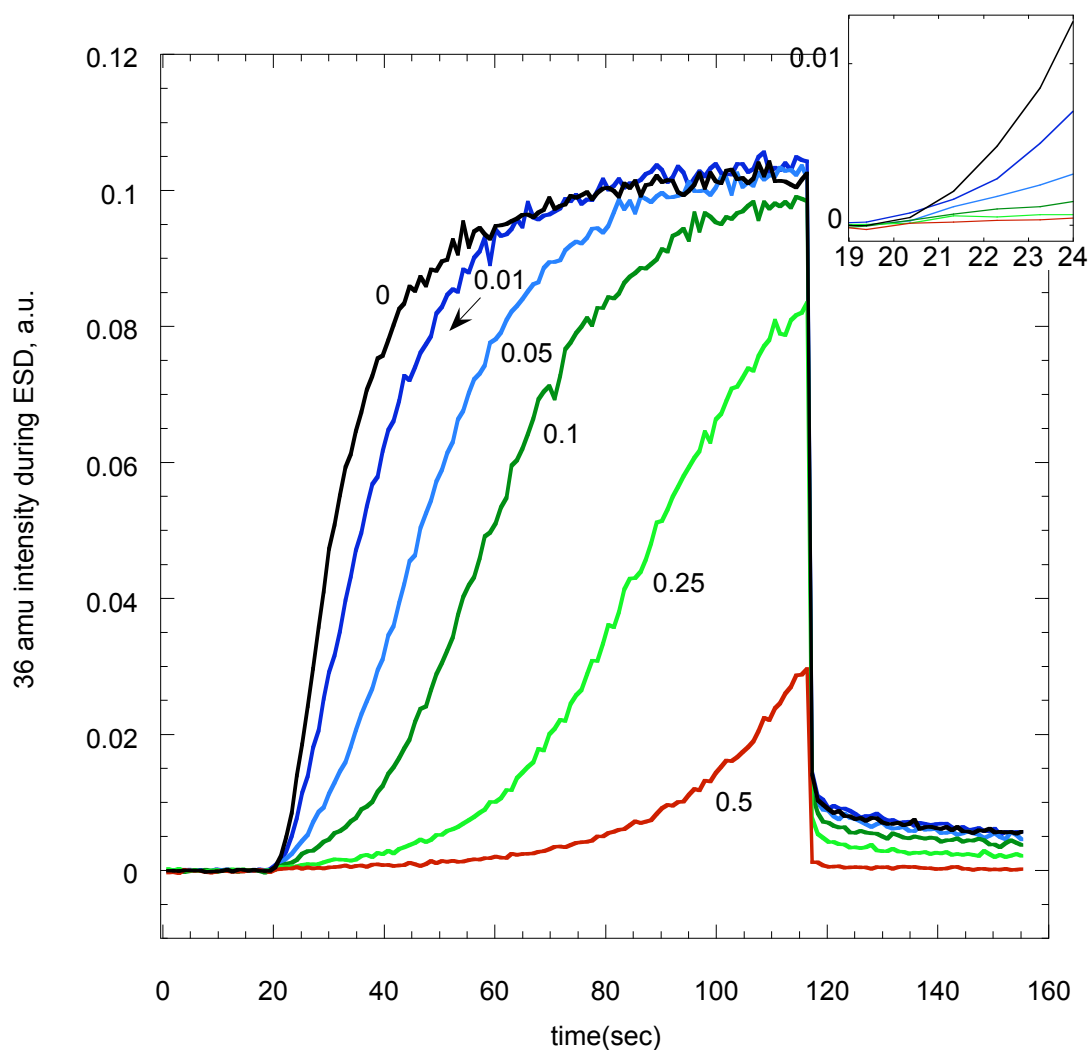


**Figure 3.15: Methanol may act as an internal interface.** Sandwich structures of  $n$  ML  $D_2O$  / 6 ML  $CH_3OH$  /  $80-n$  ML  $D_2O$  were grown and irradiated at 50 K. Irradiation began at 20 s and continued until 117 s using 100 eV electrons at a current of  $\sim 2\mu A$ . The  $D_2$  signal was measured during the ESD. In the  $n = 0$  case, the  $D_2$  signal rises with time as the  $CH_3OH$  desorbs. Increasing the capping thickness of  $D_2O$  up to 30 ML increases the prompt  $D_2$  signal (due to  $D_2$  produced at the vacuum interface), with the prompt signal beginning to saturate at  $n = 17$  ML and decreasing once  $n$  is greater than 30 ML. A similar pattern is seen in the late  $D_2$  signal, which results from  $D_2$  produced deeper in the film and peaks around  $n = 20$ . Methanol capped by more than  $\sim 30$  ML  $D_2O$  appears to have little effect on the  $D_2$  yield.



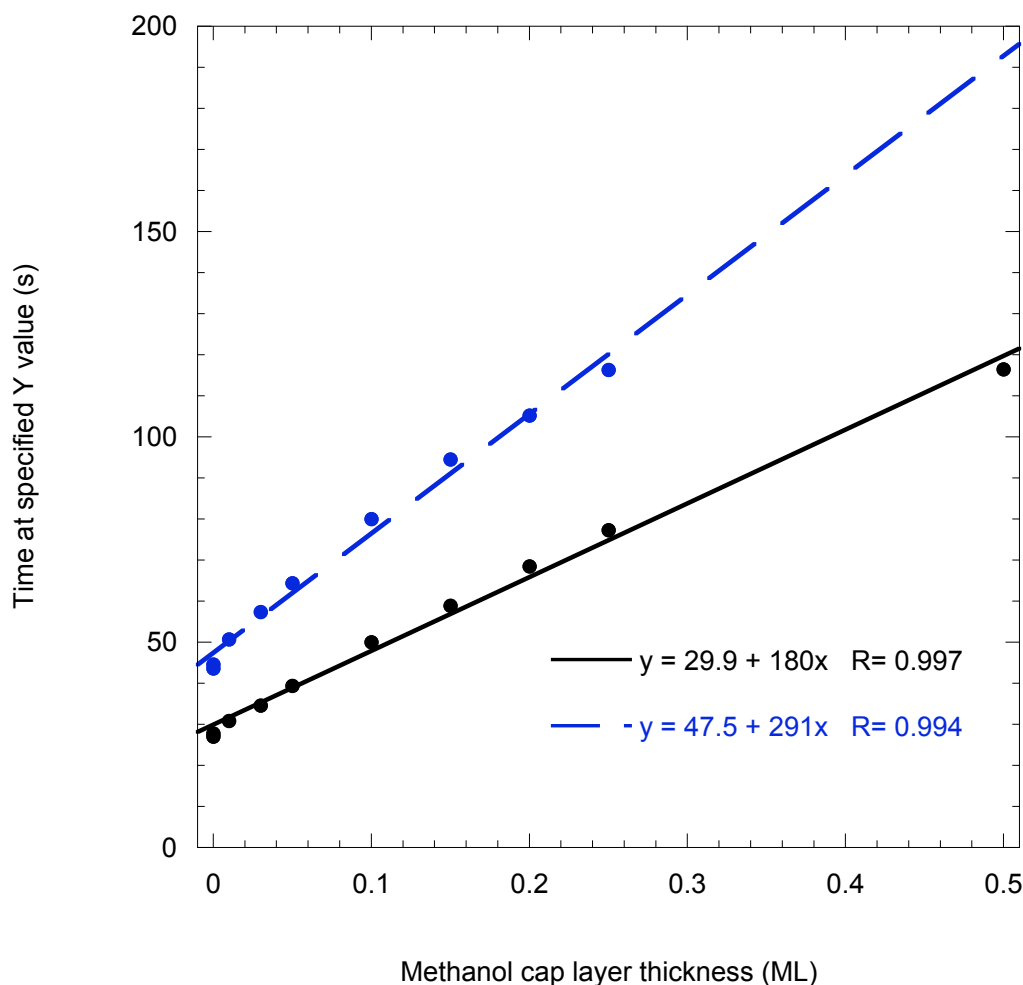


**Figure 3.16: Saturation of D<sub>2</sub> production.** Sandwich structures of  $n$  ML D<sub>2</sub>O / 6 ML CH<sub>3</sub>OH / 80- $n$  ML D<sub>2</sub>O were grown and irradiated at 50 K. Irradiation exposure was 97 s using 100 eV electrons at a current of  $\sim 2\mu\text{A}$ . The D<sub>2</sub> signal was measured during the ESD and integrated over three ranges: the first 3 s of exposure, representing prompt D<sub>2</sub> production, which occurs at the vacuum interface; the last 5 s of exposure, representing D<sub>2</sub> production saturation and D<sub>2</sub> produced deeper in the film, which includes mixing effects; and the full irradiation cycle (97 s) to consider total D<sub>2</sub> production. Prompt D<sub>2</sub> production quickly saturates at  $n = 10$  ML. Late and total production both peak at  $n = 20$  ML and decrease to  $n = 30$  ML after which they saturate.

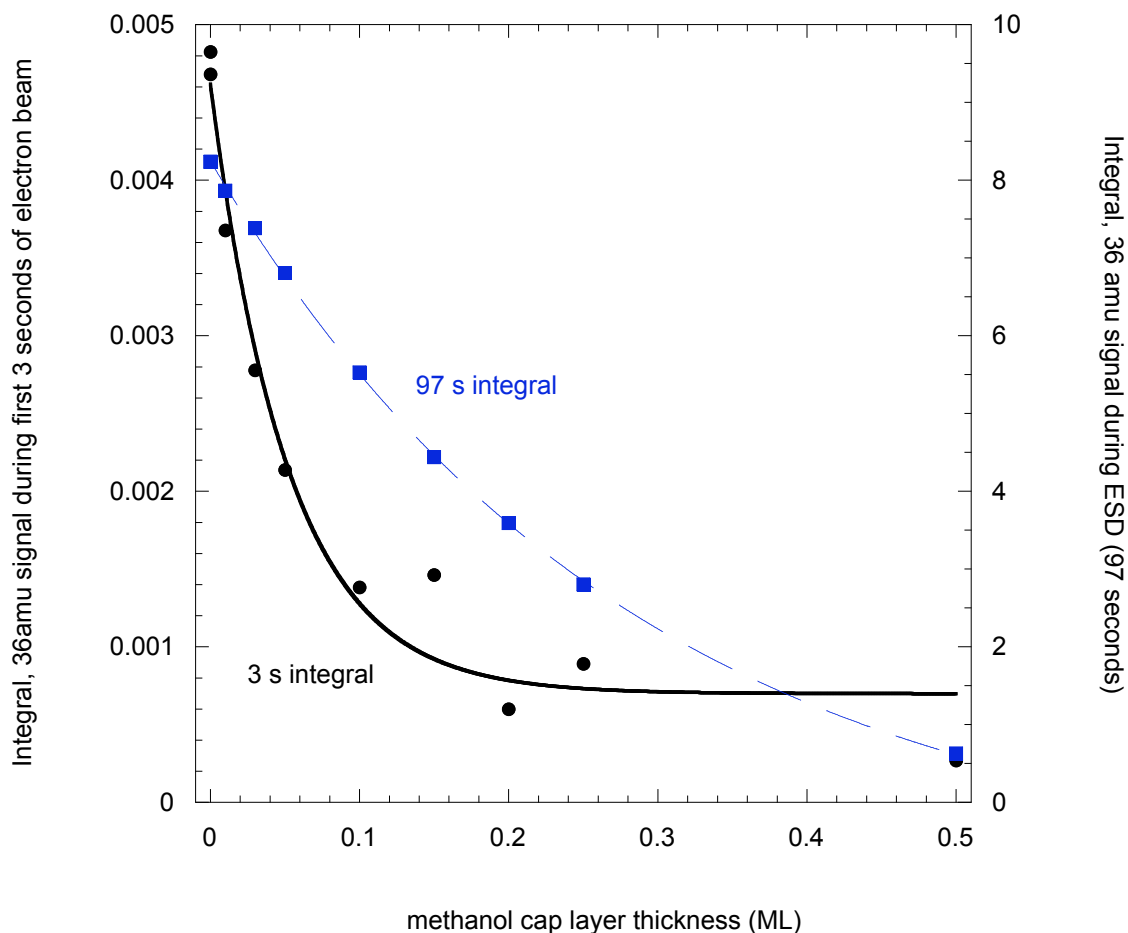


**Figure 4.1: Suppression of O<sub>2</sub> production by CH<sub>3</sub>OH capping layer.**  $n$  ML of CH<sub>3</sub>OH were deposited on 80 ML unprocessed H<sub>2</sub><sup>18</sup>O in the structure shown below. The film was grown and irradiated at 80 K, with irradiation beginning at 20s and ending at 117s. The <sup>18</sup>O<sub>2</sub> signal was monitored during ESD. The addition of small quantities of methanol reduces the O<sub>2</sub> signal from water. **Inset:** An expanded view of the <sup>18</sup>O<sub>2</sub> signals during the first four seconds of irradiation.

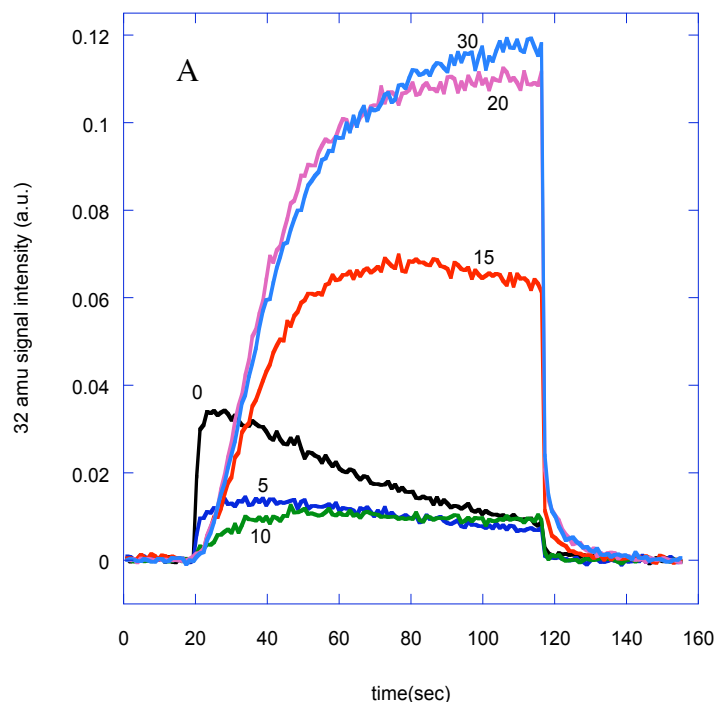




**Figure 4.2: Time delay in O<sub>2</sub> production caused by methanol.** n ML of CH<sub>3</sub>OH were deposited on 80 ML unprocessed H<sub>2</sub><sup>18</sup>O in the structure shown in Figure 1. The film was grown and irradiated at 80 K for 97s. The <sup>18</sup>O<sub>2</sub> signal was monitored during ESD. The length of time that it takes for the O<sub>2</sub> signal to reach a specified level was measured from the data given in Figure 1 to find how much the addition of methanol delayed O<sub>2</sub> production. The specified signal levels were determined by the intensity of the 0.5 and 0.25 ML CH<sub>3</sub>OH-capped ASW film just before the beam was turned off. The final intensity of the 0.5 ML CH<sub>3</sub>OH/80 ML ASW film is 0.0296 (shown in black), while the final intensity of the 0.25 ML CH<sub>3</sub>OH/80 ML ASW film is 0.0834 (shown in blue). The delay caused by the addition of methanol for a specified signal intensity increases linearly with methanol dose.

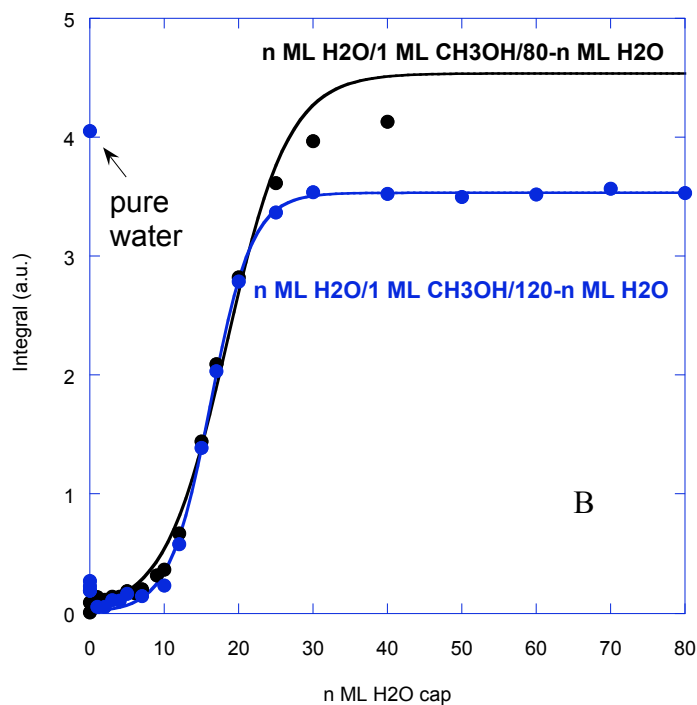


**Figure 4.3:  $^{18}\text{O}_2$  Suppression kinetics.** n ML of  $\text{CH}_3\text{OH}$  were deposited on 80 ML unprocessed  $\text{H}_2^{18}\text{O}$  in the structure shown in Figure 1. The film was grown and irradiated at 80 K for 97s. The  $^{18}\text{O}_2$  signal was monitored during ESD. The resulting desorption signals (shown in Figure 1) were integrated over two ranges: 3 s and 97 s. The 3 s integral includes the first three seconds of irradiation, reflecting the initial suppression of  $\text{O}_2$  prior to any induced mixing. The 97 s integral includes the full irradiation cycle and reflects total  $\text{O}_2$  suppression as a function of deposited  $\text{CH}_3\text{OH}$ ; the total signal is affected by mixing and  $\text{CH}_3\text{OH}$  desorption, and does not show as strong a suppression effect as  $\text{O}_2$  begins to recover at later exposure times. The integrals were found to exponentially decay with increasing methanol dose, with  $1/e$  constants of 0.05 ML  $\text{CH}_3\text{OH}$  and 0.29 ML  $\text{CH}_3\text{OH}$  for the 3 s and 97 s integrals, respectively.

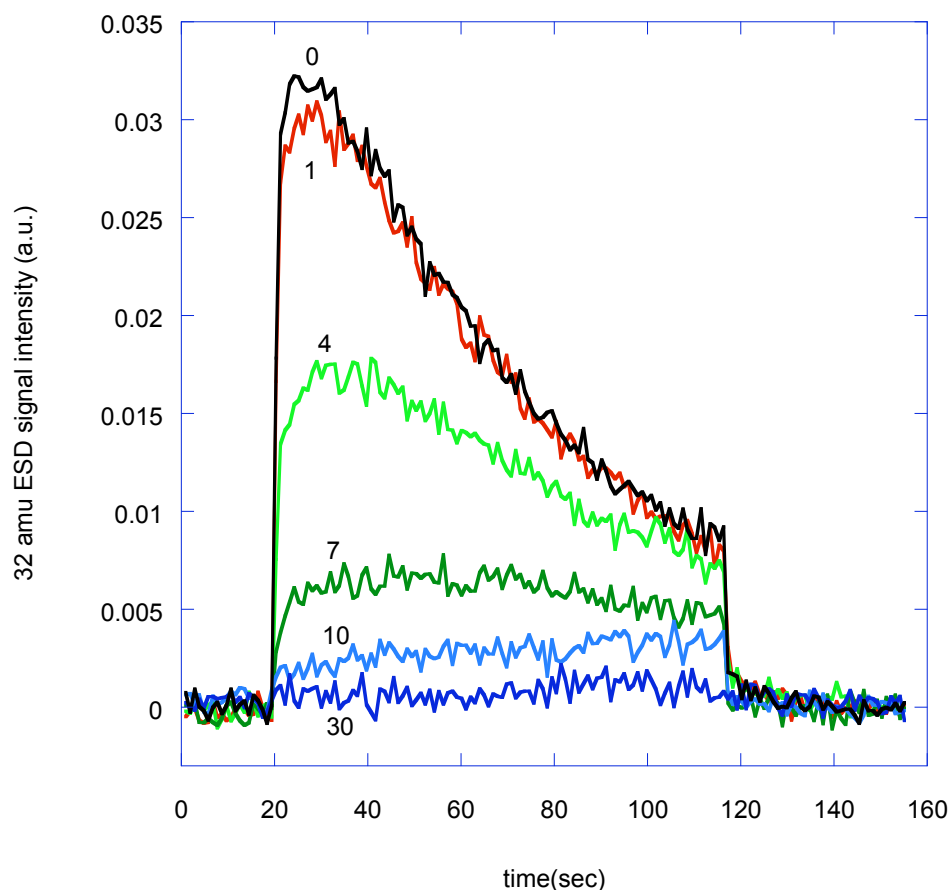


**Figure 4.4: Sandwich films of water and 1 ML  $\text{CH}_3\text{OH}$ .**

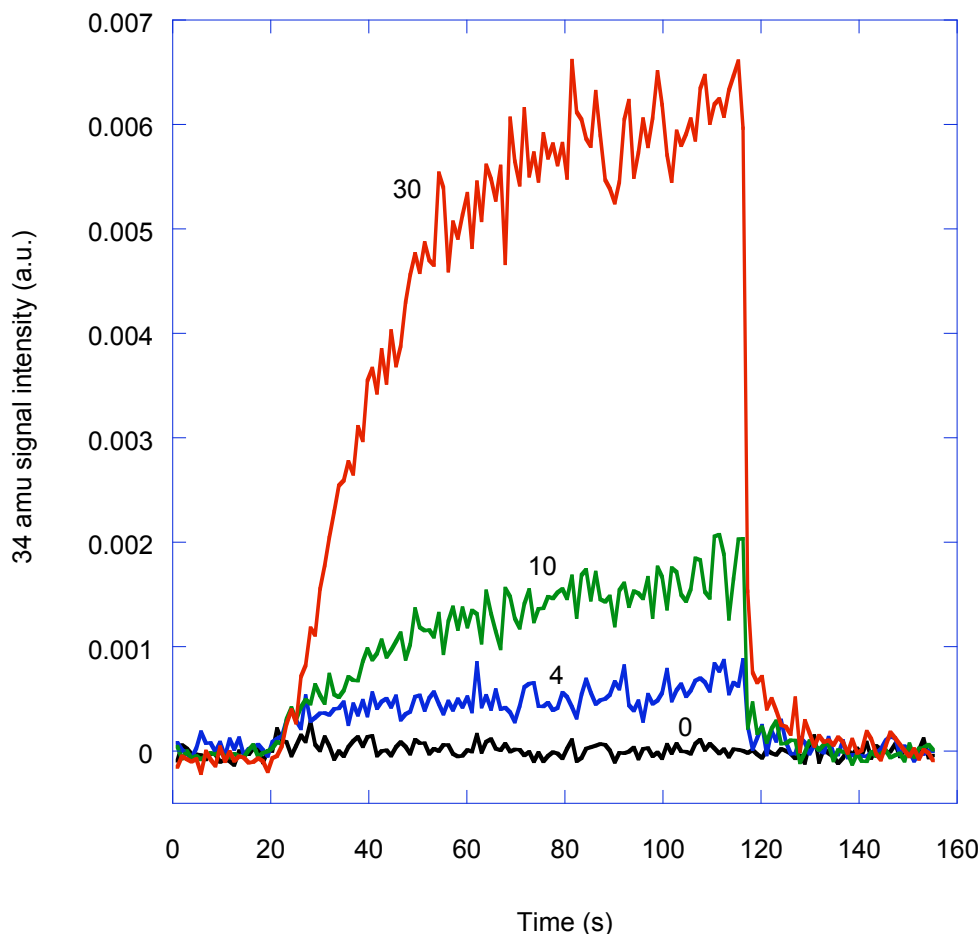
**4.4 A**, top: 32amu signal during ESD. The initial rise in 32 amu signal is due to desorption of  $\text{CH}_3\text{OH}$ ; the later slow rise of 32amu signal is due to  $\text{O}_2$  production. Note that  $\text{O}_2$  production does not resume until the capping layer is  $\sim 10$  ML thick.



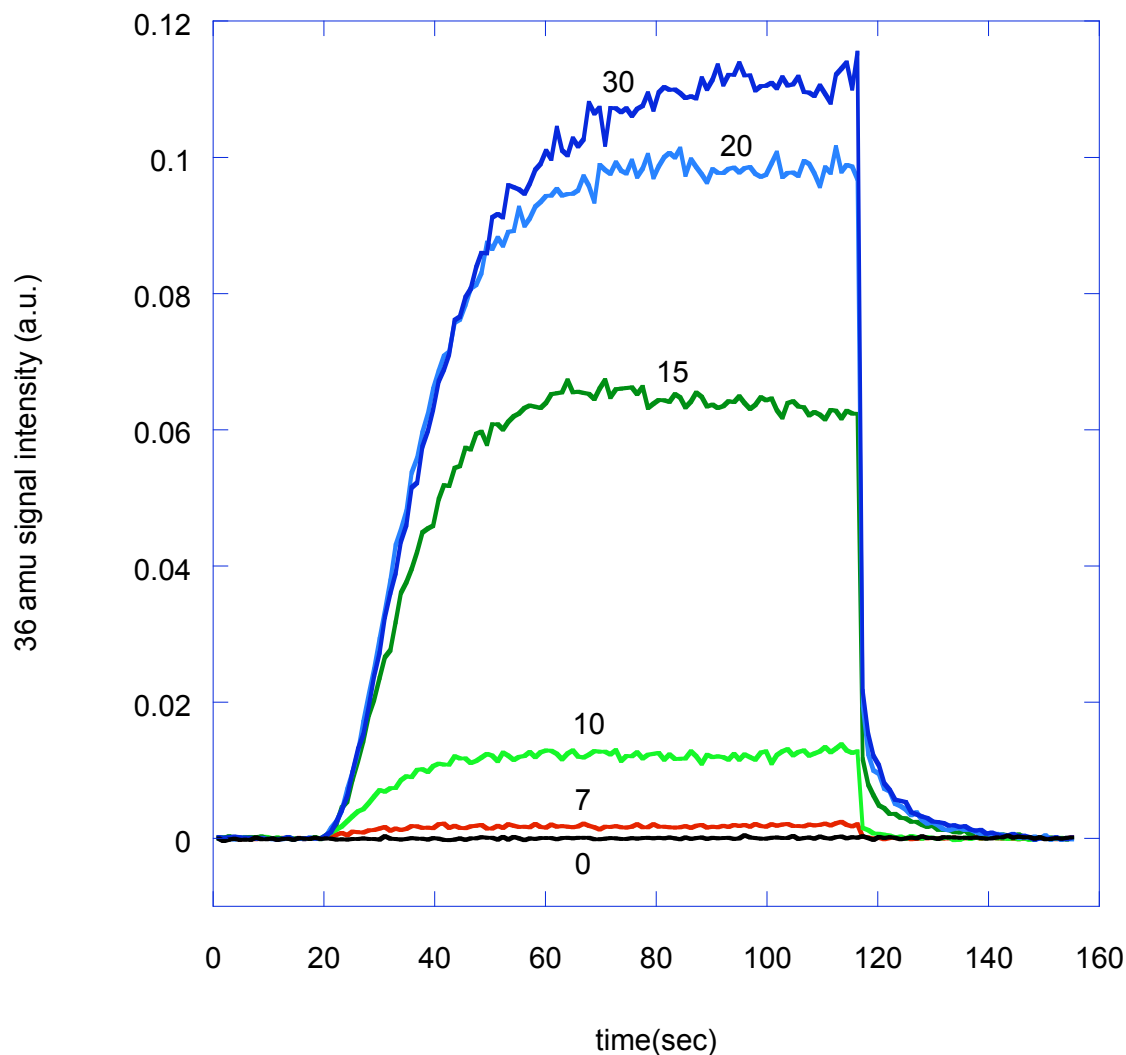
**4.4 B**, bottom: The  $\text{O}_2$  production signal was integrated over the 97 s scan and plotted with respect to capping layer thickness for two total film thicknesses: 80 ML ASW + 1 ML  $\text{CH}_3\text{OH}$ , and 120 ML ASW + 1 ML  $\text{CH}_3\text{OH}$ . Note that even in the 80 ML ASW / 1 ML  $\text{CH}_3\text{OH}$  / 40 ML ASW case, the production level is about 15% lower than in a 120 ML film of pure water.



**Figure 4.5:  $^{16}\text{O}_2$  production during ESD from isotopically labeled sandwich films.** Films of  $n$  ML  $\text{H}_2^{18}\text{O}$ /1 ML  $\text{CH}_3\text{OH}$  /80- $n$  ML  $\text{H}_2^{16}\text{O}$  were deposited at 25 K, and then irradiated at 80 K. The electron beam was turned on at 20 seconds and turned off at 117 seconds. Mass 32, due to the  $\text{CH}_3\text{OH}$  and  $\text{O}_2$  signals, was monitored during desorption.  $\text{CH}_3\text{OH}$  is generally seen in the prompt portion of the signal immediately after the beam is turned on, while  $\text{O}_2$  forming from  $\text{H}_2^{16}\text{O}$  in the presence of  $\text{CH}_3\text{OH}$  is seen later. This graph shows the desorption of  $\text{CH}_3\text{OH}$  clearly, but no appreciable  $\text{O}_2$  signal is observed. This absence, in combination with the late 36 amu ( $^{18}\text{O}_2$ ) signal seen in this film, suggests that  $\text{CH}_3\text{OH}$  blocks the formation/desorption of  $\text{O}_2$  formed from the bottom,  $\text{H}_2^{16}\text{O}$ , layer. In this way,  $\text{CH}_3\text{OH}$  is acting as an internal interface in much the same way that Pt or  $\text{TiO}_2$  acts as an interface: the upper layers can interact with the  $\text{CH}_3\text{OH}$  but the lower layers appear to be totally blocked. These results suggest that MeOH is an effective barrier to  $\text{O}_2$  production from the lower layers, possibly as the result of efficient exciton trapping or side reactions.

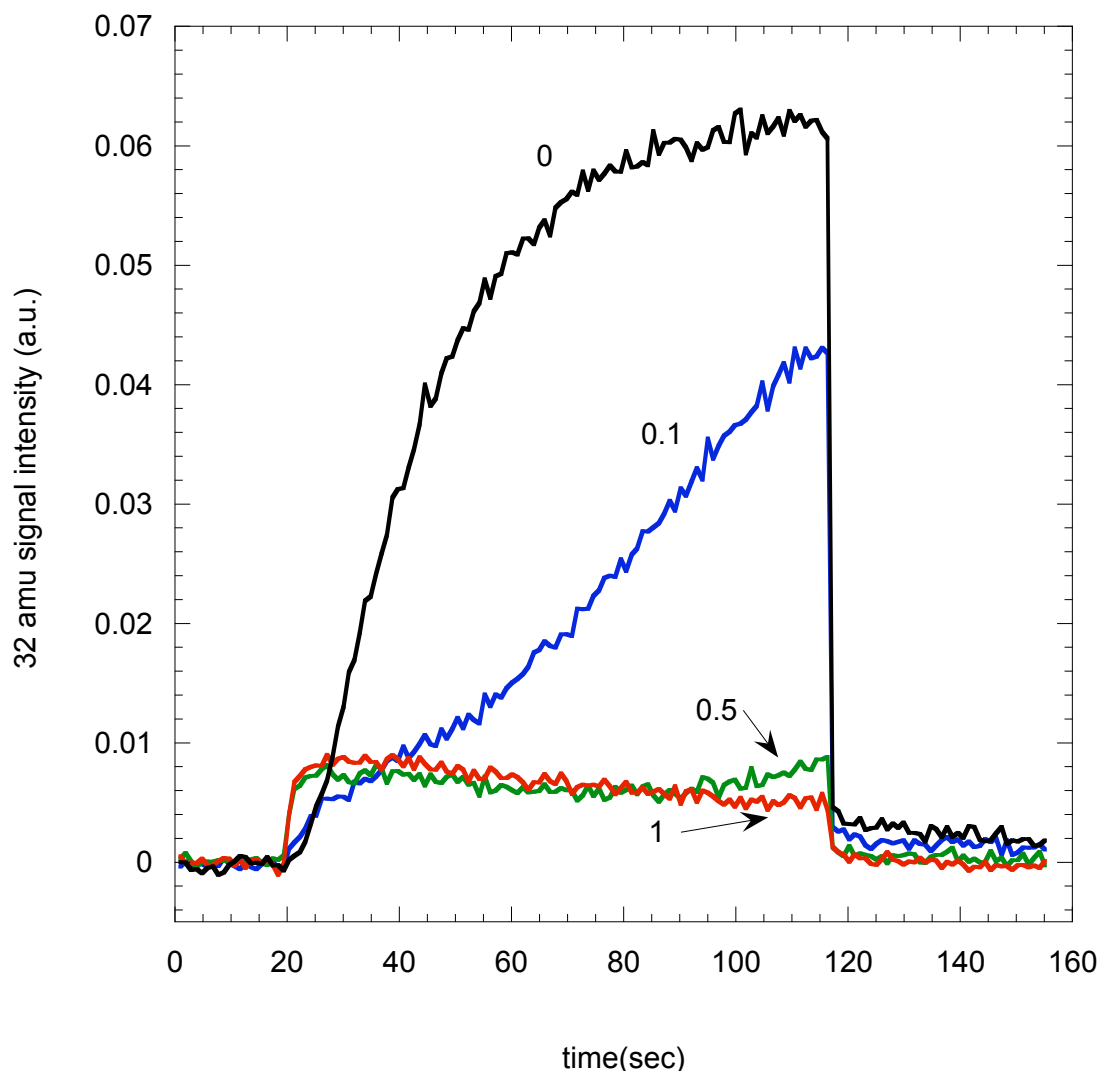


**Figure 4.6:  $^{16}\text{O}^{18}\text{O}$  production during ESD from isotopically labeled sandwich films.** Films of  $n$  ML  $\text{H}_2^{18}\text{O}$ /1 ML  $\text{CH}_3\text{OH}$ /80- $n$  ML  $\text{H}_2^{16}\text{O}$  were grown at 25 K and irradiated at 80 K. The electron beam was turned on at 20 seconds and continued until 117 seconds. The 34 amu signal for  $^{16}\text{O}^{18}\text{O}$  was measured to determine the amount of mixing between the upper  $\text{H}_2^{18}\text{O}$  layer and the  $\text{CH}_3\text{OH}$  and  $\text{H}_2^{16}\text{O}$  layers. Although the  $^{16}\text{O}^{18}\text{O}$  signal increases with thicker  $\text{H}_2^{18}\text{O}$  films as expected, the total signal is minimal for all thicknesses, indicating that mixing between the layers is not a major process.



**Figure 4.7:  $^{18}\text{O}_2$  production during ESD from isotopically labeled sandwich films.** Films of  $n$  ML  $\text{H}_2^{18}\text{O}$ /1 ML  $\text{CH}_3\text{OH}$ /80- $n$  ML  $\text{H}_2^{16}\text{O}$  were grown at 25 K and irradiated at 80 K. The electron beam was turned on at 20 seconds and continued until 117 seconds. The 36 amu signal for  $^{18}\text{O}_2$  was measured to determine the  $\text{O}_2$  produced in the upper  $\text{H}_2^{18}\text{O}$  layer. Although the  $^{18}\text{O}_2$  signal increases with thicker  $\text{H}_2^{18}\text{O}$  layers, it does not return to a signal intensity comparable to that from a methanol-free film until the  $\text{H}_2^{18}\text{O}$  layer is thicker than 20 ML. For comparison, in an isotopically labeled pure water film, a 10 ML thick  $\text{H}_2^{18}\text{O}$  capping layer on 70 ML  $\text{H}_2^{16}\text{O}$  produces nearly as much  $^{18}\text{O}_2$  (70%) as an 80 ML  $\text{H}_2^{18}\text{O}$  film. Total  $^{18}\text{O}_2$  signal from the 10 ML  $\text{H}_2^{18}\text{O}$ /1 ML  $\text{CH}_3\text{OH}$ /70 ML  $\text{H}_2^{16}\text{O}$  film is only 12% of the total  $^{18}\text{O}_2$  signal from the 30 ML  $\text{H}_2^{18}\text{O}$ /1 ML  $\text{CH}_3\text{OH}$ /50 ML  $\text{H}_2^{16}\text{O}$  film, making it clear that a buried methanol interface can suppress  $\text{O}_2$  production over long ranges.





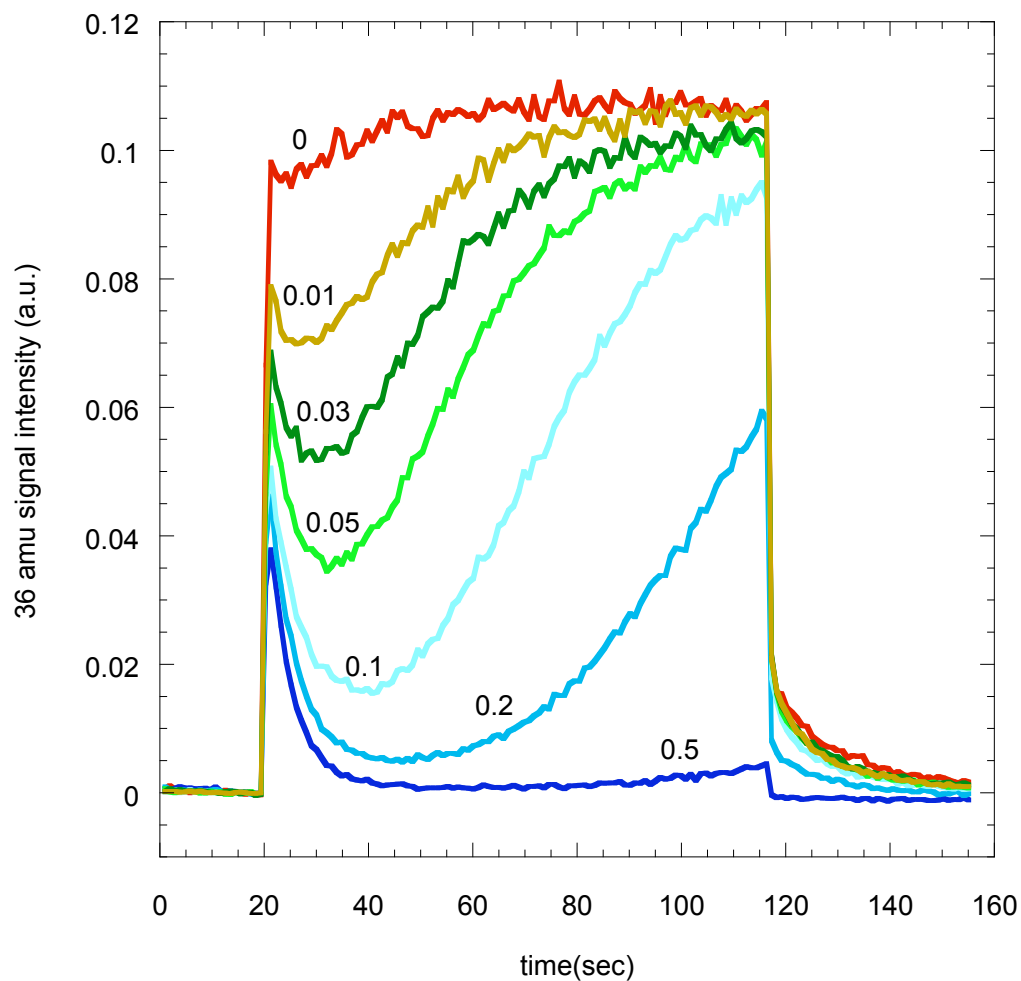
**Figure 4.8: Dose dependence of oxygen suppression by buried methanol.** 6 ML  $\text{H}_2\text{O}$ /n ML  $\text{CH}_3\text{OH}$ /80 ML  $\text{H}_2\text{O}$  films were grown and irradiated at 50 K. The electron beam was turned on at 20 seconds and continued for 97 seconds. Values of n ranging from 0 to 10 ML were dosed. However, methanol layers greater than 1 ML  $\text{CH}_3\text{OH}$  are not shown here as the 32 amu signals from these films are indistinguishable from the 6 ML  $\text{H}_2\text{O}$ /1 ML  $\text{CH}_3\text{OH}$ /80 ML  $\text{H}_2\text{O}$  films. Note that  $\text{O}_2$  suppression is apparent before the methanol layer is complete; the signal from a film with 0.1 ML  $\text{CH}_3\text{OH}$  is roughly half that of the  $\text{O}_2$  signal from a pure water film. As higher coverages of methanol (0.5 ML or more) are buried in the film, the initial  $\text{O}_2$  signal is replaced by a prompt  $\text{CH}_3\text{OH}$  signal and the  $\text{O}_2$  signal is increasingly eliminated.

6 ML ASW

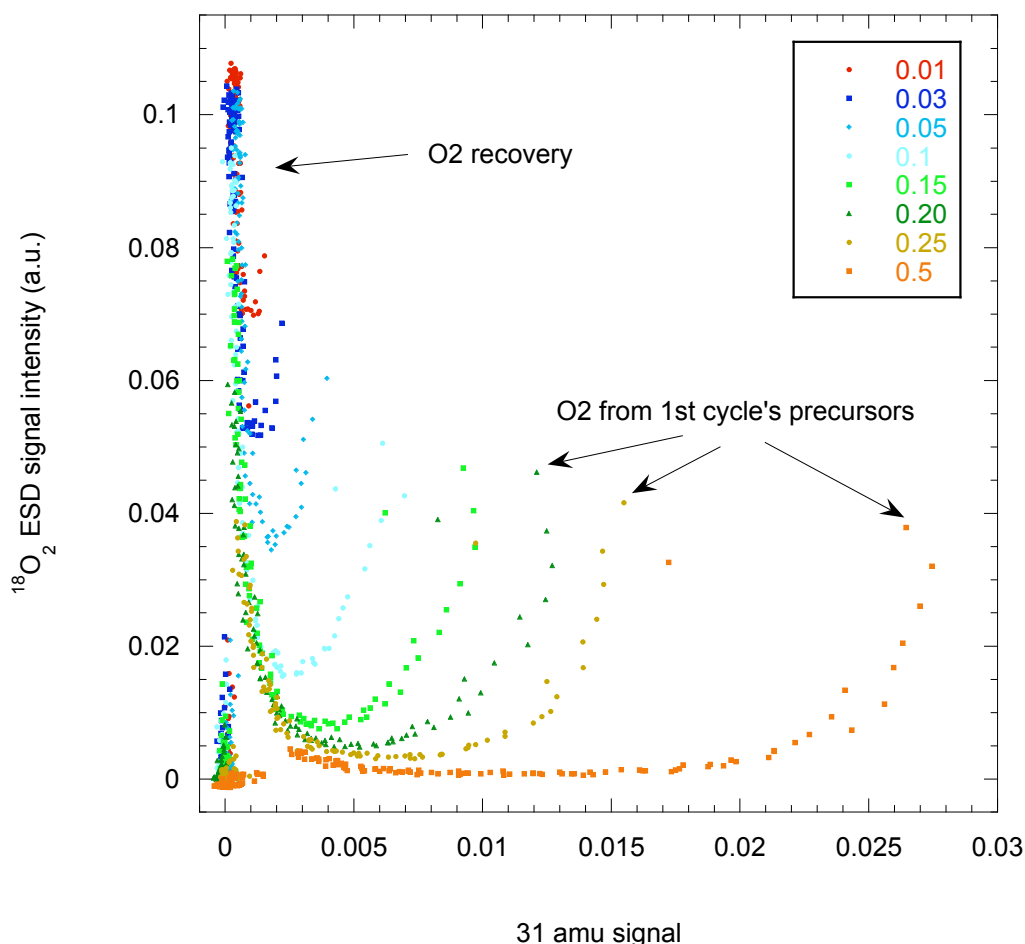
n ML MeOH

80 ML ASW

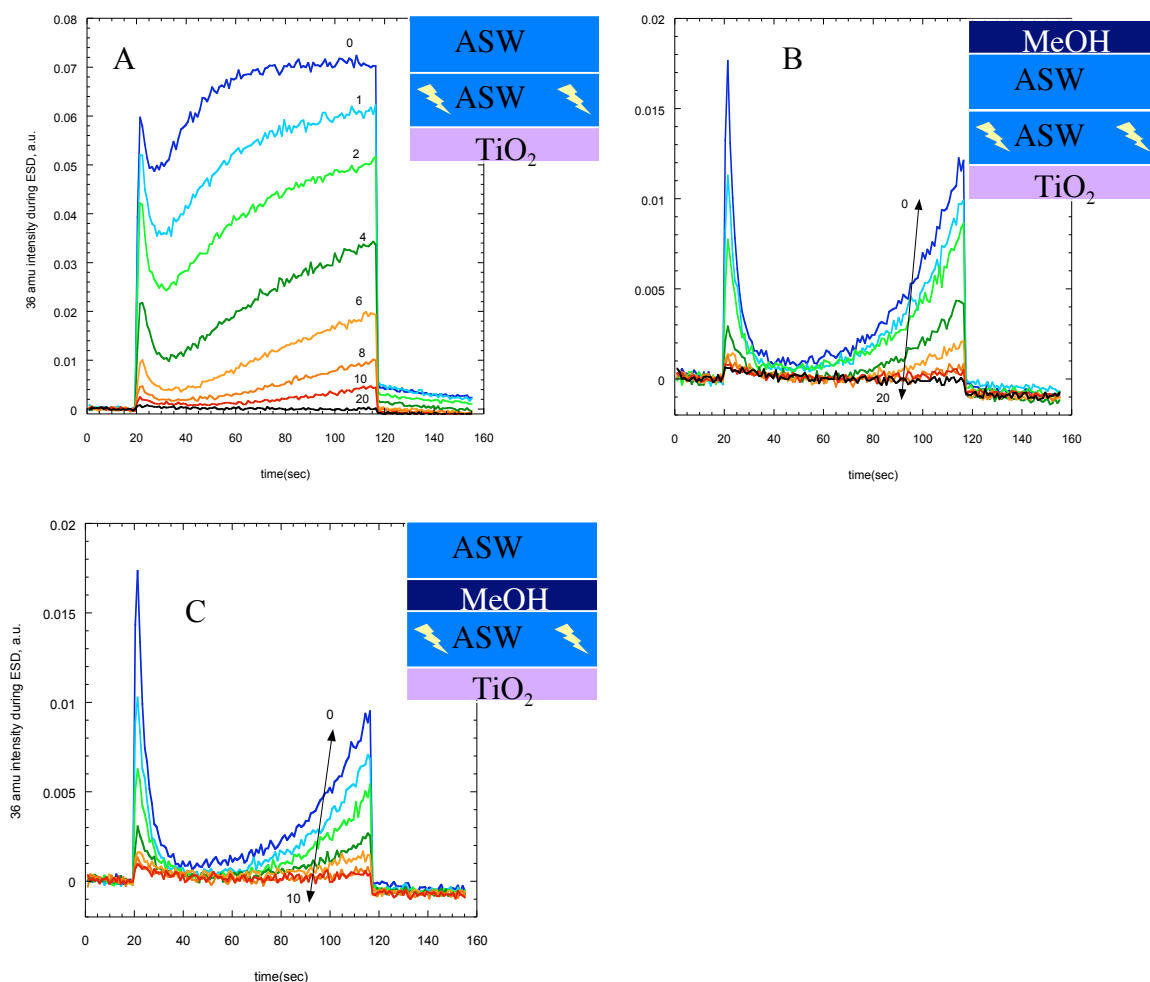
$\text{TiO}_2$



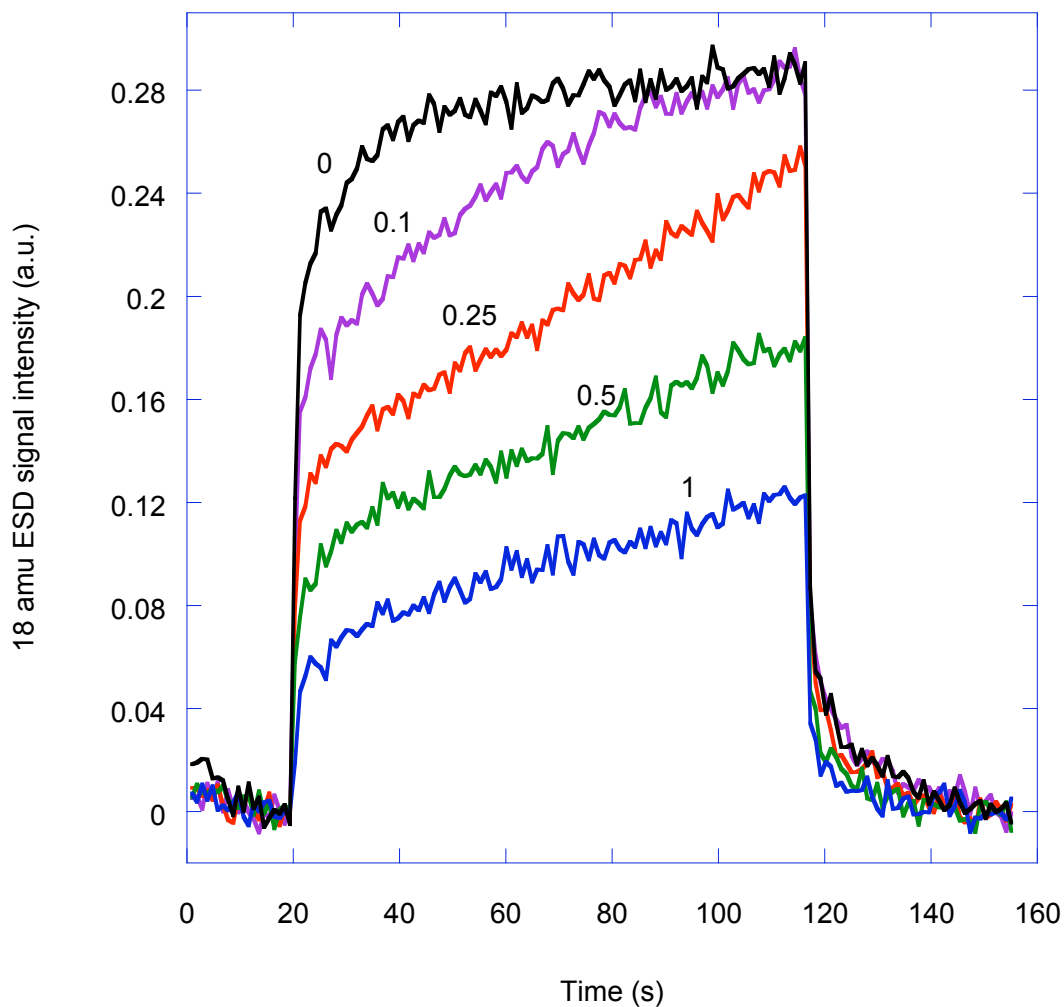
**Figure 4.9: O<sub>2</sub> production from capped pre-irradiated H<sub>2</sub><sup>18</sup>O films.** 80 ML H<sub>2</sub><sup>18</sup>O were dosed and irradiated at 80 K for 97 s. The preirradiated film was then capped with n ML CH<sub>3</sub>OH and irradiated a second time at 80 K, beginning at 20 s above. In the graph above, the labels indicate the value of n. In the absence of CH<sub>3</sub>OH, the <sup>18</sup>O<sub>2</sub> signal returns promptly to its steady state value, as illustrated by the red trace labeled “0.” The addition of CH<sub>3</sub>OH suppresses the prompt production of O<sub>2</sub>, and slows the recovery of O<sub>2</sub> production.



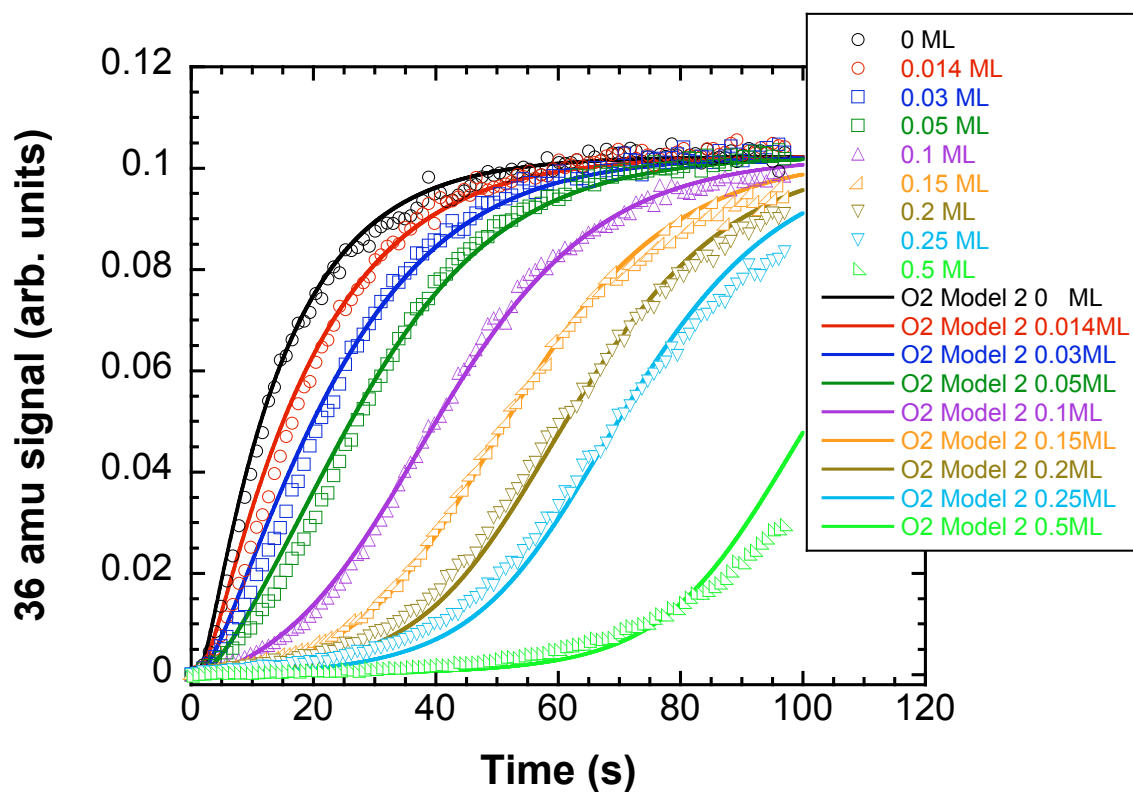
**Figure 4.10:  $\text{O}_2$  production dependence on surface MeOH concentration.** 80 ML  $\text{H}_2^{18}\text{O}$  were irradiated at 80 K to saturate the precursor population. Then,  $n$  ML  $\text{CH}_3\text{OH}$  were dosed on the processed film at 80 K and irradiated a second time for 97 s. The  $^{18}\text{O}_2$  (36 amu) and the  $\text{CH}_3\text{OH}$  (31 amu) signals were measured in a series of ESDs. The dependency of the  $^{18}\text{O}_2$  signal on the  $\text{CH}_3\text{OH}$  signal (which reflects the amount of  $\text{CH}_3\text{OH}$  remaining at the vacuum interface) is plotted above. Early in the cycle, when large quantities of methanol remain at the surface, the precursors formed in the first irradiation scan are scavenged, leading to a rapid decrease in prompt  $\text{O}_2$  production. As methanol is removed from the film surface by mixing, reacting, and sputtering,  $\text{O}_2$  production recovers. There is a strong correlation between the amount of  $\text{CH}_3\text{OH}$  remaining on the film, and the onset of  $\text{O}_2$  recovery, with the recovery signals converging as the methanol signal falls below 0.003 units. Fitting the convergent recovery signals shows that less than 0.007 ML  $\text{CH}_3\text{OH}$  remains on the surface when recovery begins.



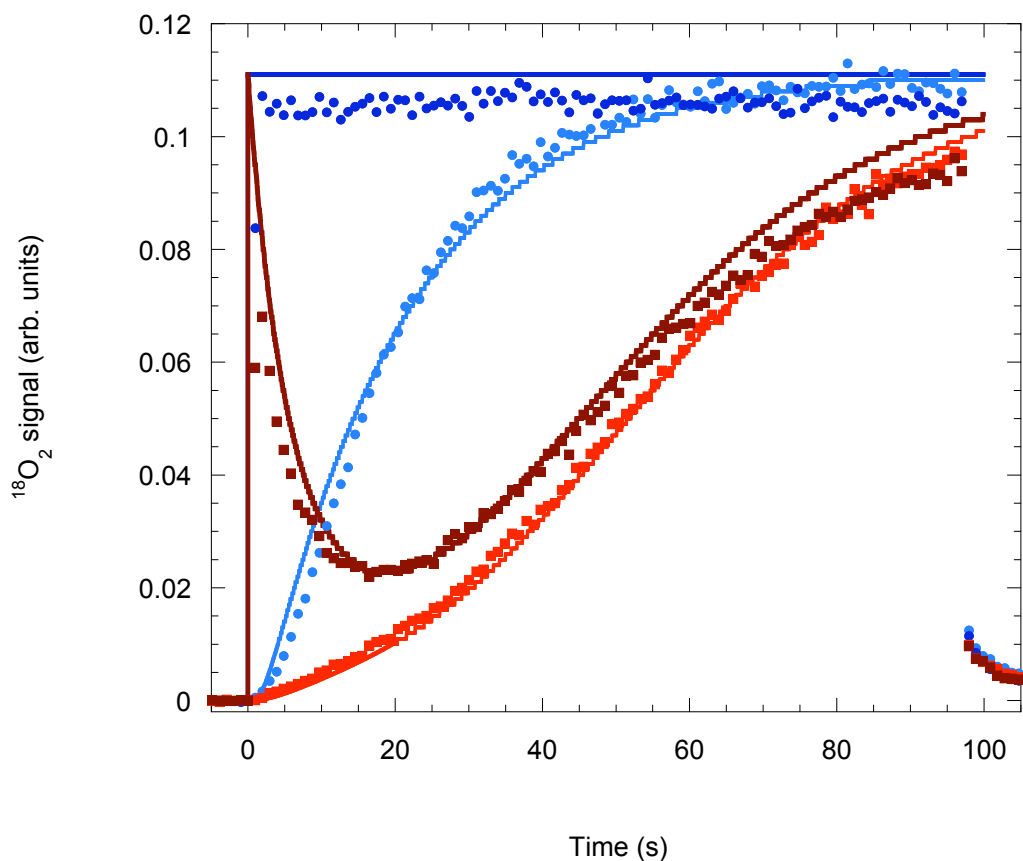
**Figure 4.11: Effect of a  $\text{H}_2^{16}\text{O}$  spacer layer on  $\text{O}_2$  suppression by methanol.** 80 ML  $\text{H}_2^{18}\text{O}$  were irradiated for 97 s at 80 K to saturate the precursor population. This preprocessed film was then capped at 50 K by A)  $n$  ML unprocessed  $\text{H}_2^{16}\text{O}$ , B)  $n$  ML unprocessed  $\text{H}_2^{16}\text{O}$ , followed by 0.5 ML  $\text{CH}_3\text{OH}$ , or C) 0.5 ML  $\text{CH}_3\text{OH}$  followed by  $n$  ML unprocessed  $\text{H}_2^{16}\text{O}$ . The films were then irradiated at second time at 50 K, beginning at 20 s and continuing until 117 s, monitoring the  $^{18}\text{O}_2$  signal from the pre-processed layer. Both irradiation cycles used 100 eV electrons at a current of  $\sim 2\mu\text{A}$ . The addition of  $\text{CH}_3\text{OH}$  reduced the  $^{18}\text{O}_2$  signal, regardless of whether it was in direct contact with the precursor-rich  $\text{H}_2^{18}\text{O}$  layer. The placement of an  $\text{H}_2^{16}\text{O}$  spacer layer between the methanol and the preprocessed film made no difference in the prompt portion of the ESD signal, which reflects  $\text{O}_2$  forming from pre-existing precursors, and only very little difference in the recovery of the  $^{18}\text{O}_2$  signal. This result suggests that the suppression effect caused by  $\text{CH}_3\text{OH}$  is due to some long-range process.



**Figure 4.12: Suppression of water by CH<sub>3</sub>OH.** *n* ML CH<sub>3</sub>OH were deposited atop an 80 ML H<sub>2</sub>O film at 80 K. The film was irradiated beginning at 20 s and continuing until 117 s using 100 eV electrons at ~2μA current at 80 K. The H<sub>2</sub>O signal was measured during ESD to determine how the addition of CH<sub>3</sub>OH suppresses water desorption. Increasing quantities of methanol decrease the amount of water observed during ESD.



**Figure 4.13: Model 2 predictions compared to data from Figure 4.1.** The addition of reactions modeling scavenging of OH by  $\text{CH}_3\text{OH}$  and destruction of  $\text{CH}_3\text{OH}$  by electrons yields a good fit to the data.



**Figure 4.14: A comparison of Model 3 with the data.** The  $^{18}\text{O}_2$  signals from unprocessed and pre-irradiated films of pure  $\text{H}_2^{18}\text{O}$  (light blue and dark blue, respectively) and unprocessed and pre-irradiated films of  $\text{H}_2^{18}\text{O}$  capped with 0.1 ML  $\text{CH}_3\text{OH}$  (red and maroon, respectively) are compared with predictions by Model 3. Data, shown earlier in Figure 4.9, are represented by points; model predictions are represented by solid lines. The addition of the  $\text{HO}_2$  scavenging reaction 10 allows the model to accurately predict suppression of  $\text{O}_2$  production from both unprocessed and pre-processed films.

## Appendix

The kinetic model used in Chapter 4 was developed by Nikolay Petrik at Pacific Northwest National Laboratory. Using the ten reaction equations described in Chapter 4, a series of differential equations were determined and solved numerically. For more details on the technique used, please see “Electron-stimulated production of molecular oxygen in amorphous solid water.” by Petrik, Kavetsky, and Kimmel (*Journal of Physical Chemistry B*, 2006, volume 110, pp. 2723-2731).

$$\frac{d[OH]}{dt} = k_1 + 2k_3[H_2O_2] - k_2[OH]^2 - k_4[OH][H_2O_2] - k_6[OH][CH_3OH]$$

$$\frac{d[H_2O_2]}{dt} = k_2[OH]^2 - k_3[H_2O_2] - k_4[OH][H_2O_2]$$

$$\frac{d[HO_2]}{dt} = k_4[OH][H_2O_2] - k_5[HO_2] - k_8[HO_2][CH_3OH]$$

$$\frac{d[CH_3OH]}{dt} = -k_6[OH][CH_3OH] - k_7[CH_3OH] - k_8[HO_2][CH_3OH]$$

$$Y_{O_2}(t) = \alpha k_5[HO_2]$$

$$Y_{CH_3OH}(t) = \beta k_7[CH_3OH]$$



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